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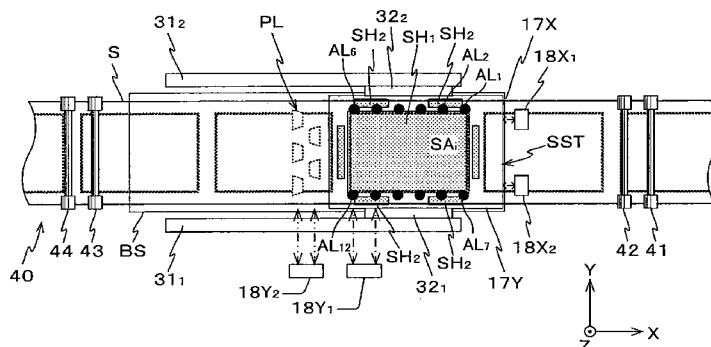
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FIG. 13



(57) Abstract: Six auxiliary sheet holders (SH₂) and (SH₃) temporarily holding a sheet (S) are minutely driven in the — Z-axis direction by a control device so that holding surfaces thereof are positioned on the slightly lower side (—Z side) of the holding surface of the sheet holder (SH₁). Accordingly, an appropriate tension is applied to the sheet (S) in the width direction (Y-axis direction) and the longitudinal direction, so that the center portion of the sheet (S) is fixed onto the holding surface of the sheet holder (SH₁). That is, in the state where an XY two-dimensional tension is applied to a separate area (SA_i) of the sheet (S) a rear surface portion corresponding to the separate area (SA_i) of the sheet (S) is changed in accordance with the flat shape of the holding surface of the sheet holder (SH₁). In addition, in the state where the tension is applied to the predetermined area in the longitudinal direction and the width direction, the rear surface portion corresponding to the predetermined area of the sheet material (S) is changed in accordance with the flat reference surface so as to be flattened. In addition, the predetermined area of the flattened sheet material is irradiated with an energy beam so as to form a pattern thereon.

DESCRIPTION

PATTERN FORMING DEVICE, PATTERN FORMING METHOD, AND DEVICE
MANUFACTURING METHOD

5

BACKGROUND

The present invention relates to a pattern forming device, a pattern forming method, and a device manufacturing device, and more particularly, to a pattern forming device and a pattern forming method of forming a pattern in a plurality of areas of a surface of an elongated sheet material through a scanning exposure, and to a device manufacturing method of manufacturing an electronic device by using the pattern forming method.

Priority is claimed on U.S. Provisional Application No. 61/226,330, filed July 17, 2009, U.S. Provisional Application No. 61/226,458, filed July 17, 2009, and U.S. Patent Application No. 12/822,773, filed June, 24, 2010, the contents of which are incorporated herein by reference.

The size of a flat display panel such as a liquid crystal display panel and a plasma display panel has been increased. For example, in the case of the liquid crystal display panel, as a glass substrate (large substrate) used for the manufacture thereof, a large substrate of which the length of a side is more than 3 m is used in order to efficiently manufacture a plurality of displays as a whole. For this reason, a stage device for holding the substrate increases in size in accordance with an increase in size of the substrate. In the stage device for treating a substrate weighing several tens of kg, the weight of a movable portion is almost equal to 10 tons, and the entire weight of the device exceeds 100 tons. For this reason, in the near future, the manufacture and the

delivery of the substrate can be difficult due to a further increase in size of the substrate.

In addition, it is certain that a large amount of investment is necessary for the infrastructure improvement due to a further increase in size of the stage device.

Meanwhile, there is known an exposure device which is mainly used in the field
5 of manufacturing a printed interconnection substrate, and a roll-sheet-like recording medium is set as an exposure target object. When such an exposure device is applied to manufacture, for example, a liquid crystal display element, various problems caused by an increase in size of the above-described glass substrate can be solved. For this reason, this exposure device can be used as one of the exposure devices for manufacturing the
10 liquid crystal display element in the future.

As the existing exposure devices for a sheet-like recording medium, for example, there are known exposure devices disclosed in Patent Documents (US Patent No. 5652645, US Patent Application Publication No. 2006/0066715, US Patent No. 6243160). However, even when such exposure devices are directly used to manufacture the liquid
15 crystal display element, it is difficult to manufacture the liquid crystal display element with desired precision. For example, in the liquid crystal display element, patterns are overlapped in a plurality of layers through an exposure. However, since each of the layers is subjected to a process, a phenomenon arises in that the sheet is contracted by heat or the like. Accordingly, such a phenomenon needs to be handled.

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SUMMARY

According to a first aspect of the present invention, there is provided a pattern forming device for forming a predetermined pattern in a predetermined area of an elongated sheet material, the pattern forming device including: a tension applying device
25 which applies a two-dimensional tension to a portion including the predetermined area of

the sheet material; an adsorption device which includes a reference surface member having a flat reference surface and allows the reference surface to adsorb a rear surface portion corresponding to the predetermined area of the sheet material applied with the two-dimensional tension; and an illumination device which illuminates an energy beam
5 corresponding to the pattern to the predetermined area of the sheet material adsorbed to the reference surface.

Accordingly, the two-dimensional tension is applied to the portion including the predetermined area of the sheet material by the tension applying device, and the rear surface portion corresponding to the predetermined area of the sheet material applied
10 with the two-dimensional tension is adsorbed to the flat reference surface by the adsorption device. In addition, the energy beam corresponding to the pattern is illuminated to the predetermined area of the flat sheet material adsorbed to the reference surface by the illumination device, so that the sheet material is exposed and the pattern is formed thereon. Accordingly, even in the case of the sheet material becoming
15 contracted by, for example, heat generated during a treatment of a process, it is possible to perform the exposure with high precision.

According to a second aspect of the present invention, there is provided a pattern forming method of forming a predetermined pattern in a predetermined area of an elongated sheet material, the pattern forming method including: applying a
20 two-dimensional tension to a portion including the predetermined area of the sheet material; allowing a flat reference surface to adsorb a rear surface portion corresponding to the predetermined area of the sheet material applied with the two-dimensional tension; and illuminating an energy beam corresponding to the pattern to the predetermined area of the sheet material adsorbed to the reference surface.

25 Accordingly, even in the case of the sheet material contracted by, for example,

heat generated during a treatment of a process, it is possible to perform the exposure with high precision.

According to a third aspect of the present invention, there is provided a device manufacturing method including: forming a pattern on an elongated sheet material by
5 using the pattern forming device according to the present invention; and performing a process on the sheet material having the pattern formed thereon.

According to a fourth aspect of the present invention, there is provided a pattern forming method of forming a predetermined pattern in a predetermined area of a surface of an elongated sheet material, the pattern forming method including: restraining at least
10 two positions of the sheet material in the longitudinal direction so as to apply a first tension to the predetermined area in the longitudinal direction; restraining both sides of the sheet material in the width direction intersecting the longitudinal direction of the sheet material so as to apply a second tension to the predetermined area in the width direction; allowing a rear surface portion corresponding to the predetermined area of the
15 sheet material to change in accordance with a flat reference surface in the state where the first and second tensions are applied to the predetermined area; and illuminating an energy beam corresponding to the pattern to the predetermined area of the flattened sheet material.

Accordingly, even in the case of the sheet material becoming contracted by, for
20 example, heat generated during a treatment of a process, it is possible to perform the exposure with high precision.

According to a fifth aspect of the present invention, there is provided a device manufacturing method including: forming a pattern on an elongated sheet material by
using the pattern forming method according to the present invention; and performing a
25 process on the sheet material having the pattern formed thereon.

According to a sixth aspect of the present invention, there is provided a pattern forming device for forming a predetermined pattern in a predetermined area of a surface of an elongated sheet material, the pattern forming device including: a first tension applying device which restrains at least two positions of the sheet material in the longitudinal direction so as to apply a first tension to the predetermined area in the longitudinal direction; a second tension applying device which restrains both sides of the sheet material in the width direction intersecting the longitudinal direction of the sheet material so as to apply a second tension to the predetermined area in the width direction; a flattening device which includes a reference surface member having a flat reference surface, and allows a rear surface portion corresponding to the predetermined area of the sheet material to change in accordance with the reference surface in the state where the first and second tensions are applied to the predetermined area; and an illumination device which illuminates an energy beam corresponding to the pattern to the predetermined area of the flattened sheet material.

Accordingly, the first tension applying device restrains at least two positions of the sheet material in the longitudinal direction so as to apply the first tension to the predetermined area in the longitudinal direction, and the second tension applying device restrains both sides of the sheet material in the width direction so as to apply the second tension to the predetermined area in the width direction. Then, in the state where the first and second tensions are applied to the predetermined area of the sheet material, the flattening device allows the rear surface portion corresponding to the predetermined area of the sheet material to change in accordance with the flat reference surface of the reference surface member. Then, the illumination device illuminates the energy beam corresponding to the predetermined pattern to the predetermined area of the flattened sheet material, so that the sheet material is exposed and a pattern is formed thereon.

Accordingly, even in the case of the sheet material becoming contracted by, for example, heat generated during a treatment of a process, it is possible to perform the exposure with high precision.

According to a seventh aspect of the present invention, there is provided a device
5 manufacturing method including: forming a pattern on an elongated sheet material by using the pattern forming device according to the present invention; and performing a process on the sheet material having the pattern formed thereon.

BRIEF DESCRIPTION OF THE DRAWINGS

10 FIG. 1 is a diagram showing a schematic configuration of an exposure device according to a first embodiment.

FIG. 2 is a plan view showing an arrangement of an illumination area and a schematic configuration of a mask stage provided in the exposure device of FIG. 1.

FIG. 3 is a plan view showing an arrangement of a projection area (exposure area)
15 on a sheet and a projection optical system provided in the exposure device of FIG. 1.

FIG. 4A is a side view showing a schematic configuration of the stage, and FIG. 4B is a plan view showing a schematic configuration thereof.

FIG. 5A is a sectional view of a table in the vicinity of a holder driving device and an auxiliary sheet holder, and FIG. 5B is a sectional view taken along the line B-B of FIG.
20 5A.

FIG. 6 is a plan view showing a stage device and a sheet transporting system provided in the exposure device of FIG. 1.

FIG. 7A is a plan view showing the vicinity of transportation roller portions 41 and 42, FIG. 7B is a side view showing the transportation roller portion 41, and FIGS. 7C
25 to 7G are diagrams illustrating a function of the sheet transporting system.

FIG. 8 is a diagram showing an example of an arrangement of alignment marks (positioning marks) attached to each separate area on the sheet S.

FIG. 9 is a block diagram showing an input/output relationship of a main control device provided in the exposure device of FIG. 1.

5 FIG. 10 is a (first) diagram illustrating a sequence of an exposure operation for the sheet in the exposure device of FIG. 1.

FIG. 11 is a diagram illustrating a temporary holding state of the sheet using an auxiliary sheet holder.

10 FIG. 12 is a (second) diagram illustrating a sequence of the exposure operation for the sheet in the exposure device of FIG. 1.

FIG. 13 is a (third) diagram illustrating a sequence of the exposure operation for the sheet in the exposure device of FIG. 1.

FIG. 14 is a diagram illustrating a positional alignment of the sheet using the auxiliary sheet holder.

15 FIG. 15 is a (fourth) diagram illustrating a sequence of the exposure operation for the sheet in the exposure device of FIG. 1.

FIG. 16 is a (fifth) diagram illustrating a sequence of the exposure operation for the sheet in the exposure device of FIG. 1.

20 FIG. 17 is a (sixth) diagram illustrating a sequence of the exposure operation in the exposure device of FIG. 1.

FIG. 18 is a (seventh) diagram illustrating a sequence of the exposure operation in the exposure device of FIG. 1.

FIG. 19 is an (eighth) diagram illustrating a sequence of the exposure operation in the exposure device of FIG. 1.

25 FIG. 20 is a diagram showing an arrangement of an alignment system according

to the modified example of the first embodiment.

FIG. 21 is a diagram showing a schematic configuration of an exposure device according to a second embodiment.

FIG. 22 is a plan view showing an arrangement of an illumination area and a
5 schematic configuration of a mask stage provided in the exposure device of FIG. 21.

FIG. 23 is a plan view showing an arrangement of a projection area (exposure area) on a sheet and a projection optical system provided in the exposure device of FIG. 21.

FIG. 24A is a side view showing a schematic configuration of the stage, and FIG.
10 24B is a plan view showing a schematic configuration thereof.

FIG. 25A is a sectional view of a table in the vicinity of a holder driving device and an auxiliary sheet holder, and FIG. 25B is a sectional view taken along the line B-B of FIG. 25A.

FIG. 26 is a plan view showing a stage device and a sheet transporting system
15 provided in the exposure device of FIG. 21.

FIG. 27A is a plan view showing the vicinity of transportation roller portions 41 and 42, FIG. 27B is a side view showing the transportation roller portion 41, and FIGS. 27C to 27G are diagrams illustrating a function of the sheet transporting system.

FIG. 28 is a diagram showing an example of an arrangement of alignment marks
20 (positioning marks) attached to each separate area on the sheet S.

FIG. 29 is a block diagram showing an input/output relationship of a main control device provided in the exposure device of FIG. 21.

FIG. 30 is a (first) diagram illustrating a sequence of an exposure operation for the sheet in the exposure device of FIG. 21.

25 FIG. 31 is a diagram illustrating a temporary holding state of the sheet using an

auxiliary sheet holder.

FIG. 32 is a (second) diagram illustrating a sequence of the exposure operation for the sheet in the exposure device of FIG. 21.

FIG. 33 is a (third) diagram illustrating a sequence of the exposure operation for
5 the sheet in the exposure device of FIG. 21.

FIG. 34 is a diagram illustrating a positional alignment of the sheet using the auxiliary sheet holder.

FIG. 35 is a (fourth) diagram illustrating a sequence of the exposure operation for the sheet in the exposure device of FIG. 21.

10 FIG. 36 is a (fifth) diagram illustrating a sequence of the exposure operation for the sheet in the exposure device of FIG. 21.

FIG. 37 is a (sixth) diagram illustrating a sequence of the exposure operation in the exposure device of FIG. 21.

FIG. 38 is a (seventh) diagram illustrating a sequence of the exposure operation in
15 the exposure device of FIG. 21.

FIG. 39 is an (eighth) diagram illustrating a sequence of the exposure operation in the exposure device of FIG. 21.

FIG. 40 is a diagram showing an arrangement of an alignment system relating to a modified example of the second embodiment.

20

DESCRIPTION OF THE REFERENCE SYMBOLS

40: SHEET TRANSPORTING SYSTEM

41, 42, 43, 44: TRANSPORTATION ROLLER PORTION

41₁, 42₁, 43₁, 44₁: PRESSURE ROLLER

25 41₂, 42₂, 43₂, 44₂: DRIVING ROLLER

- 45: CLAMPER PORTION
- 45₁, 45₂: CLAMPER MEMBER
- 50: MAIN CONTROL DEVICE
- 60: HOLDER DRIVING DEVICE
- 5 60₁: BASE
- 61: PARALLEL LINK MECHANISM
- 63: DRIVING MECHANISM
- 100: EXPOSURE DEVICE
- S: SHEET
- 10 SA_i: SEPARATE AREA
- SH₂: AUXILIARY SHEET HOLDER
- SH₃: AUXILIARY SHEET HOLDER
- SH₁: SHEET HOLDER
- TB: TABLE
- 15 IOP (IOP₁ TO IOP₅): ILLUMINATION SYSTEM
- PL (PL₁ TO PL₅): PROJECTION OPTICAL SYSTEM
- IL₁ TO IL₅: ILLUMINATION LIGHT
- AL₁ TO AL₁₂: ALIGNMENT SYSTEM
- AM: ALIGNMENT MARK
- 20 LC: LENS CONTROLLER

DESCRIPTION OF EMBODIMENTS

<First Embodiment>

Hereinafter, first embodiment of the present invention will be described with
25 reference to FIGS. 1 to 19.

FIG. 1 shows a schematic configuration of an exposure device 100 according to a first embodiment. The exposure device 100 is a multi-lens type projection exposure device, that is, a so-called scanner in which a flexible sheet or film (hereinafter, totally referred to as a sheet) is an exposure target object. In the embodiment, as an example, a
5 sheet having a thickness of about 100 μm is used.

The exposure device 100 includes an illumination system IOP, a mask stage MST which holds a mask M, a projection optical system PL which projects an image of a pattern formed on the mask M onto a sheet S, a stage device SS which includes a sheet stage (hereinafter, simply referred to as a stage) SST for holding the sheet S, a sheet
10 transporting system 40 which transports the sheet S, a control system thereof, and the like.

In addition, the sheet S used in the exposure device 100 of the embodiment is a continuously elongated sheet. The sheet S is wound in a roll shape, and is set in a roller 40₁. As described below, the sheet S is extracted from the roller 40₁ by (transportation
15 roller portions 41 to 44 constituting) the sheet transporting system 40, passes through an area directly below of the projection optical system PL, and is wound on a winding roller 40₂. In addition, a photosensitizing agent (resist) is coated on the surface of the sheet S. In the embodiment, as an example, the sheet S is extracted from the roller 40₁ and is wound on the winding roller 40₂, but the present invention is not limited thereto. A
20 sheet extracted from a resist coating device for performing a treatment before an exposure, for example, a resist coating treatment and transported to a developing device for performing a treatment after an exposure, for example, a developing treatment can be subjected to an exposure by the exposure device 100.

Hereinafter, a vertical direction (the up/down direction of FIG. 1) parallel to the
25 light axis (here, the middle portion between both portions is excluded) of the object

surface side and the upper surface side of the projection optical system PL is set to the Z-axis direction, a scanning direction (the left/right direction of FIG. 1) in which the mask M and the sheet S are relatively scanned by the projection optical system PL within a plane perpendicular to the Z-axis direction is set to the X-axis direction, and a direction perpendicular to the Z-axis direction and the X-axis direction is set to the Y-axis direction. Then, the rotation (inclination) directions of the X, Y, and Z-axis directions are respectively described as θ_x , θ_y , and θ_z directions.

The illumination system IOP includes a plurality of (herein, five) illumination system modules (hereinafter, simply referred to as illumination systems) IOP₁ to IOP₅. Each of the illumination systems IOP₁ to IOP₅ includes an ultra high pressure mercury lamp (light source) which emits UV light, an oval mirror which collects the UV light from the light source, a wavelength selection filter which is disposed on the light path of the collected UV light, an optical integrator, and an illumination optical system (are not shown) which includes a visual field diaphragm. The emission line, for example, a line i (having a wavelength of 365 nm), a line g (having a wavelength of 436 nm), or a line h (having a wavelength of 405 nm) from the UV light is extracted as illumination light IL₁ to IL₅ through the wavelength selection filter. Each of the extracted illumination light IL₁ to IL₅ is emitted (toward the mask M) on the outside of the illumination system IOP (IOP₁ to IOP₅) along each of the light axes AX₁ to AX₅ (refer to FIG. 2).

In addition, as shown in FIG. 2, the light axes AX₁, AX₃, and AX₅ are arranged at a predetermined interval in the Y-axis direction within the XY plane (the pattern surface of the mask M). Further, the light axes AX₂ and AX₄ are respectively disposed between the light axes AX₁ and AX₃ and between the light axes AX₃ and AX₅ with a predetermined distance therebetween from the light axes AX₁, AX₃, and AX₅ to the +X side. That is, the light axes AX₁ to AX₅ are arranged in a zigzag shape within the XY

plane.

The illumination systems IOP_1 to IOP_5 illuminate illumination light IL_1 to IL_5 to illumination areas IAM_1 to IAM_5 on the mask M along the light axes AX_1 to AX_5 with uniform intensity of illumination. Each of the illumination areas has an isosceles trapezoid shape stipulated by the visual field diaphragm (not shown) within the illumination optical system. In addition, the detailed configuration of the illumination system IOP (IOP_1 to IOP_5) is disclosed in, for example, the specification of US Patent No. 6,552,775.

As shown in FIG. 1, the mask stage MST is disposed at the low position ($-Z$ side) of the illumination system IOP . The rectangular mask M is fixed onto the mask stage MST by, for example, vacuum adsorption, where the mask indicates that a rectangular pattern area is formed in the pattern surface ($-Z$ side surface). The mask stage MST can be minutely driven within the XY plane by a mask stage driving system MSD (not shown in FIG. 1, refer to FIG. 9) including a linear motor and the like, and can be driven at a predetermined scanning speed of a predetermined stroke in the scanning direction (X -axis direction).

Positional information within the XY plane of the mask stage MST is constantly measured while having, for example, a resolution of about 0.25 to 1 nm by laser interferometers (hereinafter, simply referred to as interferometers) 16X and 16Y constituting a part of a mask stage interferometer system 16 (refer to FIG. 9). As shown in FIG. 2, the $+X$ side surface and the $-Y$ side surface of the mask stage MST are subjected to mirror-like finishing so as to have reflection surfaces 15X and 15Y. The interferometer 16X measures the rotation in the direction θ_z and the position (X position) in the X -axis direction of the mask stage MST by emitting a plurality of length measurement beams to the reflection surface 15X along the light path parallel to the X

axis and receiving the reflected beams from the reflection surfaces 15X. The substantial length measurement axis of the interferometer 16X is an axis parallel to the X axis perpendicular to the light axis AX_3 . The interferometer 16Y measures the position (Y position) in the Y-axis direction of the mask stage MST by emitting two length measurement beams to the reflection surface 15Y along the light path parallel to the Y axis perpendicular to the light axes AX_1 and AX_2 and receiving the reflected beams from the reflection surface 15Y. In addition, instead of the above-described reflection surfaces 15X and 15Y, a moving mirror formed by a plane mirror can be fixed to the mask stage MST.

The measurement information of the interferometers 16X and 16Y is supplied to a main control device 50 (refer to FIG. 9). The main control device 50 controls the mask stage MST through the mask stage driving system MSD on the basis of the measurement information (the positional information of the mask stage MST) of the interferometers 16X and 16Y.

As shown in FIG. 1, the projection optical system PL is disposed at the low position (-Z side) of the mask stage MST. For example, as shown in FIG. 3, the projection optical system PL according to the embodiment includes five projection optical system modules (hereinafter, simply referred to as projection optical systems) PL_1 to PL_5 which are disposed in a zigzag shape so as to correspond to arrangement of the light axes AX_1 to AX_5 . In FIG. 1, the projection optical systems PL_3 , PL_5 , and PL_4 are disposed backward the projection optical systems PL_1 and PL_2 in this paper plane. As each of the projection optical systems PL_1 to PL_5 , for example, a both-side telecentric reflection-refraction system is used which forms an erect image on an image surface at the same magnification.

By means of the arrangement of the above-described projection optical systems

PL₁ to PL₅ (the light axes AX₁ to AX₅), the projection areas IA₁ to IA₅ where the image of the pattern is projected by the projection optical systems PL₁ to PL₅ on the sheet S are arranged in a zigzag shape as in the illumination areas IAM₁ to IAM₅. Here, the projection areas IA₁ to IA₅ have an isosceles trapezoid shape as in the illumination areas IAM₁ to IAM₅. By means of the arrangement and the shape of the projection areas IA₁ to IA₅, the mask M and the sheet S are driven in a synchronized manner in the scanning direction (X-axis direction) while the image (the partial image) of the pattern within the illumination areas IAM₁ to IAM₅ on the mask M is projected onto the projection areas IA₁ to IA₅ on the sheet S through the projection optical systems PL₁ to PL₅, so that the partial images of the pattern projected onto the sheet S are synthesized as one image (synthesized image) which is the same as the pattern formed in the mask M.

Accordingly, by means of the scanning exposure, the pattern of the mask M is transferred onto (one short area (separate area) SA_i) the sheet S through the projection optical systems PL₁ to PL₅. In addition, the detail of the scanning exposure will be described later.

In the embodiment, since the optical system for projecting the erected image at the same magnification is adopted as the projection optical systems PL₁ to PL₅, the shape and the arrangement (positional relationship) of the projection areas IA₁ to IA₅ are the same as the shape and the arrangement (positional relationship) of the illumination areas IAM₁ to IAM₅. The detailed configuration of the projection optical system PL according to the embodiment is disclosed in, for example, US Patent No. 6,552,775 and the like.

The exposure device 100 includes a lens controller LC (refer to FIG. 9) which corrects a distortion (the positional deviation and/or the shape error) of the image projected onto the sheet S by the projection optical systems PL₁ to PL₅. The lens

controller LC drives at least a part of an optical element group (lens group) constituting each of the projection optical systems PL_1 to PL_5 in a direction parallel to the light axes AX_1 to AX_5 and a direction inclined relative to the XY plane perpendicular to the light axes AX_1 to AX_5 . Accordingly, the distortion (the shift, the rotation, the magnification (scaling), and the like) of the partial image of the pattern projected onto the projection areas IA_1 to IA_5 of the sheet S is corrected. In addition, the lens controller LC can change a pressure of a gas inside a hermetic room formed inside the projection optical systems PL_1 to PL_5 or change the wavelength of the illumination light instead of or in addition to driving the optical element group.

As shown in FIG. 1, the stage device SS is disposed at the low position (-Z side) of the projection optical system PL (PL_1 to PL_5). The stage device SS includes a base member BS which is supported on a bottom surface by an anti-vibration mechanism (not shown) so as to be substantially horizontal, a stage SST which moves and supports the sheet S on the base member BS, a driving system SSD (not shown in FIG. 1, refer to FIG. 9) which drives the stage SST, a stage interferometer system 18 (refer to FIG. 9) which measures positional information of the stage SST, and the like. In addition, in FIG. 1, the sheet S is adsorbed and held onto the stage SST.

As shown in FIG. 1, the stage SST includes a stage body ST which is supported on the base member BS in an uplifted state by a plurality of non-contact bearings (for example, air bearings (not shown)) provided in the bottom surface, a Z-leveling device 38 (refer to FIG. 4A) which is disposed on the stage body ST, and a table TB which is supported at three points by the Z-leveling device 38.

As shown in FIG. 4B, the Z-leveling device 38 includes three Z driving mechanisms 38a, 38b, and 38c which are disposed at three points not existing in one line on the stage body ST and including, for example, a voice coil motor and the like. By

means of the Z-leveling device 38, it is possible to minutely drive the table TB on the stage body ST in a direction of three degrees of freedom of the Z-axis direction, the θ_x direction, and the θ_y direction.

The stage SST (stage body ST) is scan-driven on the base member BS by the stage driving system SSD in the X-axis direction (scanning direction), and is also minutely driven in the Y-axis direction and the θ_z direction. The stage driving system SSD includes a minute movement device (not shown) which minutely drives the stage SST in the Y-axis direction, and a rough movement device 30 (refer to FIG. 9) which drives the minute movement device (not shown) in the scanning direction (X-axis direction).

As shown in FIGS. 4B and 6, the rough movement device 30 includes a pair of linear motors 30₁ and 30₂ respectively provided in one side and the other side of the Y-axis direction of the stage SST. The one linear motor 30₁ includes a fixed portion 31₁ which is disposed on the -Y side of the base member BS and extends in the X-axis direction, and a movable portion 32₁ which is attached to the fixed portion 31₁ so as to be movable along the longitudinal direction. The other linear motor 30₂ includes a fixed portion 31₂ which is disposed on the +Y side of the base member BS and extends in the X-axis direction, and a movable portion 32₂ which is attached to the fixed portion 31₂ so as to be movable along the longitudinal direction. Each of the fixed portions 31₁ and 31₂ includes a plurality of magnets (or coils) arranged along the X-axis direction, and each of the movable portions 32₁ and 32₂ includes coils (or magnets). The movable portions 32₁ and 32₂ are respectively fixed to the -Y side surface and the +Y side surface of the stage body ST through a minute movement device (not shown) which minutely moves them in the Y-axis direction. In addition, the stage body ST can be minutely driven in the θ_z direction by generating different thrust forces in the linear motors 30₁

and 30₂. In addition, a stage driving system can be configured which two-dimensionally moves the stage SST along the upper surface (guide surface) of the base member BS by using a planar motor of a Lorentz electromagnetic driving type, a planar motor of a variable electromagnetic resistance driving type, a planar motor of a magnetic suspension type, and the like disclosed in, for example, the specification of US Patent No. 5,196,745 instead of the rough movement device 30 and the minute movement device.

The table TB is driven on the base member BS by the stage driving system SSD (refer to FIG. 9) including the rough movement device 30, the minute movement device (not shown), and the Z-leveling device 38 so as to have six degrees of freedom in the X-axis direction, the Y-axis direction, the Z-axis direction, the θ_x direction, the θ_y direction, and the θ_z direction.

As shown in FIGS. 4A and 4B, a sheet holder SH₁ is provided at the center portion of the upper surface of the table TB so as to adsorb and hold the sheet S. The sheet holder SH₁ is substantially parallel to the XY plane, and includes a rectangular holding surface which is slightly larger than the separate area arranged on the sheet S, thereby flatly holding the sheet S on the holding surface. Here, in order to adsorb and hold the sheet S, as the sheet holder SH₁, a pin chuck holder is adopted in which the arrangement interval (pitch) of the pins is sufficiently small, and the height of the pin is low so as to be, for example, about 200 μm .

In addition, six auxiliary sheet holders SH₂ and SH₃ are provided on the upper surface of the table TB so as to adsorb and hold the rear surface in the periphery of the separate areas arranged on the sheet S. In detail, the $\pm Y$ sides of the sheet holder SH₁ are provided with two auxiliary sheet holders SH₂ which are thin and long in the X-axis direction and are distant from each other by a predetermined distance in the X-axis

direction. In addition, the $\pm X$ sides of the sheet holder SH_1 are provided with one auxiliary sheet holder SH_3 which is thin and long in the Y-axis direction. Each of the auxiliary sheet holders SH_2 and SH_3 includes a rectangular holding surface, and the holding surface can be minutely driven in a direction perpendicular to the longitudinal direction and the Z-axis direction by a holder driving device provided in the table TB.

FIG. 5A is a plan view showing a configuration of a holder driving device 60 provided inside the table TB, and FIG. 5B is a sectional view taken along the line B-B of FIG. 5A. Here, as an example, the holder driving device 60 is shown which drives the auxiliary sheet holder SH_2 located at the +Y-side end and the +X-side end of the table TB.

The holder driving device 60 includes a Y driving unit which includes a parallel link mechanism 61 as one type of a four-joint link mechanism provided inside a hollow portion provided in the table TB and a driving mechanism 63 driving (the driving joint of) the parallel link mechanism 61 and drives the auxiliary sheet holder SH_2 in the Y-axis direction, and a Z driving unit (not shown) which includes, for example, a driving element, a voice coil motor, and the like supporting a rectangular base 60_1 having the auxiliary sheet holder SH_2 fixed to the upper surface thereof on the bottom surface of the table TB and minutely driving that in the Z-axis direction. One end (-X end) of the base 60_1 is integrated with a link (hereinafter, conveniently referred to as a parallel movement link) which is located on the opposite side of the fixed link of the parallel link mechanism 61.

In detail, the parallel link mechanism 61 includes a pair of oscillation links 64_4 and 64_5 of which one end is respectively connected to a pair of link support members 66_3 and 66_4 fixed to the +X side wall of the hollow portion of the table TB and the other ends are respectively connected to one end 66_5 and the other end 66_6 of the above-described

parallel movement link. In this case, the link support members 66₃ and 66₄ are fixed to the table TB to thereby configure a fixed link. The fixed link, the oscillation links 64₄ and 64₅, and the parallel link are adjacent links and configure a revolute pair.

The driving mechanism 63 includes an actuator 62 of which one end is fixed to a part of the side wall of the hollow portion of the table TB, an L-shaped lever link 64₁ of which one end (driving point 68₀) comes into contact with the actuator 62 with pressure and a support point 68₂ of the middle portion is rotatably supported to a fixator 66₁ fixed to the bottom wall of the table TB, and a movable link 64₂ of which one end is connected to the other end (action point 68₃) of the lever link 64₁ and the other end is connected to an attachment member 66₇ fixed to a part of the above-described parallel movement link. The lever link 64₁ and the movable link 64₂ configure a revolute pair, and the movable link 64₂ and the attachment member 66₇ configure a revolute pair.

In addition, the attachment member 66₇ is connected to an attachment member 66₂ which is fixed to a part of the side wall of the -Y side wall of the hollow portion of the table TB through a spring member (pulling spring) 64₃. In this case, the attachment member 66₇ and the spring member (pulling spring) 64₃ form a revolute pair, and the spring member (pulling spring) 64₃ and the attachment member 66₂ form a revolute pair.

In the Y driving unit having the above-described configuration, one end (driving point 68₀) of the lever link 64₁ is constantly pressed and contacted by the actuator 62 by the spring member (pulling spring) 64₃. In addition, when the actuator 62 drives one end (driving point 68₀) of the lever link 64₁ in a direction (+X-axis direction) depicted by the white arrow of FIG. 5A while resisting the pressing and contacting force of the spring member 64₃, the attachment member 66₇ is driven in a direction (+Y-axis direction) depicted by the black arrow through the movable link 64₂. That is, the auxiliary sheet holder SH₂ is driven in the +Y-axis direction together with the base 60₁. In this case,

the movement amount of the auxiliary sheet holder SH_2 is determined by a force generated by the actuator 62. In addition, as described above, the auxiliary sheet holder SH_2 is driven in the Z-axis direction together with the base 60_1 by the Z driving unit disposed below the base 60_1 . However, in the below description, it will be described
5 that the auxiliary sheet holder SH_2 is driven in the Z-axis direction by the base 60_1 . That is, the base 60_1 is described as the Z driving unit.

The driving devices for the auxiliary sheet holder SH_2 provided in the +X-side end and the -Y-side end of the table TB have the similar configuration as the above-described holder driving device 60 being symmetric in the X axis. In addition,
10 the driving devices for the pair of auxiliary sheet holders SH_3 provided in $\pm X$ sides of the table TB have the similar configuration as the above-described holder driving device 60 with deferent direction (rotated by $\pm 90^\circ$).

A length between a force point 68_1 and a support point 68_2 of the lever link 64_1 and a length between a support point 68_2 and an operation point 68_3 are, for example, 1
15 to 3. For this reason, when one end of the lever link 64_1 is driven at the driving point 68_0 in the +X-axis direction by $10\ \mu\text{m}$ by the actuator 62 of the holder driving device 60 (driving mechanism 63), the bending portion (force point 68_1) of the lever link 64_1 is driven in the -Y-axis direction by $10\ \mu\text{m}$, and hence the other end (action point 68_3) of the lever link 64_1 is driven in the +Y-axis direction by $30\ \mu\text{m}$. Accordingly, it is
20 possible to drive the auxiliary sheet holder SH_2 in the +Y-axis direction by $30\ \mu\text{m}$ by using the holder driving device 60 (driving mechanism 63). In addition, in the state where both ends of the sheet S in the Y-axis direction are held by the pair of auxiliary sheet holders SH_2 disposed on the table TB while being distant from each other in the Y-axis direction, when the auxiliary sheet holders SH_2 are driven in a direction opposite

to each other (a direction moving away from each other), it is possible to stretch the sheet S by 60 μm at maximum. In the same way, it is possible to drive two auxiliary sheet holders SH₃ in the X-axis direction by 30 μm . Accordingly, in the state where the rear surface portion on the outside of both side separate areas in the X-axis direction of the separate areas of the sheet S are held by two auxiliary sheet holders SH₃, when the two auxiliary sheet holders SH₃ are driven in a direction opposite to each other (a direction moving away from each other), it is possible to stretch the sheet S in the X-axis direction by 60 μm at maximum.

The driving devices for the auxiliary sheet holders SH₂ provided in the +Y side, the -Y side, and the -X-side end of the table TB have the similar configuration as the above-described holder driving device 60 being symmetric in the Y axis.

As described below, the auxiliary sheet holders SH₂ and SH₃ are used to assist the sheet holder SH₁ when the sheet S is flatly held by the sheet holder SH₁. In addition, in the +Y end on the base 60₁, a rectangular-tray-shaped positioning member 60₂ is fixed to the auxiliary sheet holder SH₂ while coming into contact therewith. The positioning member 60₂ has a role of positioning the sheet S in the Y-axis direction by pressing the +Y end (or -Y end) of the sheet S when the sheet S is adsorbed and held by the holding surface of the auxiliary sheet holder SH₂.

As shown in FIG. 4B, the +X side surface and the -Y side surface of the table TB are subjected to mirror-like finishing so as to have reflection surfaces 17X and 17Y. The reflection surfaces 17X and 17Y are used to measure the position of the stage SST by using a stage interferometer system to be described later. In addition, instead of the above-described reflection surface 17Y, a moving mirror formed by a plane mirror can be fixed to the table TB. Further, instead of the reflection surface 17X, a moving mirror formed by a retro-reflector or a plane mirror can be fixed to the table TB.

As shown in FIG. 6, the stage interferometer system 18 (refer to FIG. 9) includes interferometers 18X₁, 18X₂, 18Y₁, and 18Y₂, and measures constantly the positional information (including the rotation information in the θ_z direction) within the XY plane of the stage SST (table TB) while having, for example, a resolution of about 0.25 to 1
5 nm.

The interferometers 18X₁, 18X₂, and 18Y₁, 18Y₂ are disposed on the +X side and the -Y side of the projection optical system PL so as to face the reflection surfaces 17X and 17Y of the table TB.

The interferometers 18X₁ and 18X₂ measure the X position of the stage SST by
10 emitting a length measurement beam parallel to the X axis to the reflection surface 17X of the table TB and receiving the reflected beam from the reflection surface 17X. The interferometers 18Y₁ and 18Y₂ measure the Y position of the stage SST by emitting two length measurement beams parallel to the Y axis to the reflection surface 17Y and receiving the reflected beam from the reflection surface 17Y. Here, one of two length
15 measurement beams of the interferometer 18Y₂ is emitted to the reflection surface 17Y along the light path parallel to the Y axis perpendicular to the light axes AX₁, AX₃, and AX₅, and the other thereof is emitted to the reflection surface 17Y along the light path parallel to the Y axis perpendicular to the light axes AX₂ and AX₄. In addition, the two light measurement beams of the interferometer 18Y₁ are emitted to the reflection surface
20 17Y along two light paths parallel to the Y axis passing the detection center of each of alignment systems AL₁₁ and AL₁₂ to be described later.

The measurement information of the stage interferometer system 18 (interferometers 18X₁, 18X₂, 18Y₁, and 18Y₂) is supplied to the main control device 50 (refer to FIG. 9). In addition, when the stage SST is located on the base member BS, at
25 least one of the length measurement beams of the interferometers 18Y₁ and 18Y₂ is

emitted to the reflection surface 17Y of the stage SST regardless of the X position thereof.

Accordingly, the main control device 50 uses any one of the measurement information of the interferometers 18Y₁ and 18Y₂ in accordance with the X position of the stage SST.

In addition, the main control device 50 measures the rotation in the θ_z direction of the stage SST on the basis of the measurement information of the interferometers 18X₁ and 18X₂.

In addition, as the interferometers 18X₁, 18X₂, 18Y₁, and 18Y₂, a multi-axis interferometer which emits a plurality of length measurement beams distant from each other in the Z-axis direction can be used. In this case, the main control device 50 can obtain the inclination information (the pitching amount (the rotation amount θ_x in the θ_x direction) and the rolling amount (the rotation amount θ_y in the θ_y direction)) with respect to the XY plane in addition to the positional information (rotation information (including yawing amount (the rotation amount θ_z in the θ_z direction))) within the XY plane of the stage SST (table TB).

As shown in FIGS. 1 and 6, the sheet transporting system 40 includes four transportation roller portions 41 to 44 which are arranged in the X-axis direction across the projection optical system PL.

As shown in FIGS. 7A to 7G, each of the transportation roller portions 41, 42, 43, and 44 includes a pair of a pressure roller and a driving roller located at the upper and lower positions. In the driving rollers 41₂, 42₂, 43₂, and 44₂ located at the lower position, both ends thereof are rotatably supported by support members (not shown) so that the upper ends thereof are slightly located at the upper position (+Z side) of the upper surface (the holding surface of the sheet holder SH₁) of the stage SST (refer to FIG. 1). The driving rollers 41₂, 42₂, 43₂, and 44₂ are rotationally driven by a rotation motor (not shown). The pressure rollers 41₁, 42₁, 43₁, and 44₁ located at the upper position are

pressed and contacted by the corresponding driving rollers from the upper side (+Z side) by a spring mechanism (not shown).

However, as shown in the transportation roller portion 41 of FIG. 7B, the pressure roller 41₁ is a stepped cylindrical roller of which a diameter of a portion except for both ends in the longitudinal direction is smaller than those of both ends, and the driving roller 41₂ is a cylindrical roller which has uniform diameter.

As shown in FIG. 7B by adopting the representative transportation roller portion 41 from the transportation roller portions 41, 42, 43, and 44, the sheet S is sandwiched between the pressure roller (41₁) and the driving roller (41₂), and the pressure roller (41₁) does not come into contact with the separate area where the pattern is formed on the surface of the sheet S. In each of the transportation roller portions 41, 42, 43, and 44, it is possible to set a first state where the sheet S can be sandwiched between the pressure roller (41₁) and the driving roller (41₂) and a second state where the operation of sandwiching the sheet S can be released by separating the pressure roller (41₁) from the driving roller (41₂) while resisting the pressing force of the spring mechanism. In each of the transportation roller portions 41, 42, 43, and 44, the change between the first state and the second is performed by the main control device 50. In addition, at least a part of the driving rollers can be formed as a stepped cylindrical shape as in the pressure roller 41₁.

The rotation and the stopping of the driving rollers 41₂, 42₂, 43₂, and 44₂ are controlled by the main control device 50 together with the rollers 40₁ and 40₂. As shown in FIG. 7B by adopting the representative transportation roller portion 41, when the driving roller (41₂) is rotated about the axis parallel to the Y axis (and the pressure roller 41₁ is rotated in the reverse direction) in the first state of the transportation roller portion, the sheet S is transported in the rotation direction.

In the sheet transporting system 40, as shown in FIG. 7C, the rollers 41₁ and 41₂ of the transportation roller portion 41 are rotated in a direction depicted by the arrow, so that the sheet S is drawn out in the -X-axis direction depicted by the white arrow from the roller 40₁ and is transported toward the transportation roller portion 42. Here, when
5 the rotation of the rollers 42₁ and 42₂ of the transportation roller portion 42 is stopped at a predetermined timing, the sheet S having a predetermined length (a degree corresponding to a distance between the transportation roller portions 42 and 43) is bent in a loop shape between the transportation roller portions 41 and 42. In addition, in the sheet transporting system 40, as shown in FIG. 7D, the rollers 42₁ and 42₂ of the
10 transportation roller portion 42 (and the rollers 43₁ and 43₂ of the transportation roller portion 43) are rotated in a direction depicted by the arrow in the state where the rotation of each of the rollers 41₁ and 41₂ of the transportation roller portion 41 is stopped, so that the sheet S bent in a loop shape is transported in the -X-axis direction depicted by the white arrow toward an area directly below the projection optical system PL.

15 In the sheet transporting system 40, as described above, the sheet S is drawn out from the area directly below the projection optical system PL by means of the rotation and the stopping of each of the rollers of the transportation roller portions 43 and 44. That is, as shown in FIG. 7E, when each of the rollers 43₁ and 43₂ of the transportation roller 43 is rotated in a direction depicted by the arrow in the state where the rotation of
20 each of the rollers 44₁ and 44₂ of the transportation roller portion 44 is stopped, the sheet S is drawn out to the area directly below the projection optical system PL, and the drawn sheet S is bent in a loop shape between the transportation roller portions 43 and 44. Then, as shown in FIG. 7F, when each of the rollers 44₁ and 44₂ of the transportation roller portion 44 is just rotated in a direction depicted by the arrow in the state where the
25 rotation of each of the rollers 43₁ and 43₂ of the transportation roller portion 43 is

stopped, the sheet S bent in a loop shape is transported to the $-X$ side of the transportation roller portion 44, and is wound on the winding roller 40₂.

In addition, in the sheet transporting system 40, as shown in FIG. 7G, each of the rollers of the transportation roller portion 43 is rotated in a direction in which the sheet S is transported in the state where the rotation of each of the rollers of the transportation roller portions 41 and 42 is stopped or each of the rollers of the transportation roller portion 42 is reversely rotated in the state where the rotation of each of the rollers of the transportation roller portions 43 and 44 is stopped, so that a predetermined tension is applied to the sheet S in the X-axis direction and the sheet S is stretched between the transportation roller portions 42 and 43. The sheet S stretched in this manner is adsorbed and held by the sheet holder SH₁ on the sheet stage SST.

The sheet transporting system 40 further includes a measurement device (not shown) which measures the transportation amount of the sheet S, for example, a rotary encoder and the like which measure the rotation amount of each of the driving rollers 41₂, 42₂, 43₂, and 44₂.

In addition, the operation of transporting the sheet S, the operation of holding the sheet S on the stage SST, and the like using the sheet transporting system 40 during the exposure process will be described later in detail.

Further, in the exposure device 100 of the embodiment, a plurality of (herein, twelve) off-axis type alignment systems AL₁ to AL₁₂ is provided so as to detect the alignment marks attached to the separate areas on the sheet S. As shown in FIG. 6, the alignment systems AL₁ to AL₆ are provided at the position of the $+X$ side of the projection optical system PL along the X axis so as to face the area of the $+Y$ -side end on the outside of the separate area on the sheet S. In addition, as shown in FIG. 6, the alignment systems AL₇ to AL₁₂ are disposed so as to be symmetric to the alignment

systems AL_1 to AL_6 with respect to the X axis perpendicular to the light axis of the projection area IA_3 . The alignment systems AL_7 to AL_{12} can be disposed so as to face the area of the -Y-side end on the outside of each separate area on the sheet S.

In the embodiment, as an example, as shown in FIG. 8, six alignment marks AM
5 (twelve in total) are provided in each area on the outside of the Y-axis direction of each separate area SA_i on the sheet S, and the alignment systems AL_1 to AL_{12} are provided so as to individually and simultaneously detect the twelve alignment marks AM.

Accordingly, the present invention is not limited thereto, and when the alignment systems are movable in the X-axis direction, at least one alignment system can be provided
10 instead of the alignment systems AL_1 to AL_6 , and at least one alignment system can be provided instead of the alignment systems AL_7 to AL_{12} .

As the alignment systems AL_1 to AL_{12} , an exemplary image process type FIA (Field Image Alignment) system is adopted. The detection result (the image information of the index mark and the detection target mark) of the alignment systems
15 AL_1 to AL_{12} are transmitted to the main control device 50 through an alignment signal process system (not shown). In addition, the present invention is not limited to the FIA. An alignment sensor, which emits coherent detection light to the target mark and detects the scattered light or the diffracted light generated from the target mark or detects two beams of diffracted light (for example, the same homogeneous number) generated from
20 the target mark through the interference, can be solely used or appropriately combined.

FIG. 9 is a block diagram showing an input/output relationship of the main control device 50 which generally controls the constituents of the control system of the exposure device 100.

Next, the sequence of the exposure operation for the sheet S using the stage SST
25 in the exposure device 100 of the embodiment will be described with reference to FIGS.

10 to 18. In addition, the operation is described with reference to a plurality of drawings, but the reference numerals can be given or not given to the same constituents for each of the drawings. That is, there is a difference in the mark of the reference numerals in each of the drawings, but the configuration is the same regardless of the mark of the reference numerals of the drawings. The same applies to the drawings which have been used for the description.

FIG. 10 shows a state where the exposure for the first (i-1) number of the separate areas SA_1 to SA_{i-1} among the plurality of separate areas arranged on the sheet S is completed, and the exposure for the subsequent separate area SA_i is about to be started.

10 In the state of FIG. 10, the stage SST used for the movement of the sheet S during the exposure for the separate area SA_i stays at the position (standby position) of the +X end on the base member BS.

In addition, since the load of the mask M to the mask stage MST and the mask alignment (the positioning operation of the mask) are generally performed before the start of the exposure for the first separate area SA_1 on the sheet S, in the state of FIG. 10, the load of the mask M and the mask alignment are of course completed. In addition, it is assumed that the mask stage MST is moved to the scanning start position (acceleration start position) for the exposure of the separate area SA_i .

a. First, the center portion of the sheet S including the separate area SA_i is held onto the stage SST in accordance with the following sequence of a1 to a4.

a1. In detail, for example, as described above with reference to FIG. 7C, the main control device 50 stops the rotation of each of the rollers of the transportation roller portion 42 of the sheet transporting system 40 and then rotates each of the rollers of the transportation roller portion 41 so as to draw out the sheet S from the roller 40₁.

25 Alternatively, the main control device 50 stops the rotation of each of the rollers of the

transportation roller portions 43 and 41 and then reversely rotates the transportation roller portion 42 so as to draw back the sheet S to the area directly below the projection optical system PL. Anyway, the sheet S having a predetermined length is bent in a loop shape between the transportation roller portions 41 and 42. The predetermined length is a
5 length corresponding to a distance between the transportation roller portions 42 and 43.

a2. Next, the main control device 50 controls the sheet transporting system 40 on the basis of the positional information of the stage SST from the stage interferometer 18 ($18X_1$, $18X_2$, $18Y_1$, and $18Y_2$) so as to position the separate area SA_i on the sheet S with respect to (the holding surface of) the sheet holder SH_1 of the stage SST. Here, as
10 described above with reference to FIG. 7G, the main control device 50 rotates each of the rollers of the transportation roller portion 43 in the state where the rotation of each of the rollers of the transportation roller portions 41, 42, and 44 is stopped or reversely rotates each of the rollers of the transportation roller portion 42 in the state where the rotation of each of the rollers of the transportation roller portions 41, 43, and 44 is stopped, so that
15 the sheet S is applied with a predetermined tension in the X-axis direction so as to be stretched between the transportation roller portions 42 and 43. The main control device 50 further minutely drives the stage SST so as to position (the holding surface of) the sheet holder SH_1 to the separate area SA_i on the sheet S. In addition, in this state, a minute space is formed between the sheet S and (the holding surface of) the sheet holder
20 SH_1 of the stage SST.

In the state where the sheet S is positioned with respect to the stage SST at the standby position, the alignment marks AM attached to the separate area SA_i are positioned within the detection visual field of each of the alignment systems AL_1 to AL_{12} .

a3. After the positioning operation, the main control device 50 minutely drives six
25 auxiliary sheet holders SH_2 and SH_3 on the table TB in the +Z-axis direction through the

holder driving device 60 (base 60₁) while horizontally holding the table TB of the stage SST through the stage driving system SSD (Z-leveling device 38), so that the rear surface of the sheet S of the portion corresponding to the $\pm Y$ sides of the separate area S_i is adsorbed and held by using four auxiliary sheet holders SH₂, and the rear surface of the sheet S of the portion corresponding to the $\pm X$ sides of the separate area S_i is adsorbed and held by using two auxiliary sheet holders SH₃.

In detail, as shown in FIG. 11, the main control device 50 minutely drives two auxiliary sheet holders SH₂ respectively disposed in the +Y-side end and the -Y-side end on the table TB in a direction (+Y-axis direction or -Y-axis direction) depicted by the white arrow so as to widen the distance between the auxiliary sheet holders SH₂ distant from each other in the Y-axis direction on the table TB. In addition, the main control device 50 drives each of the auxiliary sheet holders SH₂ in the +Z-axis direction through the base 60₁ so that the rear surfaces of both ends in the Y-axis direction of the sheet S come into contact with the holding surfaces of four auxiliary sheet holders SH₂. After the contact, the main control device 50 minutely drives two auxiliary sheet holders SH₂ on the +Y side in the -Y-axis direction depicted by the black arrow so as to firmly press the positioning member 60₂ against the +Y end of the sheet S, and minutely drives two auxiliary sheet holders SH₂ on the -Y side in the +Y-axis direction depicted by the black arrow so as to firmly press the positioning member 60₂ against the -Y end of the sheet S, thereby positioning the sheet S. After the positioning operation, the main control device 50 allows the rear surfaces of both sides in the Y-axis direction of the separate area SA_i of the sheet S to be adsorbed and held by four auxiliary sheet holders SH₂, and allows the rear surfaces of both sides in the X-axis direction of the separate area SA_i of the sheet S to be adsorbed and held by the auxiliary sheet holder SH₃.

FIG. 12 shows a state where the sheet S is temporarily held by the auxiliary sheet

holders SH₂ and SH₃ in this manner.

a4. After the temporary holding operation of the sheet S, the main control device 50 minutely drives each of the auxiliary sheet holders SH₂ and SH₃ in the -Z-axis direction through the base 60₁ in the state where the sheet S is temporarily held so as to allow the rear surface of the center portion of the sheet S including the separate area SA_i to come into contact with the holding surface of the sheet holder SH₁. Then, the main control device 50 positions the holding surface of each of the auxiliary sheet holders SH₂ and SH₃ so as to be located on the slightly lower side (-Z side) of the holding surface of the sheet holder SH₁. Accordingly, an appropriate tension is applied to the sheet S in the Y-axis direction and the X-axis direction, so that the center portion of the sheet S is fixed to the holding surface of the sheet holder SH₁. In this state, the main control device 50 adsorbs and holds the sheet S onto the sheet holder SH₁ as shown in FIG. 12. Accordingly, the center portion of the sheet S including the separate area SA_i is flatly held onto the stage SST so as to be parallel to the XY plane.

b. Next, the alignment measurement for the sheet S is performed in accordance with the following sequences b1 to b5.

b1. As described above, in the state where the stage SST is positioned to the standby position, the alignment marks attached to the separate area SA_i are positioned within the detection visual field of each of the alignment systems AL₁ to AL₁₂. Here, as shown in FIG. 13, the main control device 50 detects the alignment marks attached to the separate area SA_i on the sheet S by using the alignment systems AL₁ to AL₁₂ (the positions of the alignment marks are measured on the basis of the index center). In addition, the main control device 50 obtains the position coordinates of twelve alignment marks on the XY coordinate on the basis of the detection result of the alignment marks and the positional information of the stage SST obtained from the stage interferometer

system 18 through the detection.

b2. Next, the main control device 50 determines whether the contraction amount of the separate area SA_i having the pattern of the sheet S in the X-axis direction and the Y-axis direction is within a predetermined range on the basis of the position coordinates
5 of the twelve alignment marks obtained.

b3. Then, as a result, for example, when it is determined that a contraction exceeding a predetermined range occurs in at least a part inside the separate area SA_i , the operation of adsorbing and holding the sheet S using the sheet holder SH_1 is released, and each of the auxiliary sheet holders SH_2 and SH_3 is driven through the base 60_1 in the
10 +Z-axis direction so as to separate the rear surface of the sheet S from the holding surface of the sheet holder SH_1 .

Here, for example, when it is determined that the -X end of the inside of the separate area SA_i on the sheet S contracts more than a predetermined range in the Y-axis direction, and the separate area SA_i contracts more than a predetermined range in the
15 X-axis direction, as shown in FIG. 14, two auxiliary sheet holders SH_2 on the -X side on the table TB are driven in a direction (depicted by the white arrow of FIG. 14) moving away from each other so as to further apply a tension to the -X-side end of the separate area SA_i of the sheet S in the Y-axis direction, and two auxiliary sheet holders SH_3 are driven in a direction (depicted by the black arrow) moving away from each other so as to
20 further apply a tension to the separate area SA_i of the sheet S in the X-axis direction, thereby correcting (adjusting) the deformation.

After the adjustment, the main control device 50 drives each of the auxiliary sheet holders SH_2 and SH_3 through the base 60_1 in the -Z-axis direction so that the rear surface of the sheet S comes into contact with the holding surface of the sheet holder SH_1 to be
25 adsorbed and held thereon again.

b4. Then, the main control device 50 detects the alignment marks attached to the separate area SA_i on the sheet S by using the alignment systems AL_1 to AL_{12} , and obtains the position coordinates of twelve alignment marks on the XY coordinates again on the basis of the detection result and the positional information of the stage SST obtained from the interferometer system 18 through the detection.

b5. Then, the main control device 50 performs a predetermined calculation of least squares by using all or a part of the position coordinates of the twelve alignment marks, and obtains the distortion, that is, the XY shift, the rotation, the XY scaling, and the perpendicularity of the pattern formed on the separate area SA_i on the sheet S.

Here, when it is determined that the contraction amount of the separate area SA_i in the Y-axis direction and the X-axis direction is within a predetermined range as the determination result of b2, the main control device 50 skips the processes of b3 and b4 and performs the process of b5.

Subsequently, the main control device 50 releases the restraint (fixation) of the sheet S performed by a predetermined transpiration roller portion of the sheet transporting system 40 used to apply a predetermined tension to the sheet S in the X-axis direction.

In addition, when the number of the alignment systems is fewer than the number of the alignment marks to be detected, it is necessary to perform the alignment measurement while stepwisely moving the stage SST holding the sheet S in the X-axis direction. At this time, the main control device 50 controls the rotation and the stopping of each of the driving rollers of the sheet transporting system 40 in accordance with the movement of the stage SST.

c. Next, the scanning exposure for the separate area SA_i on the sheet S is performed.

c1. In detail, the main control device 50 moves the stage SST holding the sheet S to the scanning start position (acceleration start position) for the exposure on the basis of the result of the alignment measurement, and particularly, the XY shift so as to perform a positioning operation with respect to the mask stage MST holding the mask M. Here, in
5 the embodiment, since the acceleration start position of the stage SST is set to the same position (or the vicinity thereof) as the above-described standby position, the minute adjustment of the position of the stage SST within the XY plane is performed.

c2. Next, the main control device 50 starts the acceleration of the stage SST in the scanning direction (-X-axis direction). Accordingly, the movement of the stage SST in
10 the -X-axis direction is started. During the movement, and particularly, before the acceleration end of the stage SST, as shown in FIG. 15, the length measurement beam from the interferometer 18Y₂ starts to collide with the reflection surface 17Y. Accordingly, immediately after the collision of the length measurement beam, the main control device 50 changes the laser interferometer for measuring the Y position of the
15 stage SST from the interferometer 18Y₁ to the interferometer 18Y₂.

c3. Then, when the acceleration operations of both stages SST and MST end, and the acceleration operations of both stages SST and MST are synchronized with uniform speed, the pattern area on the mask M starts to be illuminated by the illumination light IL₂ and IL₄, thereby starting the exposure. Then, in accordance with the
20 synchronization movement with uniform speed of both stages SST and MST, as shown in FIG. 16, the illumination areas IAM₁ to IAM₅ (refer to FIG. 2) on the mask M are illuminated by the illumination light IL₁ to IL₅, and the partial images of the patterns inside the illumination areas IAM₁ to IAM₅ are projected onto the projection areas IA₁ to IA₅ on the sheet S held on the stage SST through the projection optical systems PL₁ to
25 PL₅ (refer to FIG. 3).

When the entire area of the pattern area of the mask M is illuminated by the illumination light IL_1 to IL_5 , that is, the pattern area of the mask M passes through the illumination areas IAM_1 to IAM_5 , the scanning exposure for the separate area SA_i is completed. Accordingly, the pattern of the mask M is transferred to the separate area
5 SA_i . That is, a latent image of the pattern of the mask M is formed on the resist layer formed on the surface of the sheet S.

During the scanning exposure, the main control device 50 drives the table TB of the stage SST in the Z-axis direction while horizontally maintaining the table, so that the surface of the sheet S held on the table TB (sheet holder SH_1) is positioned to the focal
10 position (within the focal depth) of the projection optical system PL. In addition, during the scanning exposure, the main control device 50 controls the synchronization driving state (the relative position and the relative speed) of the stage SST and the mask stage MST on the basis of the result of the alignment measurement so as to correct the distortion of the entire image of the pattern projected onto the sheet S. Further, the main
15 control device 50 controls the driving state of the optical element group (lens group) constituting the projection optical systems PL_1 to PL_5 through the lens controller LC so as to correct the distortion of the partial image of the pattern projected onto the projection areas IA_1 to IA_5 on the sheet S. Accordingly, the projection image of the pattern of the mask M is highly precisely overlapped with the pattern formed within the separate area
20 SA_i .

After the scanning exposure for the separate area SA_i is completed, both stages SST and MST are decelerated. As shown in FIG. 17, when they arrive at the scanning end position (deceleration end position), they are stopped. In addition, in the embodiment, the deceleration end position of the stage SST during the scanning
25 operation is determined so as to be aligned to the $-X$ end of the base member BS.

In addition, when the main control device 50 drives the stage SST holding the sheet S in the $-X$ -axis direction during the scanning exposure, as described above, the main control device appropriately rotates or stops each of the driving rollers of the sheet transporting system 40 in accordance with the movement of the stage SST so that the movement of the stage SST is not disturbed by a tension applied to the sheet S.

d. As shown in FIG. 17, when the stage SST is stopped at the $-X$ end as the deceleration end position in front of the base member BS, the main control device 50 releases the operation of adsorbing and holding the sheet S using the sheet holder SH₁ and the sheet holder SH₂ so as to release the sheet S from the stage SST. Further, the main control device 50 retreats the table TB of the stage SST downward ($-Z$ -axis direction). Accordingly, the sheet S is stretched between the transportation roller portions 42 and 43 with a minute space with respect to the sheet holder SH₁ of the stage SST.

e. After the sheet S is released, as shown in FIG. 18, the main control device 50 drives the sheet stage SST in the $+X$ -axis direction depicted by the black arrow so as to return to the above-described standby position of the $+X$ end on the base member BS. Here, in accordance with the X position of the sheet stage SST, the interferometer for measuring the Y position is changed from the interferometer 18Y₂ to the interferometer 18Y₁. In addition, the main control device 50 drives the mask stage MST to return to the scanning start position (acceleration start position) at a high speed. Further, in addition to the operation of driving the stage, the main control device 50 pulls back the sheet S in the $+X$ -axis direction depicted by the white arrow as shown in FIG. 18.

f. The returning driving operation of the stage SST and the mask stage MST and the operation of pulling back the sheet S are completed, as shown in FIG. 19, the stage SST stays at the standby position, and the center portion of the sheet S including the

subsequent separate area SA_{i+1} is positioned to the surface of the stage SST staying at the standby position. This state is the same as that shown in FIG. 10 except that one separate area of the sheet S has transported.

Subsequently, the main control device 50 starts the exposure for the separate area
5 SA_{i+1} as in the former case. Subsequently, in the same manner, the main control device 50 repeats the above-described sequences a. to f. so as to perform an exposure for all separate areas on the sheet S.

As described above in detail, each of the rollers of the transportation roller
portion 43 is rotated in the state where the rotation of each of the rollers of the
10 transportation roller portions 41, 42, and 44 of the sheet transporting system 40 is stopped (or each of the rollers of the transportation roller portion 42 is reversely rotated in the state where the rotation of each of the rollers of the transportation roller portions 41, 43, and 44 is stopped) by the main control device 50, so that a predetermined tension is applied to the sheet S in the X-axis direction so as to be stretched between the
15 transportation roller portions 42 and 43. In addition, after the sheet S is temporarily held by six auxiliary sheet holders SH_2 and SH_3 , six auxiliary sheet holders SH_2 and SH_3 are minutely driven in the $-Z$ -axis direction in the state where the sheet S is temporarily held by the main control device 50, so that the rear surface of the center portion of the sheet S including the separate area SA_i comes into contact with the holding surface of the
20 sheet holder SH_1 . In addition, the holding surfaces of six auxiliary sheet holders SH_2 and SH_3 are positioned to be slightly on the lower side ($-Z$ side) of the holding surface of the sheet holder SH_1 by the main control device 50, so that the center portion of the sheet S is fixed onto the holding surface of the sheet holder SH_1 in the state where an appropriate tension is applied to the sheet S in the width direction (Y-axis direction) and
25 the longitudinal direction. That is, in the state where a tension is applied to the separate

area SA_i of the sheet S in the XY two-dimensional direction, the rear surface portion corresponding to the separate area SA_i of the sheet S is adsorbed by the flat holding surface of the sheet holder SH_1 . Further, the illumination system IOP illuminates the illumination light IL_1 to IL_5 to the separate area SA_i of the sheet S flatly adsorbed by the holding surface of the sheet holder SH_1 through the pattern of the mask M, so that the scanning exposure is performed on the sheet S, and the pattern is formed thereon. Accordingly, even in the case of the sheet S becoming contracted by, for example, heat generated during a treatment of a process, it is possible to perform the exposure with high precision. Therefore, it is possible to contribute to the production of an electronic device such as a flexible large-size display without increasing the size of the device.

In addition, in the above-described embodiment, a case has been described in which the holding surfaces of two auxiliary sheet holders SH_3 are positioned slightly below (-Z side) the holding surface of the sheet holder SH_1 so as to further apply a tension to the sheet S in the X-axis direction when the rear surface of the center portion of the sheet S including the separate area SA_i is adsorbed by the holding surface of the sheet holder SH_1 in the state where a predetermined tension is applied to the sheet S in the X-axis direction by the transportation roller portion of the sheet transporting system 40. However, the present invention is not limited thereto. A tension can be applied to the sheet S in the X-axis direction just by moving two auxiliary sheet holders SH_3 adsorbing and holding the sheet S in the -Z-axis direction and the direction moving away from each other. Alternatively, a tension can be applied to the sheet S in the X-axis direction by the restraint of the sheet using the constituting portion of the sheet transporting system 40 without providing the auxiliary sheet holder SH_3 . In this case, a clamper portion 45 shown in FIG. 21 can be further provided inside the sheet transporting system 40. The case of being provided the clamper portion 45 will be described in

detail after.

In addition, in the exposure device 100 of the above-described embodiment, the alignment measurement for the sheet S is performed by using the alignment systems AL_1 to AL_{12} arranged along the X-axis direction while being distant from each other in the Y-axis direction. However, the present invention is not limited thereto. For example, the alignment marks are disposed in the periphery of the separate area SA_i on the sheet S at a predetermined interval, and as shown in FIG. 20, the alignment systems AL' are disposed in the periphery of the separate area SA_i so as to correspond to the arrangement of the alignment marks, thereby simultaneously detecting all alignment marks. In this case, when it is detected that the separate area SA_i is decreased in the X-axis direction on the basis of the measurement result of the positions of the alignment marks, the scaling error in the X-axis direction of the separate area can be adjusted in such a manner that the main control device 50 drives two auxiliary sheet holders SH_3 adsorbing and holding the sheet S in a direction moving away from each other so as to apply a tension to the sheet S in the X-axis direction. In addition, a plurality of auxiliary sheet holders SH_3 can be disposed in the X-axis direction across the sheet holder SH_1 , and the scaling error in the X-axis direction corresponding to the Y position within the separate area can be adjusted by individually using the auxiliary sheet holders SH_3 on the basis of the measurement result of the positions of the alignment marks.

<Second Embodiment>

Hereinafter, second embodiment of the present invention will be described with reference to FIGS. 21 to 39.

FIG. 21 shows a schematic configuration of an exposure device 1000 according to a second embodiment. The exposure device 1000 is a multi-lens type projection exposure device, that is, a so-called scanner in which a flexible sheet or film (hereinafter,

they are all referred to as a sheet) is an exposure target object. In the embodiment, as an example, a sheet having a thickness of about 100 μm is used.

The exposure device 1000 includes an illumination system IOP, a mask stage MST which holds a mask M, a projection optical system PL which projects an image of a pattern formed on the mask M onto a sheet S, a stage device SS which includes a sheet stage (hereinafter, simply referred to as a stage) SST for holding the sheet S, a sheet transporting system 40 which transports the sheet S, a control system thereof, and the like.

In addition, the sheet S used in the exposure device 1000 of the embodiment is a continuously elongated sheet. The sheet S is wound in a roll shape, and is set in a roller 40₁. As described below, the sheet S is extracted from the roller 40₁ by (transportation roller portions 41 to 44 constituting) the sheet transporting system 40, passes through an area directly below of the projection optical system PL, and is wound on a winding roller 40₂. In addition, a photosensitizing agent (resist) is coated on the surface of the sheet S. In the embodiment, as an example, the sheet S is extracted from the roller 40₁ and is wound on the winding roller 40₂, but the present invention is not limited thereto. A sheet extracted from a resist coating device for performing a treatment before an exposure, for example, a resist coating treatment and transported to a developing device for performing a treatment after an exposure, for example, a developing treatment can be subjected to an exposure by the exposure device 1000.

Hereinafter, a vertical direction (the up/down direction of FIG. 21) parallel to the light axis (here, the middle portion between both portions is excluded) of the object surface side and the upper surface side of the projection optical system PL is set to the Z-axis direction, a scanning direction (the left/right direction of FIG. 21) in which the mask M and the sheet S are relatively scanned by the projection optical system PL within

a plane perpendicular to the Z-axis direction is set to the X-axis direction, and a direction perpendicular to the Z-axis direction and the X-axis direction is set to the Y-axis direction. Then, the rotation (inclination) directions of the X, Y, and Z-axis directions are respectively described as θ_x , θ_y , and θ_z directions.

5 The illumination system IOP includes a plurality of (herein, five) illumination system modules (hereinafter, simply referred to as illumination systems) IOP₁ to IOP₅. Each of the illumination systems IOP₁ to IOP₅ includes an ultra high pressure mercury lamp (light source) which emits UV light, an oval mirror which collects the UV light from the light source, a wavelength selection filter which is disposed on the light path of
10 the collected UV light, an optical integrator, and an illumination optical system (are not shown) which includes a visual field diaphragm. The emission line, for example, a line i (having a wavelength of 365 nm), a line g (having a wavelength of 436 nm), or a line h (having a wavelength of 405 nm) from the UV light is extracted as illumination light IL₁ to IL₅ through the wavelength selection filter. Each of the extracted illumination light
15 IL₁ to IL₅ is emitted (toward the mask M) on the outside of the illumination system IOP (IOP₁ to IOP₅) along each of the light axes AX₁ to AX₅ (refer to FIG. 22).

In addition, as shown in FIG. 22, the light axes AX₁, AX₃, and AX₅ are arranged at a predetermined interval in the Y-axis direction within the XY plane (the pattern surface of the mask M). Further, the light axes AX₂ and AX₄ are respectively disposed
20 between the light axes AX₁ and AX₃ and between the light axes AX₃ and AX₅ with a predetermined distance therebetween from the light axes AX₁, AX₃, and AX₅ to the +X side. That is, the light axes AX₁ to AX₅ are arranged in a zigzag shape within the XY plane.

The illumination systems IOP₁ to IOP₅ illuminate illumination light IL₁ to IL₅ to
25 illumination areas IAM₁ to IAM₅ on the mask M along the light axes AX₁ to AX₅ with

uniform intensity of illumination. Each of the illumination areas has an isosceles trapezoid shape stipulated by the visual field diaphragm (not shown) within the illumination optical system. In addition, the detailed configuration of the illumination system IOP (IOP₁ to IOP₅) is disclosed in, for example, the specification of US Patent No. 5 6,552,775.

As shown in FIG. 21, the mask stage MST is disposed at the low position (−Z side) of the illumination system IOP. The rectangular mask M is fixed onto the mask stage MST by, for example, vacuum adsorption, where the mask indicates that a rectangular pattern area is formed in the pattern surface (−Z side surface). The mask stage MST can be minutely driven within the XY plane by a mask stage driving system MSD (not shown in FIG. 21, and refer to FIG. 29) including a linear motor and the like, and can be driven at a predetermined scanning speed of a predetermined stroke in the scanning direction (X-axis direction).

Positional information within the XY plane of the mask stage MST is constantly measured while having, for example, a resolution of about 0.25 to 1 nm by laser interferometers (hereinafter, simply referred to as interferometers) 16X and 16Y constituting a part of a mask stage interferometer system 16 (refer to FIG. 29). As shown in FIG. 22, the +X side surface and the −Y side surface of the mask stage MST are subjected to mirror-like finishing so as to have reflection surfaces 15X and 15Y. The interferometer 16X measures the rotation in the direction θ_z and the position (X position) in the X-axis direction of the mask stage MST by emitting a plurality of length measurement beams to the reflection surface 15X along the light path parallel to the X axis and receiving the reflected beams from the reflection surfaces 15X. The substantial length measurement axis of the interferometer 16X is an axis parallel to the X axis perpendicular to the light axis AX₃. The interferometer 16Y measures the position (Y

position) in the Y-axis direction of the mask stage MST by emitting two length measurement beams to the reflection surface 15Y along the light path parallel to the Y axis perpendicular to the light axes AX_1 and AX_2 and receiving the reflected beams from the reflection surface 15Y. In addition, instead of the above-described reflection surfaces 15X and 15Y, a moving mirror formed by a plane mirror can be fixed to the mask stage MST.

The measurement information of the interferometers 16X and 16Y is supplied to a main control device 50 (refer to FIG. 29). The main control device 50 controls the mask stage MST through the mask stage driving system MSD on the basis of the measurement information (the positional information of the mask stage MST) of the interferometers 16X and 16Y.

As shown in FIG. 21, the projection optical system PL is disposed at the low position (-Z side) of the mask stage MST. For example, as shown in FIG. 23, the projection optical system PL according to the embodiment includes five projection optical system modules (hereinafter, simply referred to as projection optical systems) PL_1 to PL_5 which are disposed in a zigzag shape so as to correspond to arrangement of the light axes AX_1 to AX_5 . In FIG. 21, the projection optical systems PL_3 , PL_5 , and PL_4 are disposed backward the projection optical systems PL_1 and PL_2 in this paper plane. As each of the projection optical systems PL_1 to PL_5 , for example, a both-side telecentric reflection-refraction system is used which forms an erect image on an image surface at the same magnification.

By means of the arrangement of the above-described projection optical systems PL_1 to PL_5 (the light axes AX_1 to AX_5), the projection areas IA_1 to IA_5 where the image of the pattern is projected by the projection optical systems PL_1 to PL_5 on the sheet S are arranged in a zigzag shape as in the illumination areas IAM_1 to IAM_5 . Here, the

projection areas IA_1 to IA_5 have an isosceles trapezoid shape as in the illumination areas IAM_1 to IAM_5 . By means of the arrangement and the shape of the projection areas IA_1 to IA_5 , the mask M and the sheet S are driven in a synchronized manner in the scanning direction (X-axis direction) while the image (the partial image) of the pattern within the illumination areas IAM_1 to IAM_5 on the mask M is projected onto the projection areas IA_1 to IA_5 on the sheet S through the projection optical systems PL_1 to PL_5 , so that the partial images of the pattern projected onto the sheet S are synthesized as one image (synthesized image) which is the same as the pattern formed in the mask M .

Accordingly, by means of the scanning exposure, the pattern of the mask M is transferred onto (one short area (separate area) SA_i) the sheet S through the projection optical systems PL_1 to PL_5 . In addition, the detail of the scanning exposure will be described later.

In the embodiment, since the optical system for projecting the erected image at the same magnification is adopted as the projection optical systems PL_1 to PL_5 , the shape and the arrangement (positional relationship) of the projection areas IA_1 to IA_5 are the same as the shape and the arrangement (positional relationship) of the illumination areas IAM_1 to IAM_5 . The detailed configuration of the projection optical system PL according to the embodiment is disclosed in, for example, US Patent No. 6,552,775 and the like.

The exposure device 1000 includes a lens controller LC (refer to FIG. 29) which corrects a distortion (the positional deviation and/or the shape error) of the image projected onto the sheet S by the projection optical systems PL_1 to PL_5 . The lens controller LC drives at least a part of an optical element group (lens group) constituting each of the projection optical systems PL_1 to PL_5 in a direction parallel to the light axes AX_1 to AX_5 and a direction inclined relative to the XY plane perpendicular to the light

axes AX_1 to AX_5 . Accordingly, the distortion (the shift, the rotation, the magnification (scaling), and the like) of the partial image of the pattern projected onto the projection areas IA_1 to IA_5 of the sheet S is corrected. In addition, the lens controller LC can change a pressure of a gas inside a hermetic room formed inside the projection optical systems PL_1 to PL_5 or change the wavelength of the illumination light instead of or in addition to driving the optical element group.

As shown in FIG. 21, the stage device SS is disposed at the low position (-Z side) of the projection optical system PL (PL_1 to PL_5). The stage device SS includes a base member BS which is supported on a bottom surface by an anti-vibration mechanism (not shown) so as to be substantially horizontal, a stage SST which moves and supports the sheet S on the base member BS, a driving system SSD (not shown in FIG. 21, refer to FIG. 29) which drives the stage SST, a stage interferometer system 18 (refer to FIG. 29) which measures positional information of the stage SST, and the like. In addition, in FIG. 21, the sheet S is adsorbed and held onto the stage SST.

As shown in FIG. 21, the stage SST includes a stage body ST which is supported on the base member BS in an uplifted state by a plurality of non-contact bearings (for example, air bearings (not shown)) provided in the bottom surface, a Z-leveling device 38 (refer to FIG. 24A) which is disposed on the stage body ST, and a table TB which is supported at three points by the Z-leveling device 38.

As shown in FIG. 24B, the Z-leveling device 38 includes three Z driving mechanisms 38a, 38b, and 38c which are disposed at three points not existing in one line on the stage body ST and including, for example, a voice coil motor and the like. By means of the Z-leveling device 38, it is possible to minutely drive the table TB on the stage body ST in a direction of three degrees of freedom of the Z-axis direction, the θ_x direction, and the θ_y direction.

The stage SST (stage body ST) is scan-driven on the base member BS by the stage driving system SSD in the X-axis direction (scanning direction), and is also minutely driven in the Y-axis direction and the θ_z direction. The stage driving system SSD includes a minute movement device (not shown) which minutely drives the stage SST in the Y-axis direction, and a rough movement device 30 (refer to FIG. 29) which drives the minute movement device (not shown) in the scanning direction (X-axis direction).

As shown in FIGS. 24B and 26, the rough movement device 30 includes a pair of linear motors 30₁ and 30₂ respectively provided in one side and the other side of the Y-axis direction of the stage SST. The one linear motor 30₁ includes a fixed portion 31₁ which is disposed on the -Y side of the base member BS and extends in the X-axis direction, and a movable portion 32₁ which is attached to the fixed portion 31₁ so as to be movable along the longitudinal direction. The other linear motor 30₂ includes a fixed portion 31₂ which is disposed on the +Y side of the base member BS and extends in the X-axis direction, and a movable portion 32₂ which is attached to the fixed portion 31₂ so as to be movable along the longitudinal direction. Each of the fixed portions 31₁ and 31₂ includes a plurality of magnets (or coils) arranged along the X-axis direction, and each of the movable portions 32₁ and 32₂ includes coils (or magnets). The movable portions 32₁ and 32₂ are respectively fixed to the -Y side surface and the +Y side surface of the stage body ST through a minute movement device (not shown) which minutely moves them in the Y-axis direction. In addition, the stage body ST can be minutely driven in the θ_z direction by generating different thrust forces in the linear motors 30₁ and 30₂. In addition, a stage driving system can be configured which two-dimensionally moves the stage SST along the upper surface (guide surface) of the base member BS by using a planar motor of a Lorentz electromagnetic driving type, a

planar motor of a variable electromagnetic resistance driving type, a planar motor of a magnetic suspension type, and the like disclosed in, for example, the specification of US Patent No. 5,196,745 instead of the rough movement device 30 and the minute movement device.

5 The table TB is driven on the base member BS by the stage driving system SSD (refer to FIG. 29) including the rough movement device 30, the minute movement device (not shown), and the Z-leveling device 38 so as to have six degrees of freedom in the X-axis direction, the Y-axis direction, the Z-axis direction, the θ_x direction, the θ_y direction, and the θ_z direction.

10 As shown in FIGS. 24A and 24B, a sheet holder SH_1 is provided at the center portion of the upper surface of the table TB so as to adsorb and hold the sheet S. The sheet holder SH_1 is substantially parallel to the XY plane, and includes a rectangular holding surface which is slightly larger than the separate area arranged on the sheet S, thereby flatly holding the sheet S on the holding surface. Here, in order to adsorb and
15 hold the sheet S, as the sheet holder SH_1 , a pin chuck holder is adopted in which the arrangement interval (pitch) of the pins is sufficiently small, and the height of the pin is low so as to be, for example, about 200 μm .

In addition, four auxiliary sheet holders SH_2 are provided on the upper surface of the table TB so as to adsorb and hold the rear surface of both ends of the sheet S in the
20 width direction (the Y-axis direction perpendicular to the longitudinal direction). In detail, the $\pm Y$ sides of the sheet holder SH_1 are provided with two auxiliary sheet holders SH_2 which are thin and long in the X-axis direction and are distant from each other by a predetermined distance in the X-axis direction. Each of the auxiliary sheet holders SH_2 includes a rectangular holding surface, and can be minutely driven in the Y-axis direction
25 and the Z-axis direction by a holder driving device provided in the table TB.

FIG. 25A is a plan view showing a configuration of a holder driving device 60 provided inside the table TB, and FIG. 25B is a sectional view taken along the line B-B of FIG. 25A. Here, as an example, the holder driving device 60 is shown which drives the auxiliary sheet holder SH₂ located at the +Y-side end and the +X-side end of the table TB.

The holder driving device 60 includes a Y driving unit which includes a parallel link mechanism 61 as one type of a four-joint link mechanism provided inside a hollow portion provided in the table TB and a driving mechanism 63 driving (the driving joint of) the parallel link mechanism 61 and drives the auxiliary sheet holder SH₂ in the Y-axis direction, and a Z driving unit (not shown) which includes, for example, a driving element, a voice coil motor, and the like supporting a rectangular base 60₁ having the auxiliary sheet holder SH₂ fixed to the upper surface thereof on the bottom surface of the table TB and minutely driving that in the Z-axis direction. One end (-X end) of the base 60₁ is integrated with a link (hereinafter, conveniently referred to as a parallel movement link) which is located on the opposite side of the fixed link of the parallel link mechanism 61.

In detail, the parallel link mechanism 61 includes a pair of oscillation links 64₄ and 64₅ of which one end is respectively connected to a pair of link support members 66₃ and 66₄ fixed to the +X side wall of the hollow portion of the table TB and the other ends are respectively connected to one end 66₅ and the other end 66₆ of the above-described parallel movement link. In this case, the link support members 66₃ and 66₄ are fixed to the table TB to thereby configure a fixed link. The fixed link, the oscillation links 64₄ and 64₅, and the parallel link are adjacent links and configure a revolute pair.

The driving mechanism 63 includes an actuator 62 of which one end is fixed to a part of the side wall of the hollow portion of the table TB, an L-shaped lever link 64₁ of

which one end (driving point 68₀) comes into contact with the actuator 62 with pressure and a support point 68₂ of the middle portion is rotatably supported to a fixator 66₁ fixed to the bottom wall of the table TB, and a movable link 64₂ of which one end is connected to the other end (action point 68₃) of the lever link 64₁ and the other end is connected to an attachment member 66₇ fixed to a part of the above-described parallel movement link. The lever link 64₁ and the movable link 64₂ configure a revolute pair, and the movable link 64₂ and the attachment member 66₇ configure a revolute pair.

In addition, the attachment member 66₇ is connected to an attachment member 66₂ which is fixed to a part of the side wall of the -Y side wall of the hollow portion of the table TB through a spring member (pulling spring) 64₃. In this case, the attachment member 66₇ and the spring member (pulling spring) 64₃ form a revolute pair, and the spring member (pulling spring) 64₃ and the attachment member 66₂ form a revolute pair.

In the Y driving unit having the above-described configuration, one end (driving point 68₀) of the lever link 64₁ is constantly pressed and contacted by the actuator 62 by the spring member (pulling spring) 64₃. In addition, when the actuator 62 drives one end (driving point 68₀) of the lever link 64₁ in a direction (+X-axis direction) depicted by the white arrow of FIG. 25A while resisting the pressing and contacting force of the spring member 64₃, the attachment member 66₇ is driven in a direction (+Y-axis direction) depicted by the black arrow through the movable link 64₂. That is, the auxiliary sheet holder SH₂ is driven in the +Y-axis direction together with the base 60₁. In this case, the movement amount of the auxiliary sheet holder SH₂ is determined by a force generated by the actuator 62. In addition, as described above, the auxiliary sheet holder SH₂ is driven in the Z-axis direction together with the base 60₁ by the Z driving unit disposed below the base 60₁. However, in the below description, it will be described that the auxiliary sheet holder SH₂ is driven in the Z-axis direction by the base

60₁. That is, the base 60₁ is described as the Z driving unit.

The driving devices for the auxiliary sheet holder SH₂ provided in the +X-side end and the -Y-side end of the table TB have the similar configuration as the above-described holder driving device 60 being symmetric in the X axis.

5 A length between a force point 68₁ and a support point 68₂ of the lever link 64₁ and a length between a support point 68₂ and an operation point 68₃ are, for example, 1 to 3. For this reason, when one end of the lever link 64₁ is driven at the driving point 68₀ in the +X-axis direction by 10 μm by the actuator 62 of the holder driving device 60 (driving mechanism 63), the bending portion (force point 68₁) of the lever link 64₁ is
10 driven in the -Y-axis direction by 10 μm, and hence the other end (action point 68₃) of the lever link 64₁ is driven in the +Y-axis direction by 30 μm. Accordingly, it is possible to drive the auxiliary sheet holder SH₂ in the +Y-axis direction by 30 μm by using the holder driving device 60 (driving mechanism 63). In addition, in the state where both ends of the sheet S in the Y-axis direction are held by the pair of auxiliary
15 sheet holders SH₂ disposed on the table TB while being distant from each other in the Y-axis direction, when the auxiliary sheet holders SH₂ are driven in a direction opposite to each other (a direction moving away from each other), it is possible to stretch the sheet S by 60 μm at maximum.

20 The driving devices for the auxiliary sheet holders SH₂ provided in the +Y side, the -Y side, and the -X-side end of the table TB have the similar configuration as the above-described holder driving device 60 being symmetric in the Y axis.

As described below, the auxiliary sheet holders SH₂ are used to assist the sheet holder SH₁ when the sheet S is flatly held by the sheet holder SH₁. In addition, in the +Y end on the base 60₁, a rectangular-tray-shaped positioning member 60₂ is fixed to the

auxiliary sheet holder SH₂ while coming into contact therewith. The positioning member 60₂ has a role of positioning the sheet S in the Y-axis direction by pressing the +Y end (or -Y end) of the sheet S when the sheet S is adsorbed and held by the holding surface of the auxiliary sheet holder SH₂.

5 As shown in FIG. 24B, the +X side surface and the -Y side surface of the table TB are subjected to mirror-like finishing so as to have reflection surfaces 17X and 17Y. The reflection surfaces 17X and 17Y are used to measure the position of the stage SST by using a stage interferometer system to be described later. In addition, instead of the above-described reflection surface 17Y, a moving mirror formed by a plane mirror can be
10 fixed to the table TB. Further, instead of the reflection surface 17X, a moving mirror formed by a retro-reflector or a plane mirror can be fixed to the table TB.

 As shown in FIG. 26, the stage interferometer system 18 (refer to FIG. 29) includes interferometers 18X₁, 18X₂, 18Y₁, and 18Y₂, and measures constantly the positional information (including the rotation information in the θ_z direction) within the
15 XY plane of the stage SST (table TB) while having, for example, a resolution of about 0.25 to 1 nm.

 The interferometers 18X₁, 18X₂, and 18Y₁, 18Y₂ are disposed on the +X side and the -Y side of the projection optical system PL so as to face the reflection surfaces 17X and 17Y of the table TB.

20 The interferometers 18X₁ and 18X₂ measure the X position of the stage SST by emitting a length measurement beam parallel to the X axis to the reflection surface 17X of the table TB and receiving the reflected beam from the reflection surface 17X. The interferometers 18Y₁ and 18Y₂ measure the Y position of the stage SST by emitting two length measurement beams parallel to the Y axis to the reflection surface 17Y and
25 receiving the reflected beam from the reflection surface 17Y. Here, one of two length

measurement beams of the interferometer 18Y₂ is emitted to the reflection surface 17Y along the light path parallel to the Y axis perpendicular to the light axes AX₁, AX₃, and AX₅, and the other thereof is emitted to the reflection surface 17Y along the light path parallel to the Y axis perpendicular to the light axes AX₂ and AX₄. In addition, the two
5 light measurement beams of the interferometer 18Y₁ are emitted to the reflection surface 17Y along two light paths parallel to the Y axis passing the detection center of each of alignment systems AL₁₁ and AL₁₂ to be described later.

The measurement information of the stage interferometer system 18 (interferometers 18X₁, 18X₂, 18Y₁, and 18Y₂) is supplied to the main control device 50
10 (refer to FIG. 29). In addition, when the stage SST is located on the base member BS, at least one of the length measurement beams of the interferometers 18Y₁ and 18Y₂ is emitted to the reflection surface 17Y of the stage SST regardless of the X position thereof. Accordingly, the main control device 50 uses any one of the measurement information of the interferometers 18Y₁ and 18Y₂ in accordance with the X position of the stage SST.
15 In addition, the main control device 50 measures the rotation in the θ_z direction of the stage SST on the basis of the measurement information of the interferometers 18X₁ and 18X₂.

In addition, as the interferometers 18X₁, 18X₂, 18Y₁, and 18Y₂, a multi-axis interferometer which emits a plurality of length measurement beams distant from each
20 other in the Z-axis direction can be used. In this case, the main control device 50 can obtain the inclination information (the pitching amount (the rotation amount θ_x in the θ_X direction) and the rolling amount (the rotation amount θ_y in the θ_y direction)) with respect to the XY plane in addition to the positional information (rotation information (including yawing amount (the rotation amount θ_z in the θ_Z direction))) within the XY
25 plane of the stage SST (table TB).

As shown in FIGS. 21 and 26, the sheet transporting system 40 includes four transportation roller portions 41 to 44 which are arranged in the X-axis direction across the projection optical system PL and a clamper portion 45.

As shown in FIGS. 27A to 27G, each of the transportation roller portions 41, 42,
5 43, and 44 includes a pair of a pressure roller and a driving roller located at the upper and lower positions. In the driving rollers 41₂, 42₂, 43₂, and 44₂ located at the lower position, both ends thereof are rotatably supported by support members (not shown) so that the upper ends thereof are slightly located at the upper position (+Z side) of the upper surface (the holding surface of the sheet holder SH₁) of the stage SST (refer to FIG.
10 21). The driving rollers 41₂, 42₂, 43₂, and 44₂ are rotationally driven by a rotation motor (not shown). The pressure rollers 41₁, 42₁, 43₁, and 44₁ located at the upper position are pressed and contacted by the corresponding driving rollers from the upper side (+Z side) by a spring mechanism (not shown).

However, as shown in FIG. 27B by adopting the transportation roller portion 41,
15 the pressure roller 41₁ and the driving roller 41₂ are formed as a stepped cylindrical shape of which a diameter of a portion other than both ends in the longitudinal direction is smaller than those of the both ends.

For this reason, in each of the transportation roller portions 41, 42, 43, and 44, as shown in FIG. 27B by adopting the representative transportation roller portion 41, the
20 sheet S is sandwiched by both ends of the pressure roller (41₁) and the driving roller (41₂) so that that the rollers do not come into contact with the separate area where the pattern is formed on the surface of the sheet S. In each of the transportation roller portions 41, 42, 43, and 44, it is possible to set a first state where the sheet S can be sandwiched between the pressure roller (41₁) and the driving roller (41₂) and a second state where the
25 operation of sandwiching the sheet S can be released by separating the pressure roller

(41₁) from the driving roller (41₂) while resisting the pressing force of the spring mechanism. In each of the transportation roller portions 41, 42, 43, and 44, the selection of the first state and the second state is performed by the main control device 50. In addition, the driving roller coming into contact with the rear surface of the sheet S can
5 be a cylindrical roller having uniform diameter.

The rotation and the stopping of the driving rollers 41₂, 42₂, 43₂, and 44₂ are controlled by the main control device 50 together with the rollers 40₁ and 40₂. As shown in FIG. 27B by adopting the representative transportation roller portion 41, when the driving roller (41₂) is rotated about the axis parallel to the Y axis (and the pressure
10 roller 41₁ is rotated in the reverse direction) in the first state of the transportation roller portion, the sheet S is transported in the rotation direction.

In the sheet transporting system 40, as shown in FIG. 27C, the rollers 41₁ and 41₂ of the transportation roller portion 41 are rotated in a direction depicted by the arrow, so that the sheet S is drawn out in the -X-axis direction depicted by the white arrow from
15 the roller 40₁ and is transported toward the transportation roller portion 42. Here, when the rotation of the rollers 42₁ and 42₂ of the transportation roller portion 42 is stopped at a predetermined timing, the sheet S having a predetermined length (a degree corresponding to a distance between the transportation roller portions 42 and 43) is bent in a loop shape between the transportation roller portions 41 and 42. In addition, in the
20 sheet transporting system 40, as shown in FIG. 27D, the rollers 42₁ and 42₂ of the transportation roller portion 42 (and the rollers 43₁ and 43₂ of the transportation roller portion 43) are rotated in a direction depicted by the arrow in the state where the rotation of each of the rollers 41₁ and 41₂ of the transportation roller portion 41 is stopped, so that the sheet S bent in a loop shape is transported in the -X-axis direction depicted by the
25 white arrow toward an area directly below the projection optical system PL.

In the sheet transporting system 40, as described above, the sheet S is drawn out from the area directly below the projection optical system PL by means of the rotation and the stopping of each of the rollers of the transportation roller portions 43 and 44. That is, as shown in FIG. 27E, when each of the rollers 43₁ and 43₂ of the transportation roller 43 is rotated in a direction depicted by the arrow in the state where the rotation of each of the rollers 44₁ and 44₂ of the transportation roller portion 44 is stopped, the sheet S is drawn out to the area directly below the projection optical system PL, and the drawn sheet S is bent in a loop shape between the transportation roller portions 43 and 44. Then, as shown in FIG. 27F, when each of the rollers 44₁ and 44₂ of the transportation roller portion 44 is just rotated in a direction depicted by the arrow in the state where the rotation of each of the rollers 43₁ and 43₂ of the transportation roller portion 43 is stopped, the sheet S bent in a loop shape is transported to the -X side of the transportation roller portion 44, and is wound on the winding roller 40₂.

As shown in FIG. 27A and the like, the clamper portion 45 is provided on the -X side of the transportation roller portion 42. The clamper portion 45 includes a pair of clamper members 45₁ and 45₂ capable of setting a first state where the sheet S is sandwiched in the up/down direction and a second state where the sandwiching operation is released.

The upper clamper member 45₁ includes a cylindrical roller 46a which has a length slightly longer than the width of the sheet S and is disposed along the Y-axis direction, and a pair of arm members 46b which rotatably supports both ends of the roller 46a. The pair of arm members 46b is supported by a support member (not shown) so as to be rotatable about a rotation shaft parallel to the Y axis. In addition, the roller 46a is attached to the rotation end of the pair of arm members 46b. Accordingly, when the clamper member 45₁ is rotated about the rotation shaft of the pair of arm members 46b in

the clockwise direction, the roller 46a comes into contact with the surface of the sheet S (refer to FIG. 27G). When the clamper member is rotated about the rotation shaft of the pair of arm members 46b in the counter-clockwise direction, the roller 46 moves away from the sheet S.

5 The lower clamper member 45₂ is symmetric to the clamper member 45₁ in the up/down direction, and has the similar configuration. The changeover of the state of the clamper portion 45 is performed by the main control device 50.

 In the sheet transporting system 40, as shown in FIG. 27G, the pair of the clamper members 45₁ and 45₂ of the clamper portion 45 is set to the first state, so that the sheet S
10 is restrained (fixed) by the pair of clamper members 45₁ and 45₂. Also, when each of the rollers of the transportation roller portion 43 is rotated in a direction in which the sheet S is transported in the state where the rotation of each of the rollers of the transportation roller portions 41 and 42 is stopped, a predetermined tension is applied to a portion between the transportation roller portion 43 and the clamper portion 45 of the
15 sheet S in the X-axis direction and the sheet S is stretched.

 Here, as shown in FIG. 27A, the main control device 50 restrains (fixes) the sheet S so that the roller 46a does not come into contact with the separate area portion where the pattern is formed on the surface of the sheet S, that is, the rollers 46a of the pair of clamper members 45₁ and 45₂ of the clamper portion 45 come into contact with an area
20 between the adjacent separate areas of the sheet S. The sheet S stretched in this manner is adsorbed and held by the sheet holder SH₁ on the stage SST.

 The sheet transporting system 40 further includes a measurement device (not shown) which measures the transportation amount of the sheet S, for example, a rotary encoder and the like which measure the rotation amount of each of the driving rollers 41₂,
25 42₂, 43₂, and 44₂.

In addition, the operation of transporting the sheet S, the operation of holding the sheet S on the stage SST, and the like using the sheet transporting system 40 during the exposure process will be described later in detail.

Further, in the exposure device 1000 of the embodiment, a plurality of (herein,
5 twelve) off-axis type alignment systems AL_1 to AL_{12} is provided so as to detect the alignment marks attached to the separate areas on the sheet S. As shown in FIG. 26, the alignment systems AL_1 to AL_6 are provided at the position of the +X side of the projection optical system PL along the X axis so as to face the area of the +Y-side end on the outside of the separate area on the sheet S. In addition, as shown in FIG. 26, the
10 alignment systems AL_7 to AL_{12} are disposed so as to be symmetric to the alignment systems AL_1 to AL_6 with respect to the X axis perpendicular to the light axis of the projection area IA_3 . The alignment systems AL_7 to AL_{12} can be disposed so as to face the area of the -Y-side end on the outside of each separate area on the sheet S.

In the embodiment, as an example, as shown in FIG. 28, six alignment marks AM
15 (twelve in total) are provided in each area on the outside of the Y-axis direction of each separate area SA_i on the sheet S, and the alignment systems AL_1 to AL_{12} are provided so as to individually and simultaneously detect the twelve alignment marks AM.

Accordingly, the present invention is not limited thereto, and when the alignment systems are movable in the X-axis direction, at least one alignment system can be provided
20 instead of the alignment systems AL_1 to AL_6 , and at least one alignment system can be provided instead of the alignment systems AL_7 to AL_{12} .

As the alignment systems AL_1 to AL_{12} , an exemplary image process type FIA (Field Image Alignment) system is adopted. The detection result (the image information of the index mark and the detection target mark) of the alignment systems
25 AL_1 to AL_{12} are transmitted to the main control device 50 through an alignment signal

process system (not shown). In addition, the present invention is not limited to the FIA.

An alignment sensor, which emits coherent detection light to the target mark and detects the scattered light or the diffracted light generated from the target mark or detects two beams of diffracted light (for example, the same homogeneous number) generated from the target mark through the interference, can be solely used or appropriately combined.

FIG. 29 is a block diagram showing an input/output relationship of the main control device 50 which generally controls the constituents of the control system of the exposure device 1000.

Next, the sequence of the exposure operation for the sheet S using the stage SST in the exposure device 1000 of the embodiment will be described with reference to FIGS. 30 to 38. In addition, the operation is described with reference to a plurality of drawings, but the reference numerals can be given or not given to the same constituents for each of the drawings. That is, there is a difference in the mark of the reference numerals in each of the drawings, but the configuration is the same regardless of the mark of the reference numerals of the drawings. The same applies to the drawings which have been used for the description.

FIG. 30 shows a state where the exposure for the first (i-1) number of the separate areas SA_1 to SA_{i-1} among the plurality of separate areas arranged on the sheet S is completed, and the exposure for the subsequent separate area SA_i is about to be started.

In the state of FIG. 30, the stage SST used for the movement of the sheet S during the exposure for the separate area SA_i stays at the position (standby position) of the +X end on the base member BS.

In addition, since the load and the mask alignment (the positioning operation of the mask) of the mask M on the mask stage MST are generally performed before the start of the exposure for the first separate area SA_1 on the sheet S, in the state of FIG. 30, the

load and the mask alignment of the mask M are of course completed. In addition, it is assumed that the mask stage MST is moved to the scanning start position (acceleration start position) for the exposure of the separate area SA_i .

p. First, the center portion of the sheet S including the separate area SA_i is held
5 onto the stage SST in accordance with the following sequence of p1 to p4.

p1. In detail, for example, as described above with reference to FIG. 27C, the main control device 50 stops the rotation of each of the rollers of the transportation roller portion 42 of the sheet transporting system 40 and then rotates each of the rollers of the transportation roller portion 41 so as to draw out the sheet S from the roller 40₁.

10 Alternatively, the main control device 50 stops the rotation of each of the rollers of the transportation roller portions 43 and 41 and then reversely rotates the transportation roller portion 42 so as to draw back the sheet S to the area directly below the projection optical system PL. Anyway, the sheet S having a predetermined length is bent in a loop shape between the transportation roller portions 41 and 42. The predetermined length is a
15 length corresponding to a distance between the transportation roller portions 42 and 43.

p2. Next, the main control device 50 controls the sheet transporting system 40 on the basis of the positional information of the stage SST obtained from the stage interferometer system 18 ($18X_1$, $18X_2$, $18Y_1$, and $18Y_2$) so as to position the separate area SA_i on the sheet S onto (the holding surface of) the sheet holder SH_1 of the stage
20 SST. Here, as described above with reference to FIG. 27G, the main control device 50 restrains (fixes) the sheet S by sandwiching a portion between the separate area SA_{i+1} and SA_{i+2} of the sheet S using the clamber portion 45 and rotates each of the rollers of the transportation roller portion 43 in the state where the rotation of each of the rollers of the transportation roller portions 41, 42, and 44 is stopped, so that a predetermined tension is
25 applied to the sheet S in the X-axis direction so as to be stretched between the clamber

portion 45 and the transportation roller portion 43. The main control device 50 further minutely drives the stage SST so as to position (the holding surface of) the sheet holder SH₁ to the separate area SA_i on the sheet S. In addition, in this state, a minute space is formed between the sheet S and (the holding surface of) the sheet holder SH₁ of the stage
5 SST.

In the state where the sheet S is positioned with respect to the stage SST at the standby position, the alignment marks AM attached to the separate area SA_i are positioned within the detection visual field of each of the alignment systems AL₁ to AL₁₂.

p3. After the positioning operation, the main control device 50 minutely drives
10 four auxiliary sheet holders SH₂ on the table TB through the base 60₁ in the +Z-axis direction while horizontally holding the table TB of the stage SST through the stage driving system SSD (Z-leveling device 38), so that the rear surfaces of the external portions on the ±Y sides of the separate area SA_i of the sheet S are adsorbed and held by four auxiliary sheet holders SH₂.

15 In detail, as shown in FIG. 31, the main control device 50 minutely drives two auxiliary sheet holders SH₂ respectively disposed in the +Y-side end and the -Y-side end on the table TB in a direction (+Y-axis direction or -Y-axis direction) depicted by the white arrow so as to widen the distance between the auxiliary sheet holders SH₂ distant from each other in the Y-axis direction on the table TB. In addition, the main control
20 device 50 drives each of the auxiliary sheet holders SH₂ in the +Z-axis direction through the base 60₁ so that the rear surfaces of both ends in the Y-axis direction of the sheet S come into contact with the holding surfaces of four auxiliary sheet holders SH₂. After the contact, the main control device 50 minutely drives two auxiliary sheet holders SH₂ on the +Y side in the -Y-axis direction depicted by the black arrow so as to firmly press
25 the positioning member 60₂ against the +Y end of the sheet S, and minutely drives two

auxiliary sheet holders SH₂ on the -Y side in the +Y-axis direction depicted by the black arrow so as to firmly press the positioning member 60₂ against the -Y end of the sheet S, thereby positioning the sheet S. After the positioning operation, the main control device 50 allows the rear surfaces of both ends of the sheet S in the Y-axis direction to be
5 adsorbed and held by four auxiliary sheet holders SH₂. FIG. 32 shows a state where the sheet S is temporarily held by the auxiliary sheet holder SH₂.

p4. After the temporary holding operation of the sheet S, the main control device 50 minutely drives each of four auxiliary sheet holders SH₂ in the -Z-axis direction through the base 60₁ in the state where the sheet S is temporarily held so as to allow the
10 rear surface of the center portion of the sheet S including the separate area SA_i to come into contact with the holding surface of the sheet holder SH₁. Then, the main control device 50 positions the holding surface of each of the four auxiliary sheet holders SH₂ so as to be located on the slightly lower side (-Z side) of the holding surface of the sheet holder SH₁. Accordingly, an appropriate tension is applied to the sheet S in at least the
15 Y-axis direction, so that the center portion of the sheet S is fixed to the holding surface of the sheet holder SH₁. In this state, the main control device 50 adsorbs and holds the sheet S onto the sheet holder SH₁ as shown in FIG. 32. Accordingly, the center portion of the sheet S including the separate area SA_i is flatly held onto the stage SST so as to be parallel to the XY plane.

20 q. Next, the alignment measurement for the sheet S is performed in accordance with the following sequences q1 to q5.

q1. As described above, in the state where the stage SST is positioned to the standby position, the alignment marks attached to the separate area SA_i are positioned within the detection visual field of each of the alignment systems AL₁ to AL₁₂. Here, as
25 shown in FIG. 33, the main control device 50 detects the alignment marks attached to the

separate area SA_i on the sheet S by using the alignment systems AL_1 to AL_{12} (the positions of the alignment marks are measured on the basis of the index center). In addition, the main control device 50 obtains the position coordinates of twelve alignment marks on the XY coordinate on the basis of the detection result of the alignment marks and the positional information of the stage SST obtained from the stage interferometer system 18 through the detection.

q2. Next, the main control device 50 determines whether the contraction amount inside the separate area SA_i having the pattern of the sheet S in the Y-axis direction is within a predetermined range on the basis of the position coordinates of the twelve alignment marks obtained.

q3. Then, as a result, for example, when it is determined that a contraction in the Y-axis direction exceeding a predetermined range occurs in at least a part inside the separate area SA_i , the operation of adsorbing and holding the sheet S using the sheet holder SH_1 is released, and the auxiliary sheet holder SH_2 is driven through the base 60_1 in the +Z-axis direction so as to separate the rear surface of the sheet S from the holding surface of the sheet holder SH_1 .

Here, for example, when it is determined that the -X end inside the separate area SA_i is contracted more than a predetermined range in the Y-axis direction, as shown in FIG. 34, two auxiliary sheet holders SH_2 on the -X side on the table TB are driven in a direction (depicted by the white arrow in FIG. 34) moving away from each other, so that a tension in the Y-axis direction is further applied to the -X side end of the separate area SA_i of the sheet S and the distortion of the pattern is corrected (adjusted).

After the adjustment, the main control device 50 drives each of the auxiliary sheet holders SH_2 through the base 60_1 in the -Z-axis direction so that the rear surface of the sheet S comes into contact with the holding surface of the sheet holder SH_1 to be

adsorbed and held thereon again.

q4. Then, the main control device 50 detects the alignment marks attached to the separate area SA_i on the sheet S by using the alignment systems AL_1 to AL_{12} , and obtains the position coordinates of twelve alignment marks on the XY coordinates again on the basis of the detection result and the positional information of the stage SST obtained from the stage interferometer system 18 through the detection.

q5. Then, the main control device 50 performs a predetermined calculation of least squares by using all or a part of the position coordinates of the twelve alignment marks, and obtains the distortion, that is, the XY shift, the rotation, the XY scaling, and the perpendicularity of the pattern formed on the separate area SA_i on the sheet S.

Here, when it is determined that no contraction exceeding a predetermined ratio in the Y-axis direction occurs in a part of the inside of the separate area SA_i as a detection result of q2, the main control device 50 skips the processes of q3 and q4, and performs the process of q5.

Subsequently, the main control device 50 releases the operation of fixing the sheet S using the clasper 45.

In addition, when the number of the alignment systems is fewer than the number of the alignment marks to be detected, it is necessary to perform the alignment measurement while stepwisely moving the stage SST holding the sheet S in the X-axis direction. At this time, the main control device 50 controls the rotation and the stopping of each of the driving rollers of the sheet transporting system 40 in accordance with the movement of the stage SST.

r. Next, the scanning exposure for the separate area SA_i on the sheet S is performed.

r1. In detail, the main control device 50 moves the stage SST holding the sheet S

to the scanning start position (acceleration start position) for the exposure on the basis of the result of the alignment measurement, and particularly, the XY shift so as to perform a positioning operation with respect to the mask stage MST holding the mask M. Here, in the embodiment, since the acceleration start position of the stage SST is set to the same position (or the vicinity thereof) as the above-described standby position, the minute adjustment of the position of the stage SST within the XY plane is performed.

r2. Next, the main control device 50 starts the acceleration of the stage SST in the scanning direction (-X-axis direction). Accordingly, the movement of the stage SST in the -X-axis direction is started. During the movement, and particularly, before the acceleration end of the stage SST, as shown in FIG. 35, the length measurement beam from the interferometer 18Y₂ starts to collide with the reflection surface 17Y. Accordingly, immediately after the collision of the length measurement beam, the main control device 50 changes the laser interferometer for measuring the Y position of the stage SST from the interferometer 18Y₁ to the interferometer 18Y₂.

r3. Then, when the acceleration operations of both stages SST and MST end, and the acceleration operations of both stages SST and MST are synchronized with uniform speed, the pattern area on the mask M starts to be illuminated by the illumination light IL₂ and IL₄, thereby starting the exposure. Then, in accordance with the synchronization movement with uniform speed of both stages SST and MST, as shown in FIG. 36, the illumination areas IAM₁ to IAM₅ (refer to FIG. 22) on the mask M are illuminated by the illumination light IL₁ to IL₅, and the partial images of the patterns inside the illumination areas IAM₁ to IAM₅ are projected onto the projection areas IA₁ to IA₅ on the sheet S held on the stage SST through the projection optical systems PL₁ to PL₅ (refer to FIG. 23).

When the entire area of the pattern area of the mask M is illuminated by the

illumination light IL_1 to IL_5 , that is, the pattern area of the mask M passes through the illumination areas IAM_1 to IAM_5 , the scanning exposure for the separate area SA_i is completed. Accordingly, the pattern of the mask M is transferred to the separate area SA_i . That is, a latent image of the pattern of the mask M is formed on the resist layer

5 formed on the surface of the sheet S .

During the scanning exposure, the main control device 50 drives the table TB of the stage SST in the Z -axis direction while horizontally maintaining the table, so that the surface of the sheet S held on the table TB (sheet holder SH_1) is positioned to the focal position (within the focal depth) of the projection optical system PL . In addition, during

10 the scanning exposure, the main control device 50 controls the synchronization driving state (the relative position and the relative speed) of the stage SST and the mask stage MST on the basis of the result of the alignment measurement so as to correct the distortion of the entire image of the pattern projected onto the sheet S . Further, the main control device 50 controls the driving state of the optical element group (lens group)

15 constituting the projection optical systems PL_1 to PL_5 through the lens controller LC so as to correct the distortion of the partial image of the pattern projected onto the projection areas IA_1 to IA_5 on the sheet S . Accordingly, the projection image of the pattern of the mask M is highly precisely overlapped with the pattern formed within the separate area SA_i .

20 After the scanning exposure for the separate area SA_i is completed, both stages SST and MST are decelerated. As shown in FIG. 37, when they arrive at the scanning end position (deceleration end position), they are stopped. In addition, in the embodiment, the deceleration end position of the stage SST during the scanning operation is determined so as to be aligned to the $-X$ end of the base member BS .

25 In addition, when the main control device 50 drives the stage SST holding the

sheet S in the $-X$ -axis direction during the scanning exposure, as described above, the main control device appropriately rotates or stops each of the driving rollers of the sheet transporting system 40 in accordance with the movement of the stage SST so that the movement of the stage SST is not disturbed by a tension applied to the sheet S.

5 s. As shown in FIG. 37, when the stage SST is stopped at the $-X$ end as the deceleration end position in front of the base member BS, the main control device 50 releases the operation of adsorbing and holding the sheet S using the sheet holder SH₁ and the sheet holder SH₂ so as to release the sheet S from the stage SST. Further, the main control device 50 retreats the table TB of the stage SST downward (in the $-Z$ -axis
10 direction). Accordingly, the sheet S is stretched between the transportation roller portions 42 and 43 with a minute space with respect to the sheet holder SH₁ of the stage SST.

 t. After the sheet S is released, as shown in FIG. 38, the main control device 50 drives the sheet stage SST in the $+X$ -axis direction depicted by the black arrow so as to
15 be returned to the above-described standby position of the $+X$ end on the base member BS. Here, in accordance with the X position of the sheet stage SST, the interferometer for measuring the Y position is changed from the interferometer 18Y₂ to the interferometer 18Y₁. In addition, the main control device 50 drives the mask stage MST to return to the scanning start position (acceleration start position) at a high speed.
20 Further, in addition to the operation of driving the stage, the main control device 50 pulls back the sheet S in the $+X$ -axis direction depicted by the white arrow as shown in FIG. 38.

 u. The returning driving operation of the stage SST and the mask stage MST and the operation of pulling back the sheet S are completed, as shown in FIG. 39, the stage
25 SST stays at the standby position, and the center portion of the sheet S including the

subsequent separate area SA_{i+1} is positioned to the surface of the stage SST staying at the standby position. This state is the same as that shown in FIG. 30 except that one separate area of the sheet S has transported.

Subsequently, the main control device 50 starts the exposure for the separate area
5 SA_{i+1} as in the former case. Subsequently, in the same manner, the main control device 50 repeats the above-described sequences p to u so as to perform an exposure for all separate areas on the sheet S.

As described above in detail, the main control device 50 restrains (fixes) the sheet S by sandwiching a portion between the separate area SA_{i+1} and SA_{i+2} of the sheet S
10 using the clasper portion 45 of the sheet transporting system 40 and rotates each of the rollers of the transportation roller portion 43 in the state where the rotation of each of the rollers of the transportation roller portions 41, 42, and 44 is stopped, so that a predetermined tension is applied to the sheet S in the X-axis direction so as to be stretched between the clasper portion 45 and the transportation roller portion 43. Then,
15 after the sheet S is temporarily held by four auxiliary sheet holders SH_2 , the four auxiliary sheet holders SH_2 temporarily holding the sheet S are minutely driven in the $-Z$ direction by the main control device 50, so that the rear surface of the center portion of the sheet S including the separate area SA_i comes into contact with the holding surface of the sheet holder SH_1 . Then, the holding surfaces of four auxiliary sheet holders SH_2 are
20 positioned on the slightly lower side ($-Z$ side) of the holding surface of the sheet holder SH_1 by the main control device 50, so that an appropriate tension is applied to the sheet S in the width direction (Y-axis direction) and the center portion of the sheet S is fixed to the holding surface of the sheet holder SH_1 . That is, in the state where an XY two-dimensional tension is applied to the separate area SA_i of the sheet S, the rear
25 surface portion corresponding to the separate area SA_i of the sheet S is changed in

accordance with the flat shape of the holding surface of the sheet holder SH₁. Then, the illumination system IOP illuminates the illumination light IL₁ to IL₅ to the separate area SA_i of the flattened sheet S through the pattern of the mask M, so that the sheet S is scan-exposed and a pattern is formed thereon. Accordingly, even in the case of the sheet S becoming contracted by, for example, heat generated during a treatment of a process, it is possible to perform the exposure with high precision. Therefore, it is possible to contribute to the production of an electronic device such as a flexible large-size display without increasing the size of the device.

In addition, in the exposure device 1000 of the above-described embodiment, the alignment measurement for the sheet S is performed by using the alignment systems AL₁ to AL₁₂ which are distant from each other in the Y-axis direction and are arranged along the X-axis direction. However, the present invention is not limited thereto. For example, the alignment marks can be disposed in the periphery of the separate area SA_i on the sheet S at a predetermined interval therebetween, the alignment systems can be disposed so as to correspond to the peripheral portion of the separate area SA_i in accordance with the arrangement of the alignment marks as shown in FIG. 40, and all the alignment marks can be simultaneously detected. In this case, when it is detected that the separate area SA_i is decreased in the X-axis direction on the basis of the measurement result of the alignment marks, the scaling error in the X-axis direction of the separate area can be adjusted in such a manner that the main control device 50 applies a tension to the sheet S in the X-axis direction by using the clamber portion 45 and the transportation roller portion 43.

Further, in the above-described embodiments, a case has been exemplified in which the sheet S having patterns formed in a plurality of separate areas is set as the exposure target, and the second layer exposure is performed by the exposure device 100,

1000, but the present invention is not limited thereto. Of course, the first exposure can be performed by the exposure device 100, 1000 by setting the unexposed sheet S as the exposure target.

Further, in the above-described embodiments, a case has been described in which
5 the stage SST and the mask stage MST are scan-driven in the $-X$ -axis direction so as to perform the scanning exposure (called a minus scan exposure) on the sheet S. However, in addition to this case, a configuration can be adopted in which the stage SST and the mask stage MST are scan-driven in the $+X$ -axis direction so as to perform the scanning exposure (plus scan exposure) on the sheet S. Then, the minus scan exposure and the
10 plus scan exposure can be alternately repeated so as to perform the exposure on a plurality of separate areas SA_{k-1} , SA_k , SA_{k+1} , ... on the sheet S. With such a configuration, it is not necessary to rewind the mask stage MST and the stage SST. In this case, it is desirable to further provide clampers on the $+X$ sides of the transportation roller portions 43 and 44 in order to hold the sheet S on the stage SST at the $-X$ end on
15 the base member BS. In addition, it is desirable to dispose the alignment system on the $-X$ side of the projection optical system PL.

Further, in the above-described embodiments, a configuration is adopted in which only one stage SST is used, but a configuration can be adopted in which the rear surfaces of the separate areas of the exposure target of the sheet are sequentially adsorbed and
20 held by using two or more stages. In this case, in the stage, the stage device SS can be configured so as to orbit a closed path including the scanning exposure section on the base member. Accordingly, after the exposure for one separate area is completed, the used stage can be retreated to a position outside the exposure section, and another stage can be used to promptly start the exposure for the next separate area. In addition, a
25 configuration can be adopted in which a plurality of sheets is simultaneously subjected to

the exposure by using a plurality of stages.

Further, in the exposure device of the above-described embodiments, the auxiliary sheet holder is provided on the upper surface of the stage (table) so as to be minutely driven in the Z-axis direction. However, instead of or in addition to this configuration, the sheet holder can be adapted to be minutely movable in the Z-axis direction. Accordingly, the sheet holder and the auxiliary sheet holder temporarily holding the sheet are relatively moved in the Z-axis direction so as to attach or detach the sheet to or from the stage (sheet holder). In addition, in the above-described embodiments, the transportation roller portion included in the sheet transporting system 40 can be adapted to be elevated in the Z-axis direction. Accordingly, the transportation roller portion having the sheet stretched thereon can be elevated so as to attach or detach the sheet to or from the stage (sheet holder).

Further, in the above-described embodiments, a case has been exemplified in which the stage SST is dissymmetric with respect to the Y axis passing the center, but the present invention is not limited thereto. Of course, a stage can be used which is symmetric with respect to the X axis and the Y axis passing the center. In this case, since it is not possible to measure the position of the stage using the interferometer 18Y₂ immediately after the scanning exposure is completed, it is desirable to provide a measurement device for measuring the Y position thereof.

Further, in the above-described embodiments, the interferometer system 18 is adopted as the position measurement system of the stage SST, but instead of the interferometer system, an encoder (or an encoder system including a plurality of encoders) can be adopted. Alternatively, the interferometer system 18 and the encoder can be simultaneously used. In addition, the interferometer system is adopted as the position measurement system of the mask stage, but instead of the interferometer system,

an encoder (or an encoder system including a plurality of encoders) can be adopted.

Alternatively, the interferometer system and the encoder can be simultaneously used.

Further, in the exposure device 100, 1000 of the above-described embodiments, the multi-lens type projection optical system of the same magnification is used, but the present invention is not limited thereto. For example, the magnification multi-lens type projection optical system disclosed in the specification or the like of US Patent Application Publication No. 2008/0165334 can be used. In addition, of course, the projection optical system is not limited to the multi-lens type. Further, the projection optical system is not limited to the same magnification system and the magnification system, but can be the reduction system. The projection optical system is not limited to the reflection-refraction system, but can be the refraction system and the reflection system. The projection image can be any one of the erected image or the inverted image.

In addition, as the light source of the exposure device 100, 1000, in addition to the ultra high pressure mercury lamp for emitting an emission line such as a line i (having a wavelength of 365 nm), a line g (having a wavelength of 436 nm), or a line h (having a wavelength of 405 nm), solid-state laser (for example, triple harmonics of YAG laser: a wavelength of 355 nm), KrF excimer laser (248 nm), ArF excimer laser (193 nm), and F₂ laser (157 nm) can be used.

Further, in the above-described embodiments, a case has been exemplified in which a light transmission type mask having a predetermined light shielding pattern (or a phase pattern/dimming pattern) formed on a light transmission type substrate is used, and the pattern of the mask is projected onto the sheet through the projection optical system. However, the present invention is not limited thereto. By using an SLM (Spatial Light Modulator) as an element for spatially modulating the amplitude (intensity), the phase, or

the polarization state of light traveling in a predetermined direction, for example, a reflection type spatial light modulator, that is, a light non-emission type image display element, for example, a DMD (Digital Micro-mirror Device), a reflection type liquid crystal display element, an EPD (Electro Phonetic Display), an electronic paper (an electronic ink), a grating light valve, and the like instead of the mask, an electronic mask (called a variable molding mask, an active mask, or an image generator) for forming a transmission pattern, a reflection pattern, or a light emission pattern on the basis of electronic data of the pattern can be used. Such an electronic mask is disclosed in, for example, the specification of US Patent No. 6,778,257. In addition, an electronic mask can be used which uses a transmission type spatial modulator such as an LCD (Liquid Crystal Display) and an ECD (Electrochromic Display). For example, in the case of using an electronic mask such as a DMD, an energy beam corresponding to a pattern to be formed on a sheet material is projected from the electronic mask onto the sheet material through a projection optical system, and an image corresponding to the pattern is formed on the sheet material. In this case, when the projection optical system is not used, the energy beam corresponding to the pattern is illuminated onto the sheet by the electronic mask, and the pattern is formed on the sheet.

The exposure device is not limited to the exposure device for the liquid crystal display element. For example, the exposure device can be widely applied to the exposure devices for manufacturing a flexible display as an organic EL display element, an electronic paper, a printed interconnection substrate, and the like.

In addition, the device for forming a pattern on the sheet is not limited to the above-described exposure device (lithography system), but for example, the present invention can be applied to a device for forming a pattern on a sheet through an ink jet method. In this case, instead of arranging the plurality of projection optical systems PL₁

to PL₅ along the Y-axis direction, a plurality of ink jet heads (or one large ink jet head) can be arranged along the Y-axis direction.

<Device Manufacturing Method>

By forming a predetermined pattern on a sheet using the exposure device of the
5 above-described embodiment, it is possible to manufacture a liquid crystal display element as an example of an electronic device.

[Pattern Forming Process]

First, by using the exposure device of above-described embodiments, a so-called optical lithography process is performed in which an image corresponding to the pattern
10 to be formed on the sheet is sequentially formed on the sheet coated with a resist through the projection optical system. By means of the optical lithography process, a predetermined pattern including a plurality of electrodes is formed on the sheet. Subsequently, the exposed sheet is subjected to respective processes such as a developing process, an etching process, and a resist separation process so that a predetermined
15 pattern is formed on the sheet.

[Color Filter Forming Process]

Next, a color filter having a plurality of three sets of dots corresponding to R (Red), G (Green), and B (Blue) arranged thereon in a matrix shape or a color filter having a plurality of three pairs of stripes of R, G, and B arranged in a horizontal scanning
20 direction is formed.

[Cell Assembling Process]

After the color filter forming process, a cell assembling process is performed in which a liquid crystal cell is assembled by using a sheet having a predetermined pattern obtained in the pattern forming process and the color filter obtained in the color filter
25 forming process. In the cell assembling process, for example, a liquid crystal panel

(liquid cell) is manufactured by injecting a liquid crystal between the sheet having a predetermined pattern obtained in the pattern forming process and the color filter obtained in the color filter forming process.

[Module Assembling Process]

5 Subsequently, components such as an electric circuit and a backlight for performing a display operation of the assembled liquid crystal cell are installed to complete as a liquid crystal display element. Accordingly, in the pattern forming process of the method of manufacturing the micro device, it is possible to highly precisely form a pattern image having a desired line width at a desired position, and thus
10 to manufacture the liquid crystal display element with a good yield.

 In addition, the exposure device and the exposure method of the above-described embodiments are suitable for manufacturing a flexible electronic device (micro device) and a flexible display. For example, in the first embodiment, the manufacture line for manufacturing the electronic device can be configured in such a manner that a resist
15 coating device for coating a resist on the surface of the sheet S is disposed between the roller 40₁ and the exposure device 100, 1000, and a developing device for developing the sheet S having a pattern formed thereon is disposed between the exposure device 100, 1000 and the winding roller 40₂ in the longitudinal direction of the sheet.

 Further, in general, the electronic device including at least a part of the sheet S
20 can be manufactured in such a manner that a pattern is formed on the sheet S using the exposure device and the exposure method of the above-described embodiment, and the sheet S having a pattern formed thereon is processed on the basis of the pattern. Here, in the process of the sheet S on the basis of the formed pattern, a process of developing, etching, or printing the sheet S on the basis of the formed pattern can be appropriately
25 applied. In addition, as the printing process, for example, a predetermined material

such as conductive ink can be coated on the sheet S on the basis of the formed pattern.

Further, as the printing process, a layer of a functional material (for example, a material having a variable property such as a water-repellent property, a hydrophilic property, or a hydrophobic property due to the irradiation of UV light) is formed in advance on the

5 sheet S, an exposure pattern is formed on the layer of the functional material, and a material such as conductive ink is coated on the sheet S in accordance with the formed exposure pattern.

The exposure device and the exposure method according to the present invention are suitable for forming a pattern on an elongated sheet. In addition, the device
10 manufacturing method according to the present invention is suitable for manufacturing an electronic device (micro device).

CLAIMS

1. A pattern forming device for forming a predetermined pattern in a predetermined area of an elongated sheet material, the pattern forming device comprising:

5 a tension applying device which applies a two-dimensional tension to a portion including the predetermined area of the sheet material;

an adsorption device which includes a reference surface member having a flat reference surface and allows the reference surface to adsorb a rear surface portion corresponding to the predetermined area of the sheet material applied with the

10 two-dimensional tension; and

an illumination device which illuminates an energy beam corresponding to the pattern to the predetermined area of the sheet material adsorbed to the reference surface.

2. The pattern forming device according to claim 1,

15 wherein the tension applying device includes a plurality of adsorbing-holding members which adsorbs a rear surface portion on the outside of the predetermined area of the sheet material, and

wherein the plurality of adsorbing-holding members is provided in the periphery of the reference surface member so as to be relatively movable along a two-dimensional
20 plane parallel to the reference surface member.

3. The pattern forming device according to claim 2,

wherein the plurality of adsorbing-holding members includes at least a pair of first adsorbing-holding members, at least one of which is provided on each of one side
25 and the other side in a direction parallel to a second axis perpendicular to a first axis

parallel to the longitudinal direction across the reference surface member on the stage and which is movable in a direction parallel to at least the second axis.

4. The pattern forming device according to claim 3,

5 wherein the tension applying device includes a driving system which individually drives a part of the plurality of adsorbing-holding members including at least the pair of first adsorbing-holding members among the plurality of adsorbing-holding members, and

wherein the driving system includes a parallel link which is provided for each of a part of the plurality of adsorbing-holding members and a driving device which drives

10 the parallel link.

5. The pattern forming device according to any one of claims 2 to 4, further comprising:

a changing device which drives at least one of the plurality of adsorbing-holding
15 members and the reference surface member in a direction perpendicular to the two-dimensional plane so as to be capable of changing a relative position between the plurality of adsorbing-holding members and the reference surface member in a direction perpendicular to the two-dimensional plane.

20 6. The pattern forming device according to claim 5,

wherein the changing device changes the relative position by allowing the reference surface member to come into contact with the rear surface portion corresponding to the predetermined area of the sheet material of which a corresponding rear surface portion on the outside of the predetermined area is held by the plurality of
25 adsorbing-holding members.

7. The pattern forming device according to any one of claims 1 to 6, further comprising:

a sheet transporting device which includes at least two driving rollers provided to
5 be distant from each other in the longitudinal direction of the sheet material and rotating while coming into contact with the sheet material, and transports the sheet material in the longitudinal direction,

wherein the tension applying device applies a tension to the sheet material in the longitudinal direction by stopping the rotation of the driving roller located on the
10 downstream side of the transportation direction of the sheet material during the transportation of the sheet material.

8. The pattern forming device according to claim 7, further comprising:

a clamp device which temporarily stops the transportation of the sheet material by
15 sandwiching the sheet material using a pair of clamp members during the transportation of the sheet material using the driving rollers.

9. The pattern forming device according to claim 8,

wherein the clamp device sandwiches a portion on the outside of the
20 predetermined area of the sheet material.

10. The pattern forming device according to any one of claims 7 to 9,

wherein the sheet transporting device includes a plurality of rollers which includes the driving rollers with coming into contact with a front surface or a rear surface
25 of the sheet material, and the roller located on the front surface of the sheet material only

comes into contact with both side portions of the predetermined area of the sheet material in a direction perpendicular to the longitudinal direction.

11. The pattern forming device according to any one of claims 1 to 10, further
5 comprising:

a mark detecting system which detects a plurality of marks on the sheet material;

and

a control device which detects at least a part of a plurality of positioning marks
attached to the predetermined area on the sheet material by using the mark detecting
10 system so as to correct the two-dimensional tension applied to the portion including the
predetermined area of the sheet material by the tension applying device on the basis of
the detection result.

12. The pattern forming device according to claim 11, further comprising:

15 a projection optical system which projects an energy beam corresponding to the
pattern to the sheet material so as to form an image of the pattern on the sheet material;
and

an adjustment device which adjusts an optical characteristic of the projection
optical system,

20 wherein the control device detects at least a part of the plurality of positioning
marks attached to the predetermined area on the sheet material by using the mark
detecting system so as to control at least one of the adjustment device and the tension
applying device on the basis of the detection result.

25 13. A pattern forming method of forming a predetermined pattern in a predetermined

area of an elongated sheet material, the pattern forming method comprising:

applying a two-dimensional tension to a portion including the predetermined area of the sheet material;

allowing a flat reference surface to adsorb a rear surface portion corresponding to the predetermined area of the sheet material applied with the two-dimensional tension;
5 and

illuminating an energy beam corresponding to the pattern to the predetermined area of the sheet material adsorbed to the reference surface.

10 14. The pattern forming method according to claim 13, further comprising:

transporting the sheet material in the longitudinal direction by using at least two driving rollers provided to be distant from each other in the longitudinal direction of the sheet material and rotating while coming into contact with the sheet material,

wherein when the two-dimensional tension is applied to the sheet material, the tension is applied to the sheet material in the longitudinal direction by stopping the
15 rotation of the driving roller located on the downstream side of the transportation direction of the sheet material during the transportation of the sheet material.

15. The pattern forming method according to claim 14, further comprising:

20 sandwiching a portion on the outside of the predetermined area of the sheet material using a pair of clamp members during the transportation of the sheet material using the driving rollers so as to temporarily stop the transportation of the sheet material.

16. The pattern forming method according to any one of claims 13 to 15, further
25 comprising:

detecting at least a part of a plurality of positioning marks attached to the predetermined area on the sheet material so as to correct the two-dimensional tension on the basis of the detection result.

- 5 17. The pattern forming method according to any one of claims 13 to 15, further comprising:

projecting the energy beam corresponding to the pattern to the sheet material through a projection optical system so as to form an image of the pattern on the sheet material; and

- 10 detecting at least a part of the plurality of positioning marks attached to the predetermined areas on the sheet material so as to adjust at least one of an optical characteristic of the projection optical system and the two-dimensional tension on the basis of the detection result.

- 15 18. A device manufacturing method comprising:

forming a pattern on an elongated sheet material by using the pattern forming method according to any one of claims 13 to 17; and

performing a process on the sheet material having the pattern formed thereon.

- 20 19. A pattern forming method of forming a predetermined pattern in a predetermined area of a surface of an elongated sheet material, the pattern forming method comprising:

restraining at least two positions of the sheet material in the longitudinal direction so as to apply a first tension to the predetermined area in the longitudinal direction;

- 25 restraining both sides of the sheet material in the width direction intersecting the longitudinal direction of the sheet material so as to apply a second tension to the

predetermined area in the width direction;

allowing a rear surface portion corresponding to the predetermined area of the sheet material to change in accordance with a flat reference surface in the state where the first and second tensions are applied to the predetermined area; and

5 illuminating an energy beam corresponding to the pattern to the predetermined area of the flattened sheet material.

20. The pattern forming method according to claim 19,

10 wherein in order to apply the first tension to the sheet material, when the sheet material is transported in the longitudinal direction by using at least two driving rollers provided to be distant from each other in the longitudinal direction of the sheet material and rotating while coming into contact with the sheet material, the rotation of the driving roller located on the upstream side of the transportation direction of the sheet material is stopped.

15

21. The pattern forming method according to claim 19,

15 wherein in order to apply the first tension to the sheet material, when the sheet material is transported in the longitudinal direction by using a driving roller rotating while coming into contact with the sheet material, the transportation of the sheet material is temporarily stopped by sandwiching the sheet material by using a pair of clamp members.

20

22. The pattern forming method according to any one of claims 19 to 21,

25 wherein in order to apply the second tension to the sheet material, a rear surface portion on the outside of the predetermined area of the sheet material is adsorbed by

using a plurality of adsorbing-holding members, at least one of which is provided on one side and the other side in a direction parallel to a second axis perpendicular to a first axis parallel to the longitudinal direction across the reference surface member, and the plurality of adsorbing-holding members is mutually relatively moved along a direction
5 parallel to the second axis.

23. The pattern forming method according to any one of claims 19 to 22, further comprising:

detecting at least a part of a plurality of positioning marks attached to the
10 predetermined area on the sheet material so as to correct the first and second tensions on the basis of the detection result.

24. The pattern forming method according to any one of claims 19 to 23, further comprising:

15 projecting the energy beam corresponding to the pattern to the sheet material through a projection optical system so as to form an image of the pattern on the sheet material; and

detecting at least a part of the plurality of positioning marks attached to the predetermined area on the sheet material so as to adjust at least one of the first and
20 second tensions and an optical characteristic of the projection optical system on the basis of the detection result.

25. A device manufacturing method comprising:

forming a pattern on an elongated sheet material by using the pattern forming
25 method according to any one of claims 19 to 24; and

performing a process on the sheet material having the pattern formed thereon.

26. A pattern forming device for forming a predetermined pattern in a predetermined area of a surface of an elongated sheet material, the pattern forming device comprising:

5 a first tension applying device which restrains at least two positions of the sheet material in the longitudinal direction so as to apply a first tension to the predetermined area in the longitudinal direction;

a second tension applying device which restrains both sides of the sheet material in the width direction intersecting the longitudinal direction of the sheet material so as to
10 apply a second tension to the predetermined area in the width direction;

a flattening device which includes a reference surface member having a flat reference surface, and allows a rear surface portion corresponding to the predetermined area of the sheet material to change in accordance with the reference surface in the state where the first and second tensions are applied to the predetermined area; and

15 an illumination device which illuminates an energy beam corresponding to the pattern to the predetermined area of the flattened sheet material.

27. The pattern forming device according to claim 26,

wherein the first tension applying device includes at least two driving rollers
20 which are provided to be distant from each other in the longitudinal direction of the sheet material and which rotate while coming into contact with the sheet material so as to transport the sheet material in the longitudinal direction, and applies the first tension to the sheet material by stopping the rotation of the driving roller located on the upstream side of the transportation direction of the sheet material during the transportation of the
25 sheet material.

28. The pattern forming device according to claim 26,

wherein the first tension applying device includes a driving roller which rotates while coming into contact with the sheet material so as to transport the sheet material in the longitudinal direction, and a clamp device which temporarily stops the transportation of the sheet material by sandwiching the sheet material by using a pair of clamp members during the transportation of the sheet material by using the driving roller.

29. The pattern forming device according to any one of claims 26 to 28,

wherein the second tension applying device includes a plurality of adsorbing-holding members which adsorbs a rear surface portion on the outside of the predetermined area of the sheet material, and

wherein at least one of the plurality of adsorbing-holding members is provided on each of one side and the other side in a direction parallel to a second axis perpendicular to a first axis parallel to the longitudinal direction across the reference surface member so as to be relatively movable along a direction parallel to the second axis.

30. The pattern forming device according to claim 29,

wherein the plurality of adsorbing-holding members is provided on at least one side or the other side in a direction parallel to the second axis across the reference surface member .

31. The pattern forming device according to claim 29 or 30,

wherein the second tension applying device includes a driving system which drives the adsorbing-holding members; and

wherein the driving system includes a parallel link and a driving device which drives the parallel link.

32. The pattern forming device according to any one of claims 29 to 31, further
5 comprising:

a changing device which drives at least one of the pair of adsorbing-holding members and the reference surface member in a direction perpendicular to the two-dimensional plane so as to be capable of changing a relative position between at least the pair of adsorbing-holding members and the reference surface member in a
10 direction perpendicular to the two-dimensional plane.

33. The pattern forming device according to claim 32,
wherein the flattening device changes the relative position between at least the pair of adsorbing-holding members and the reference surface member in a direction
15 perpendicular to the two-dimensional plane through the changing device so as to allow the reference surface member to come into contact with the rear surface portion corresponding to the predetermined area of the sheet material of which the rear surface is held by at least the pair of adsorbing-holding members.

20 34. The pattern forming device according to any one claims 26 to 33, further comprising:

a mark detecting system which detects a plurality of marks on the sheet material;
and

a control device which detects at least a part of a plurality of positioning marks
25 attached to the predetermined area on the sheet material by using the mark detecting

system so as to correct the tension applied to the portion including the predetermined area of the sheet material by the first and second tension applying devices on the basis of the detection result.

- 5 35. The pattern forming device according to claim 34, further comprising:
 a projection optical system which projects an energy beam corresponding to the
 pattern to the sheet material so as to form an image of the pattern on the sheet material;
 and
 an adjustment device which adjusts an optical characteristic of the projection
10 optical system,
 wherein the control device detects at least a part of the plurality of positioning
 marks attached to the predetermined area on the sheet material by using the mark
 detecting system so as to control at least one of the adjustment device and the first and
 second tension applying devices on the basis of the detection result.

15

36. A device manufacturing method comprising:
 forming a pattern on an elongated sheet material by using the pattern forming
 device according to any one of claims 26 to 35; and
 performing a process on the sheet material having the pattern formed thereon.

2/30

FIG. 2

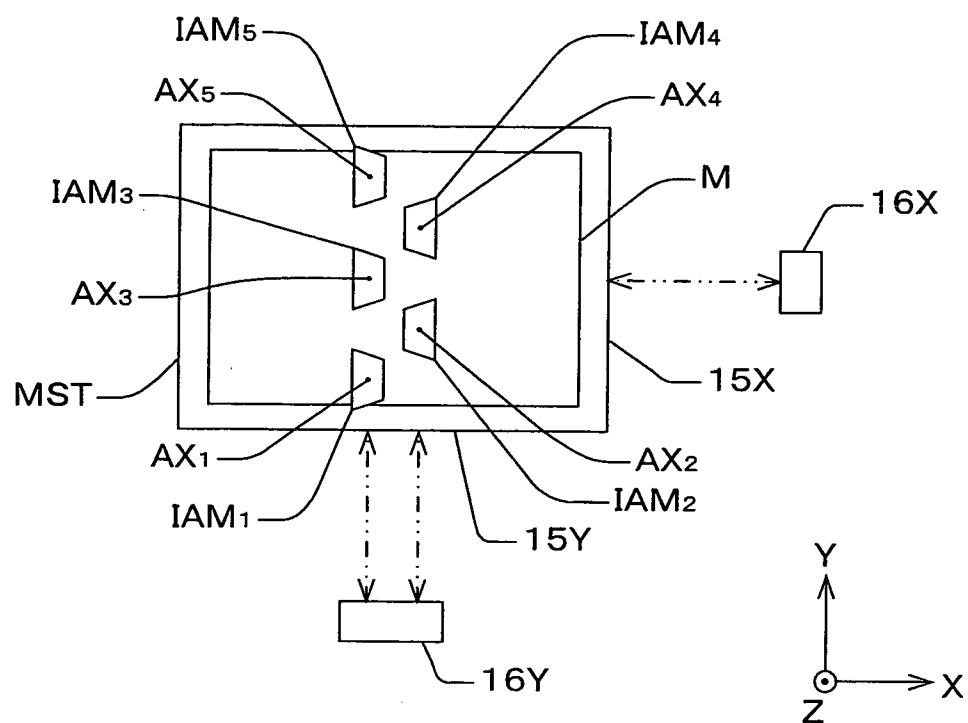
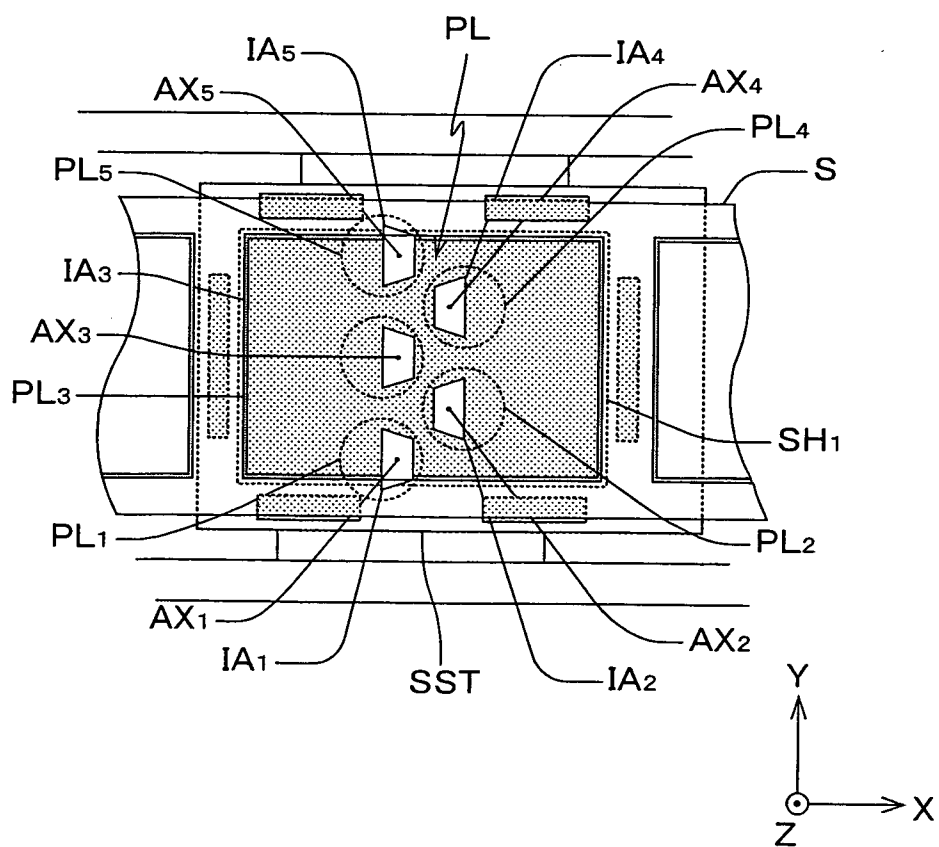


FIG. 3



3/30

FIG. 4A

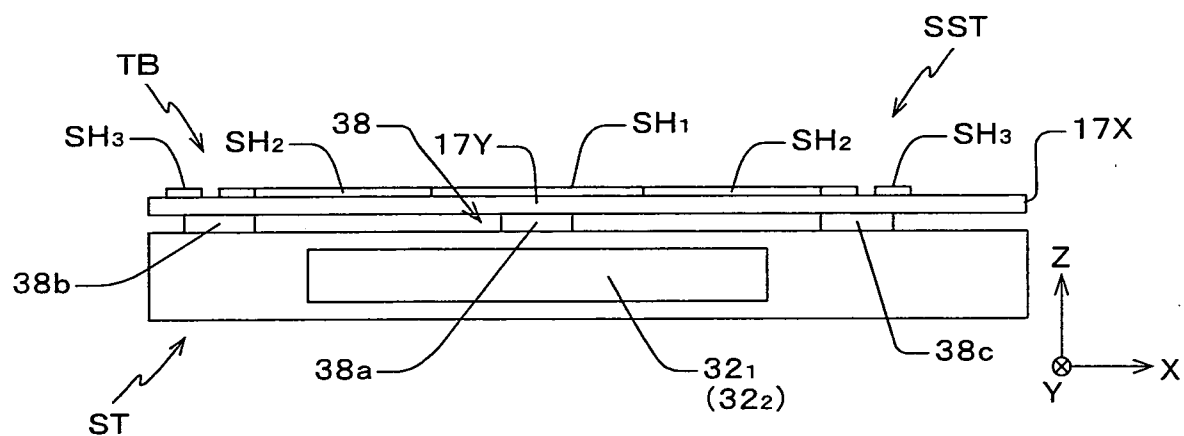


FIG. 4B

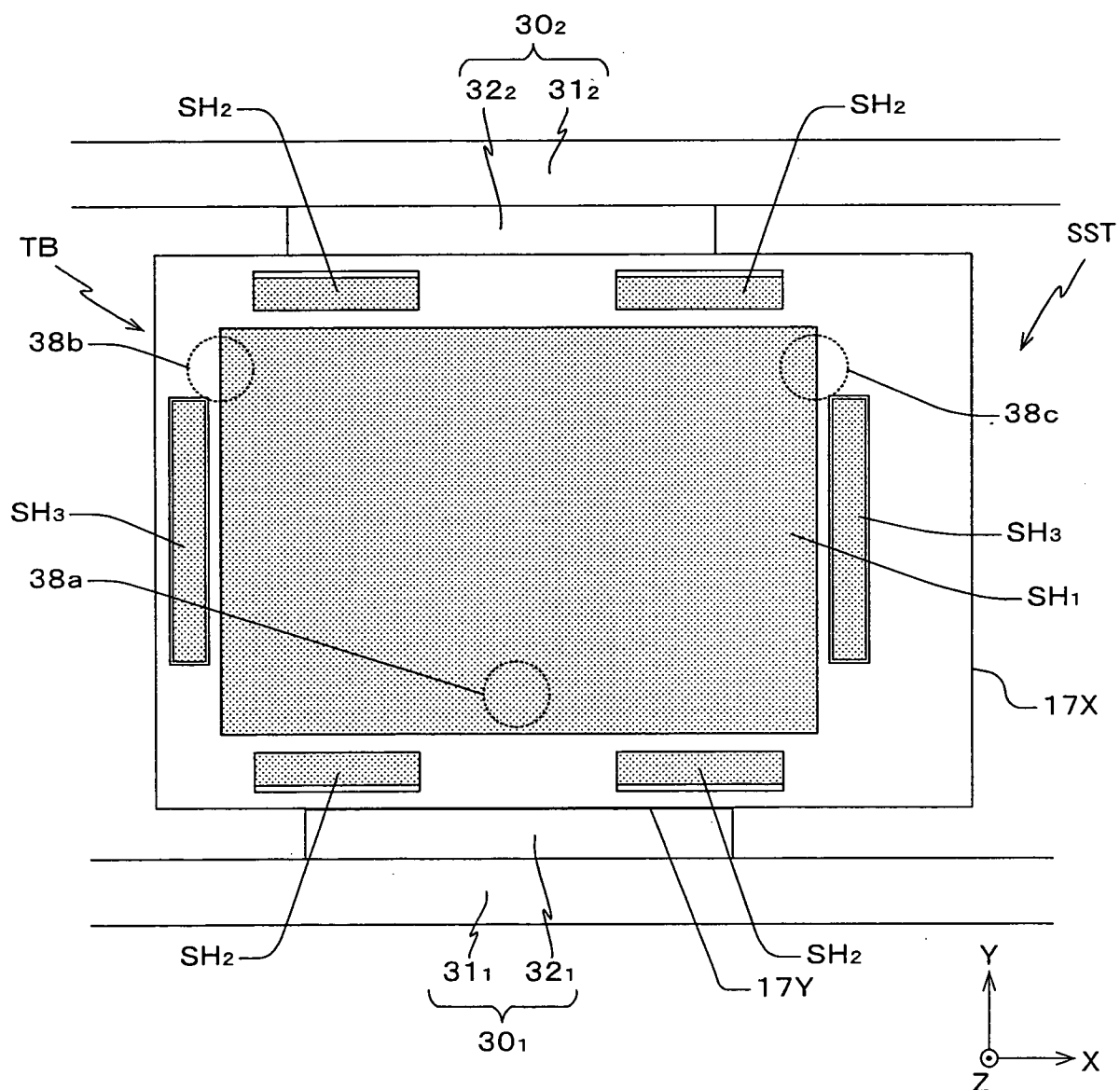


FIG. 5A

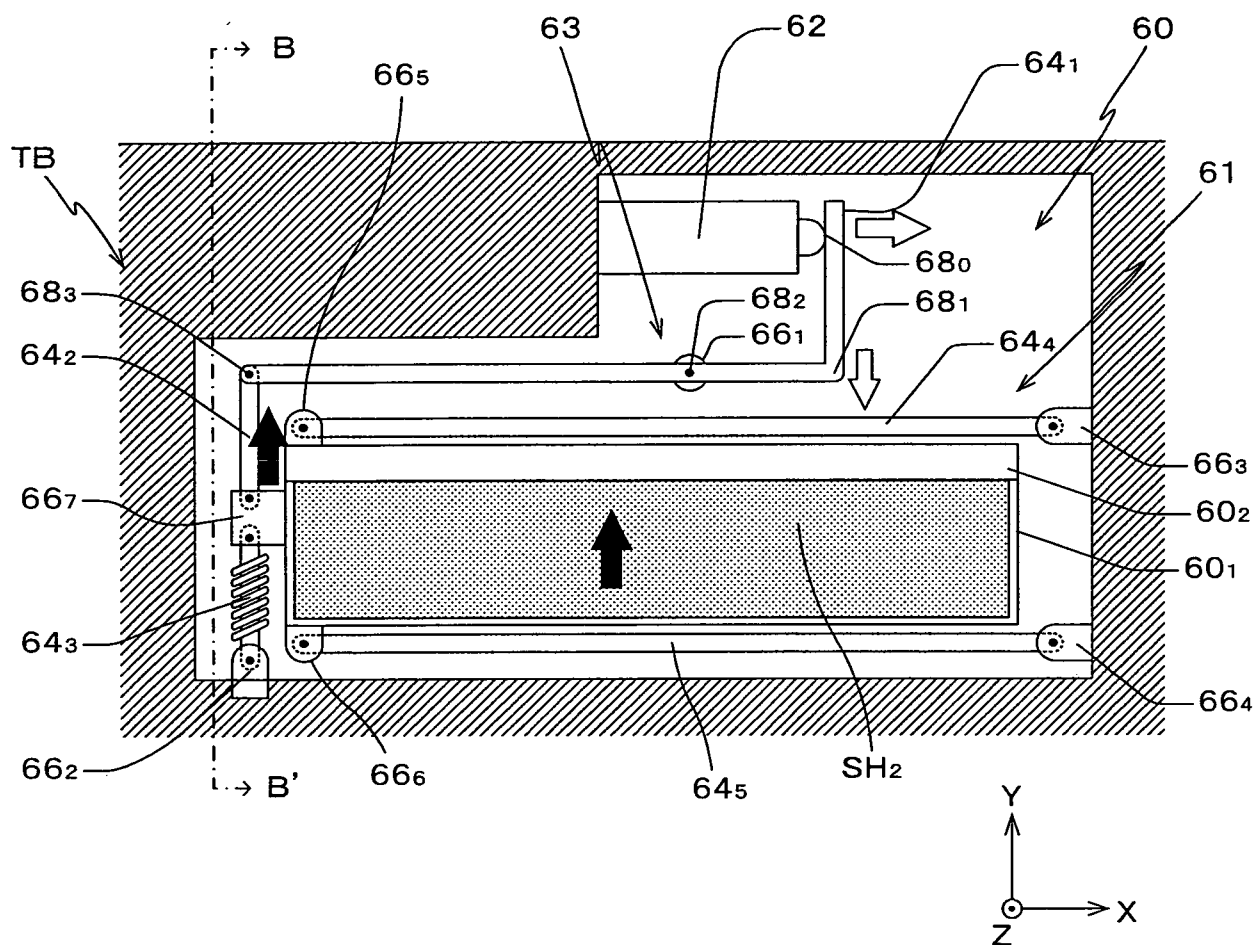


FIG. 5B

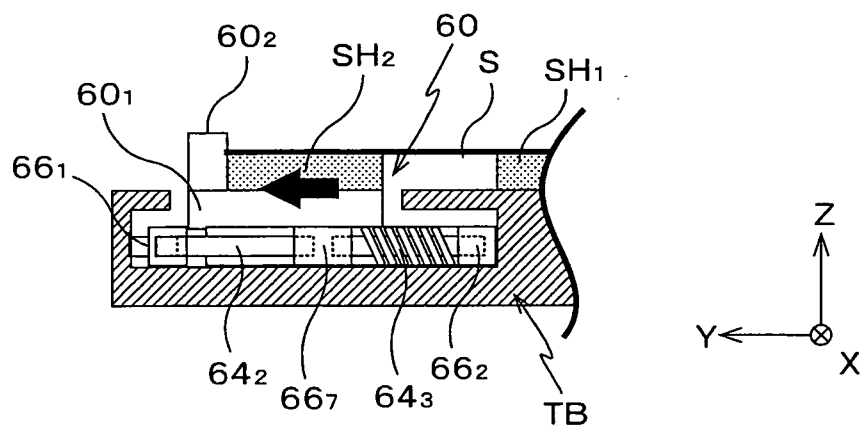


FIG. 6

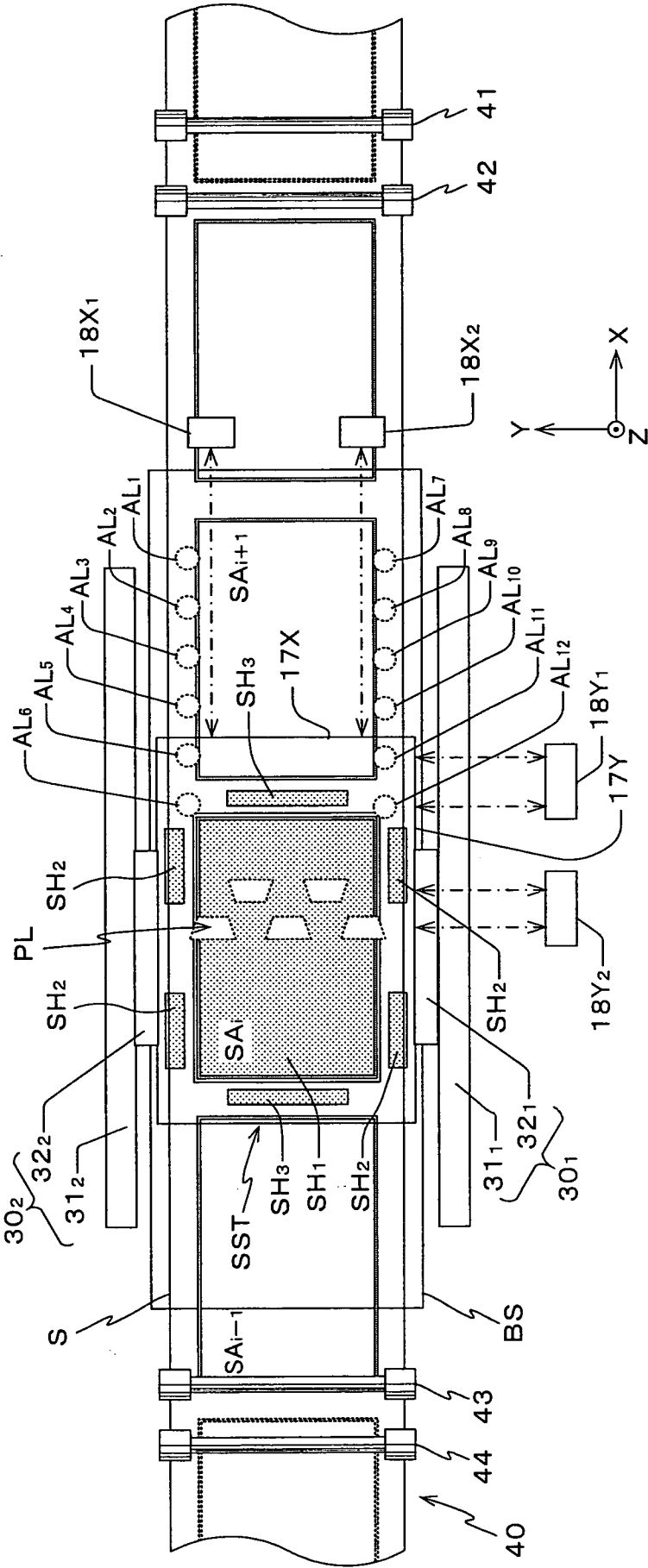


FIG. 7A

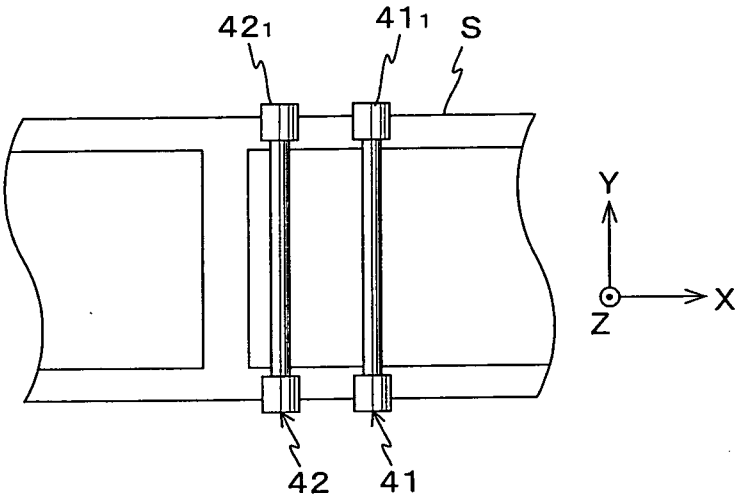


FIG. 7B

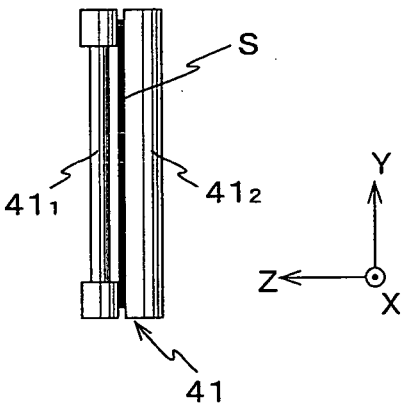


FIG. 7C

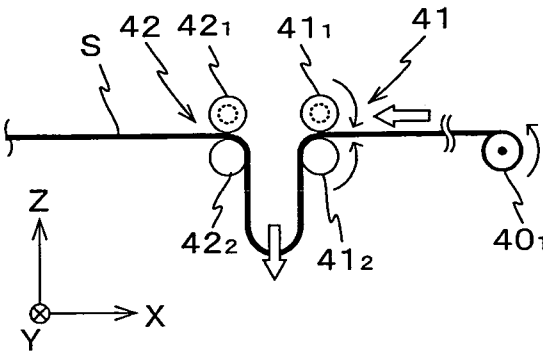


FIG. 7D

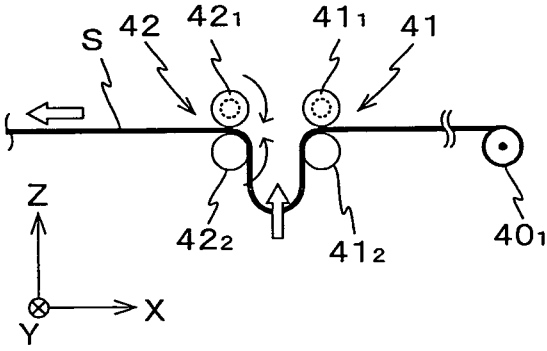


FIG. 7E

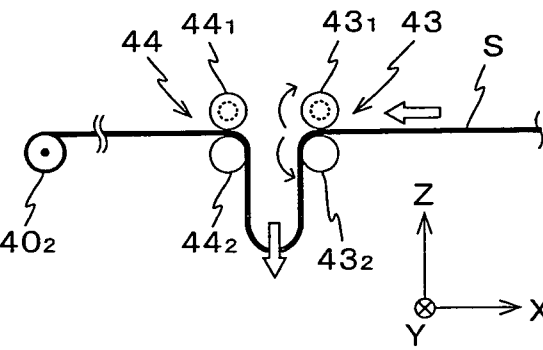


FIG. 7F

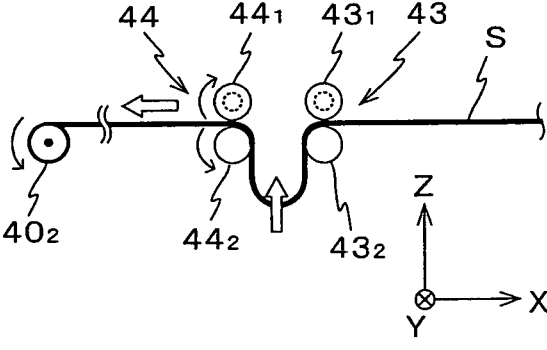
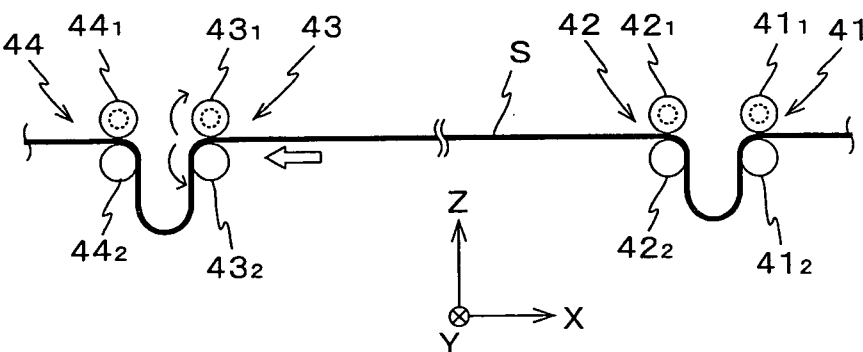
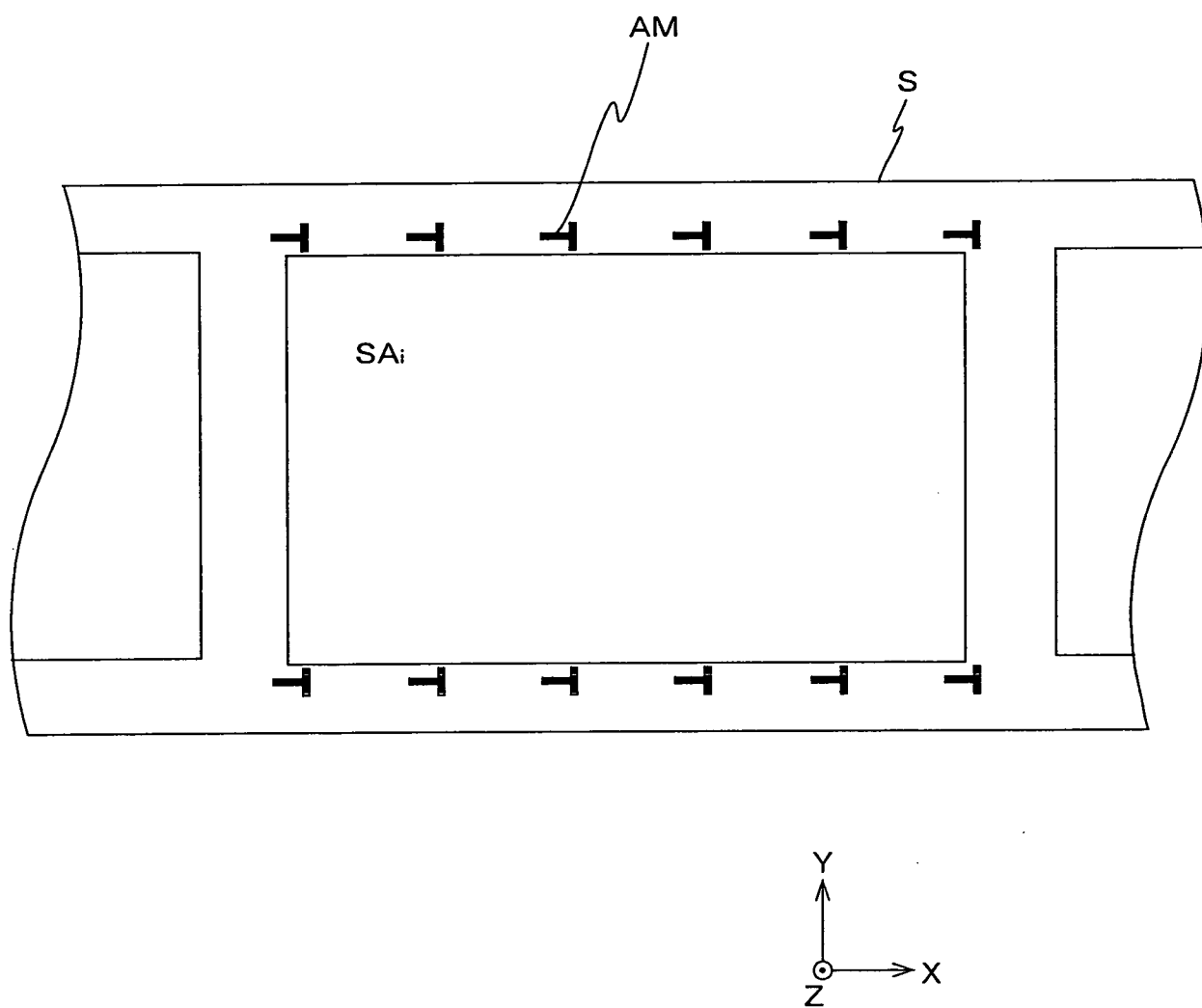


FIG. 7G



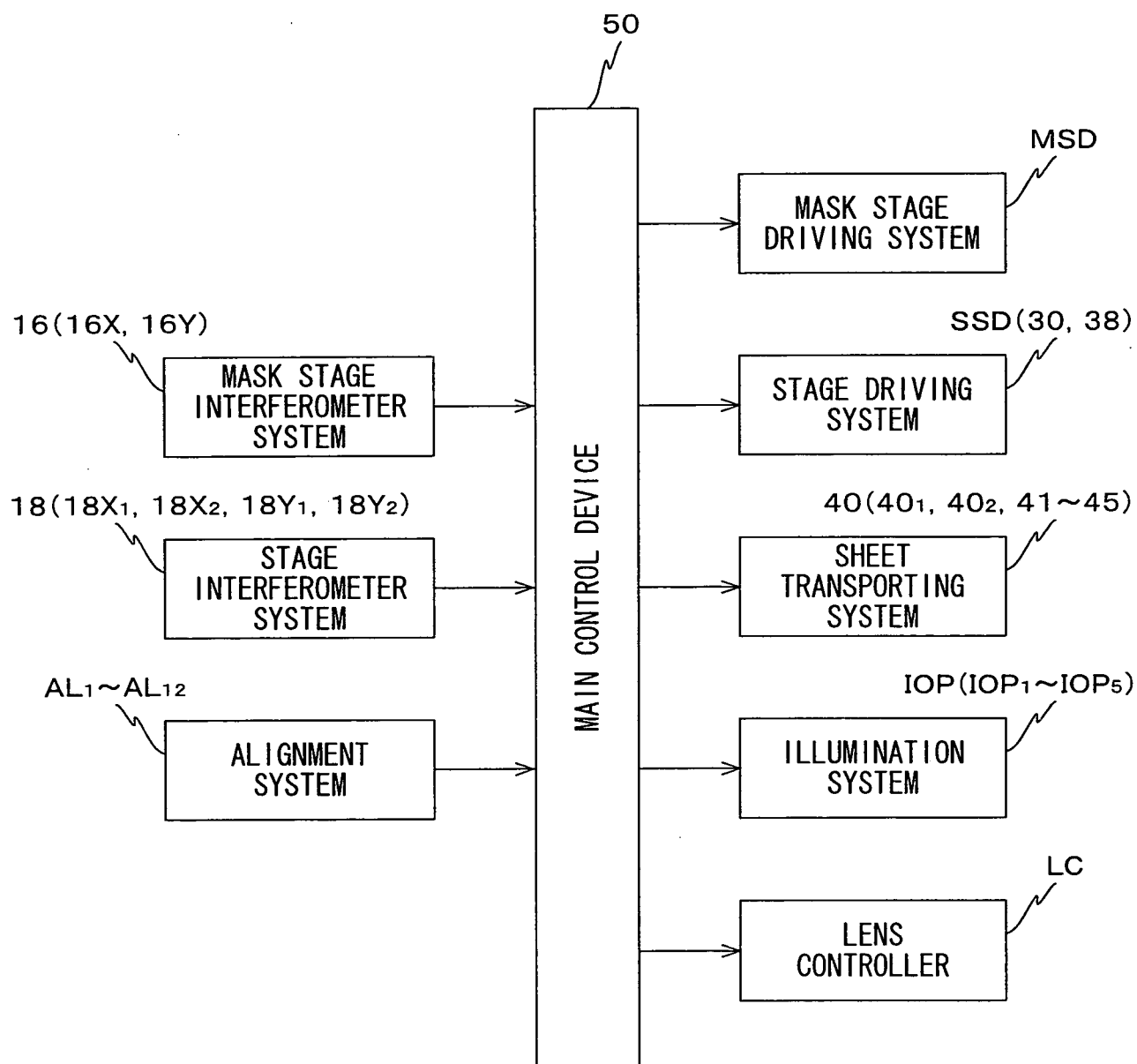
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FIG. 8



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FIG. 9



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FIG. 10

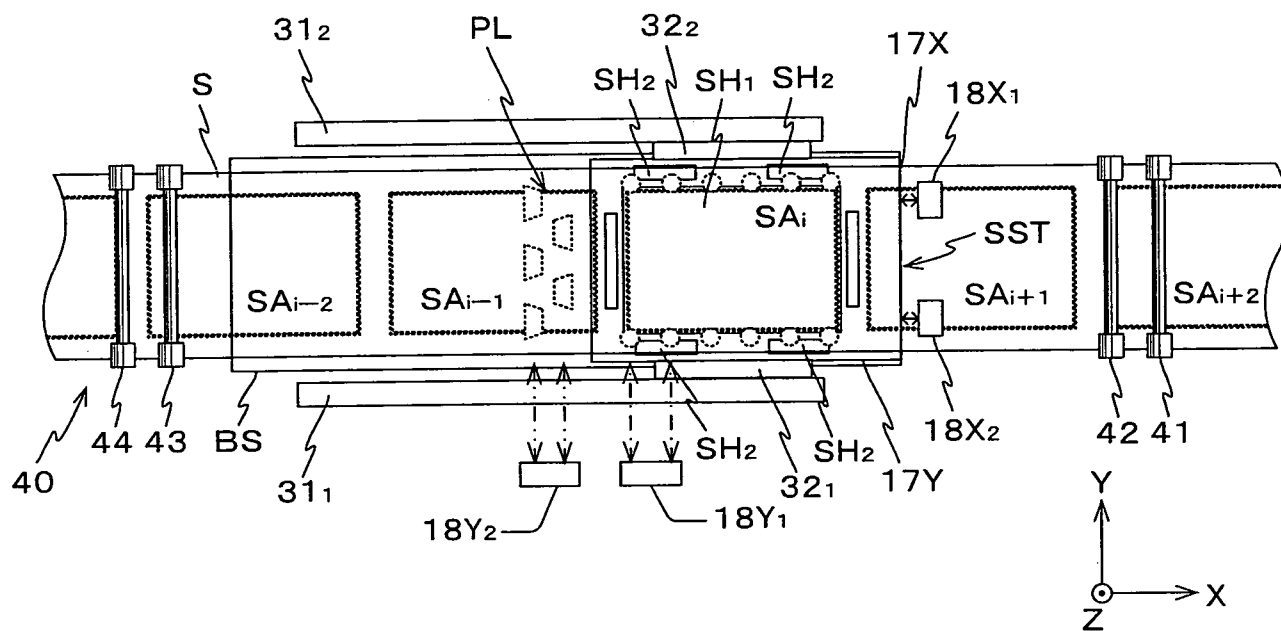


FIG. 11

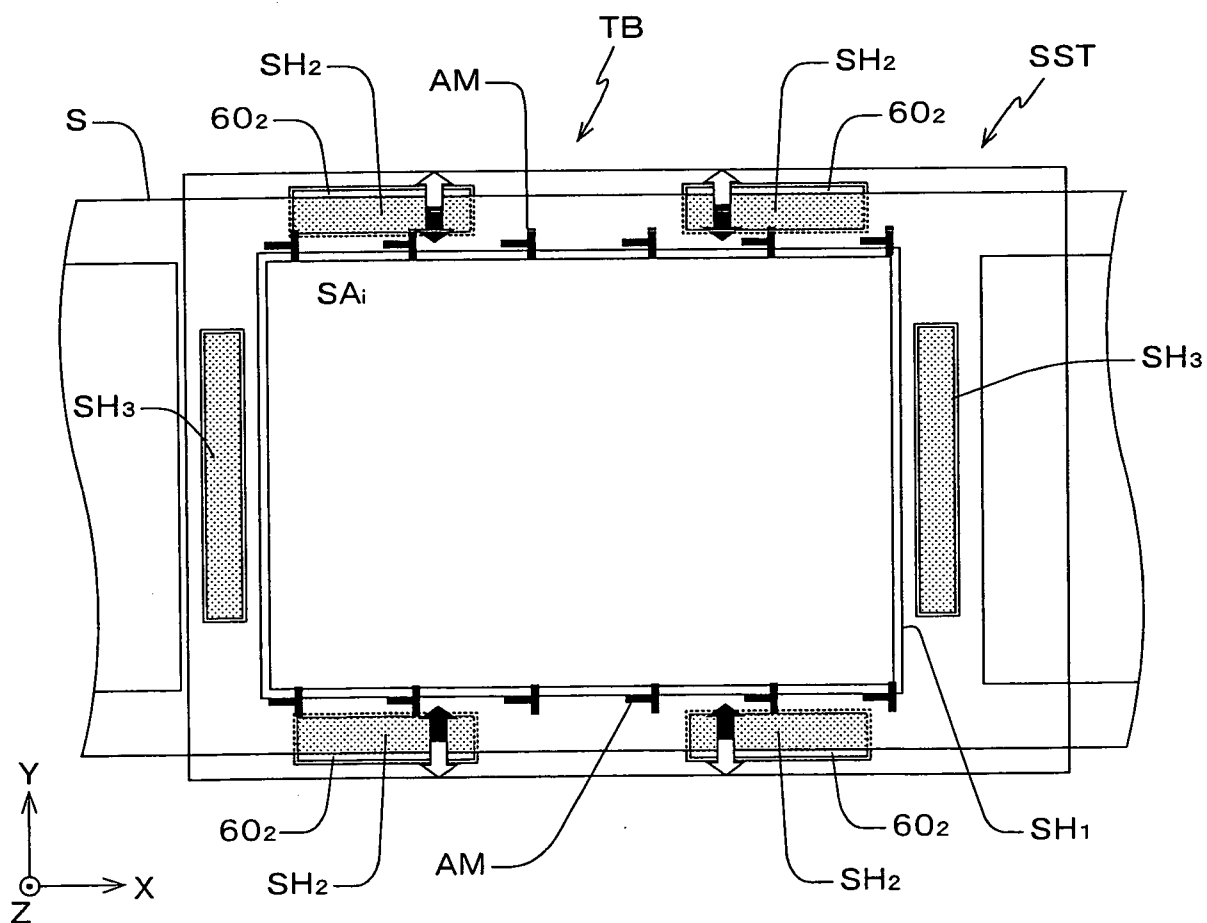
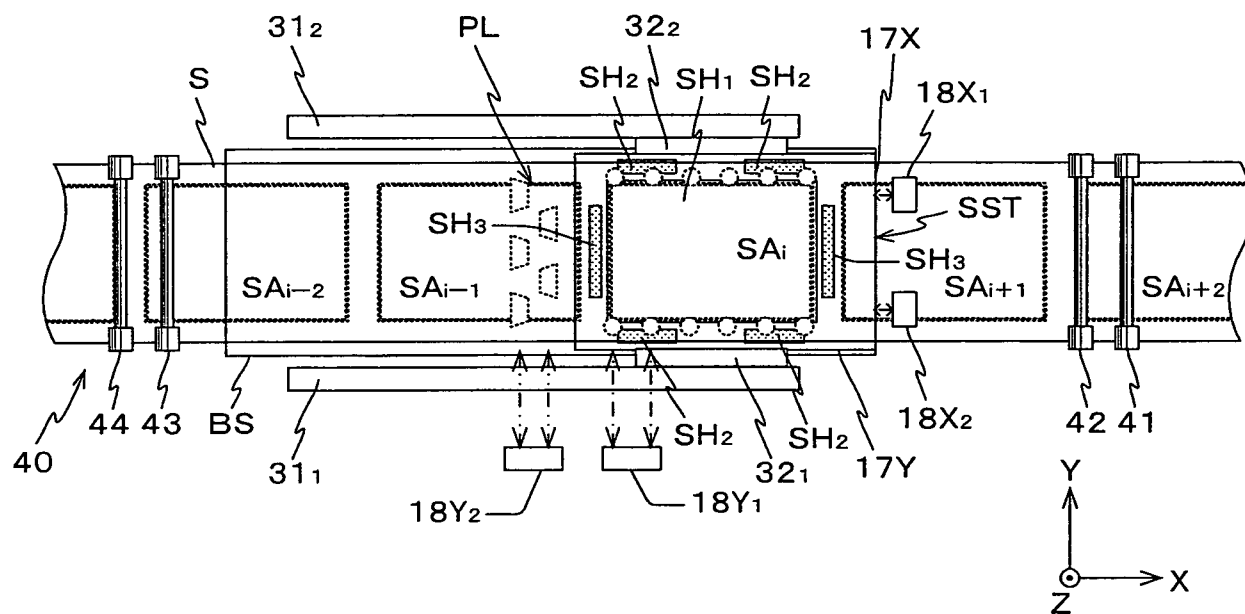


FIG. 12



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FIG. 13

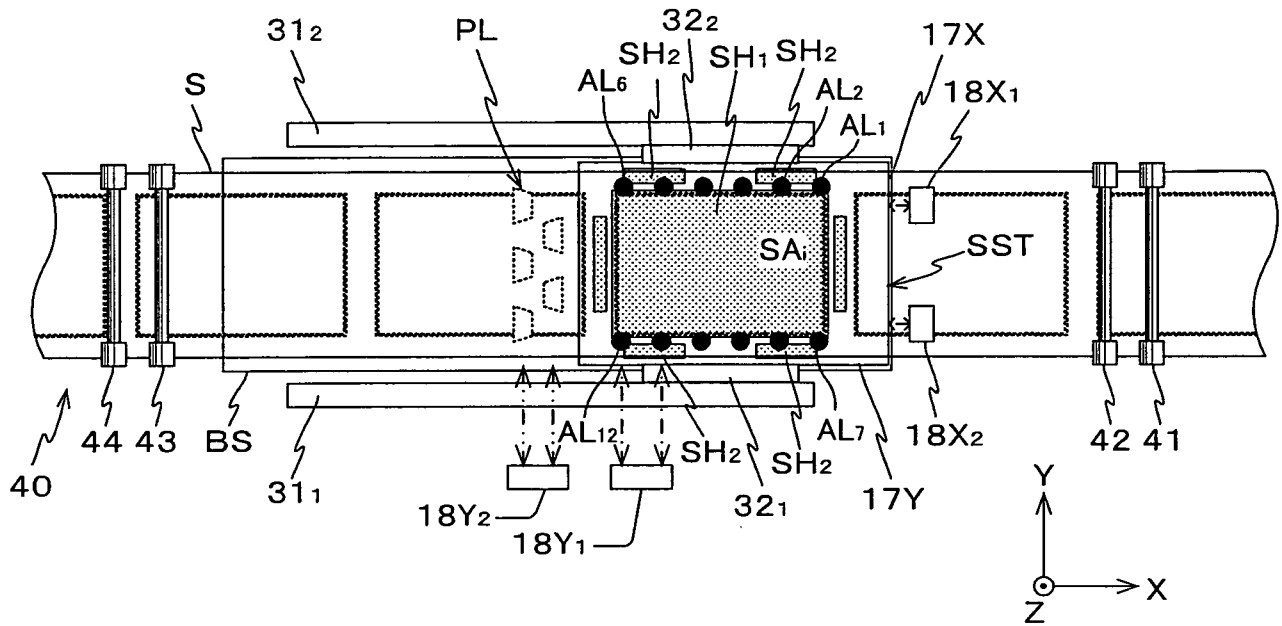
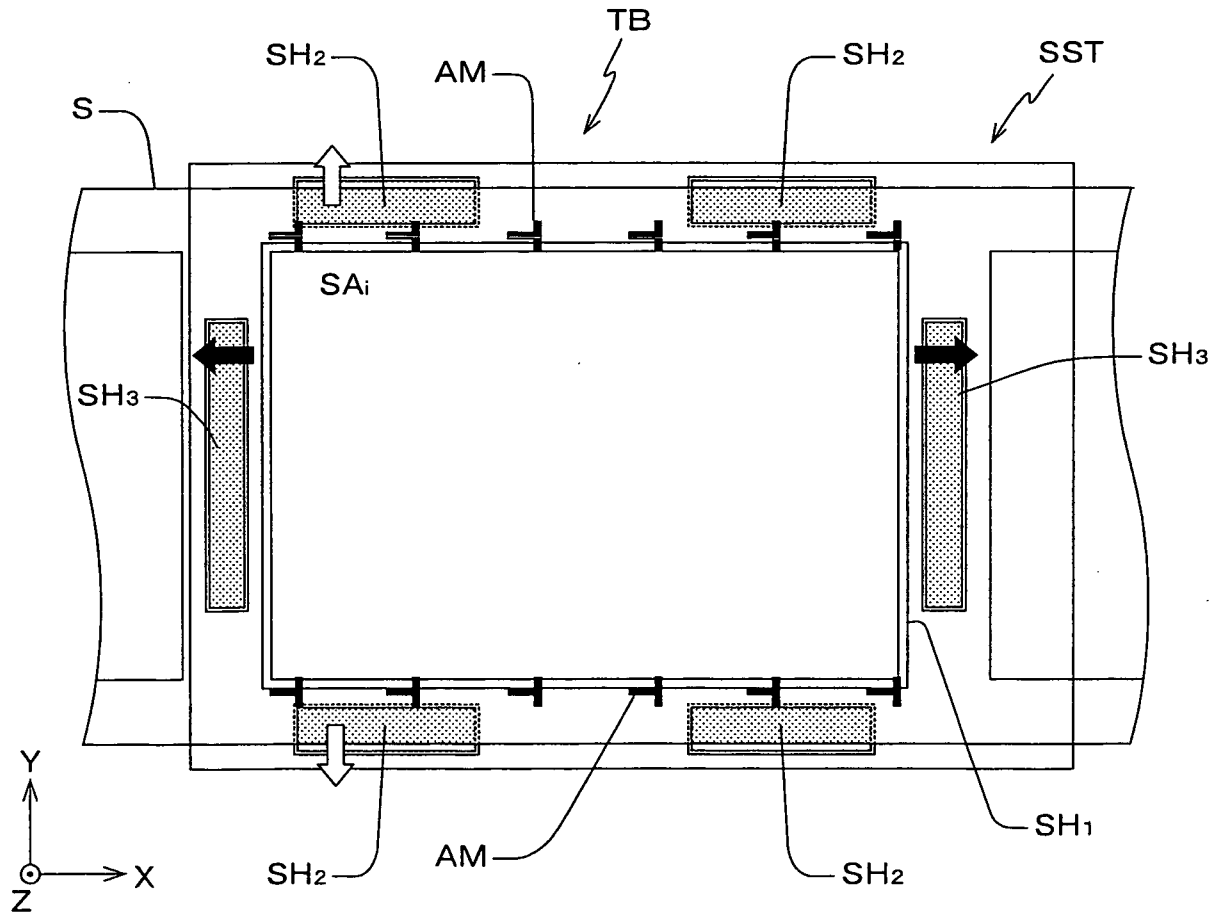
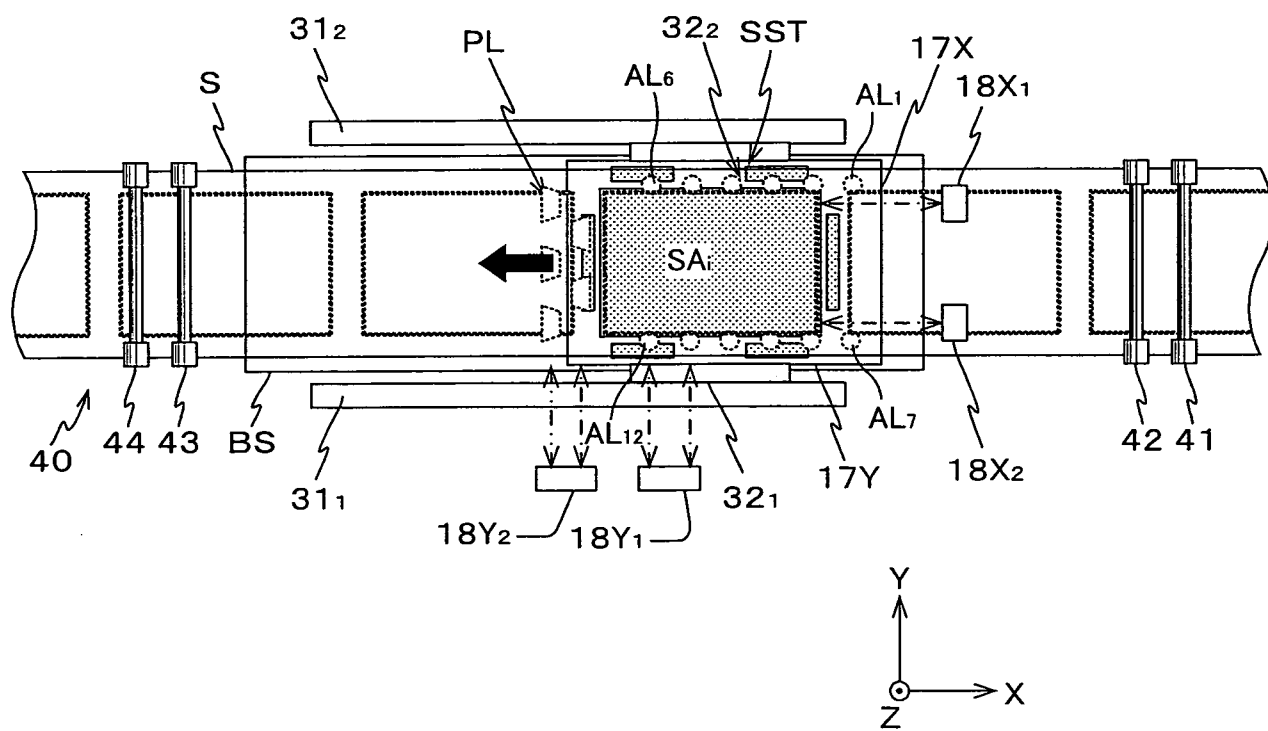


FIG. 14



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FIG. 15



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FIG. 16

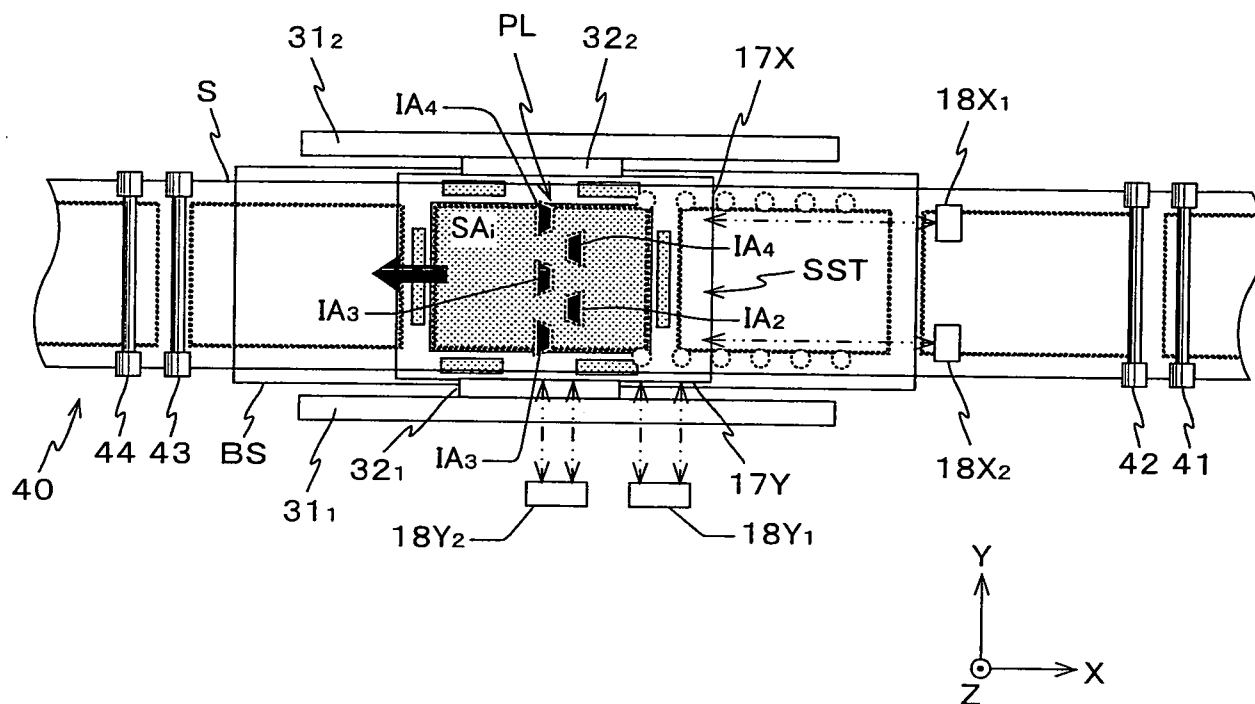


FIG. 17

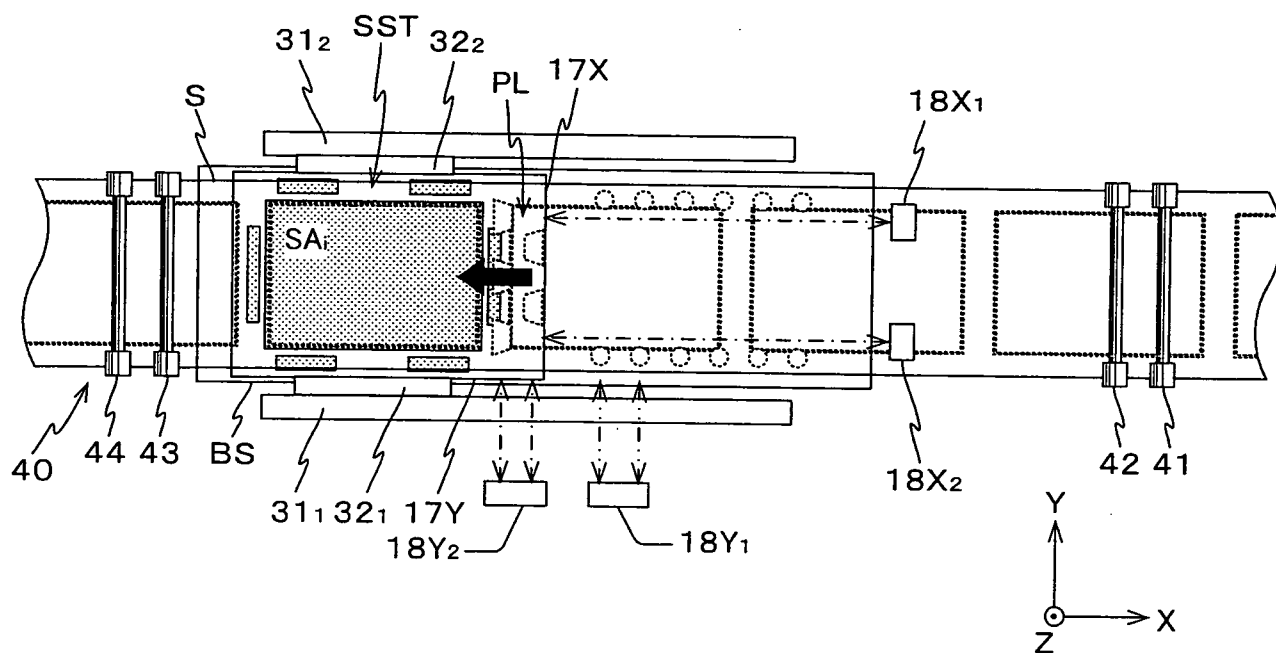


FIG. 18

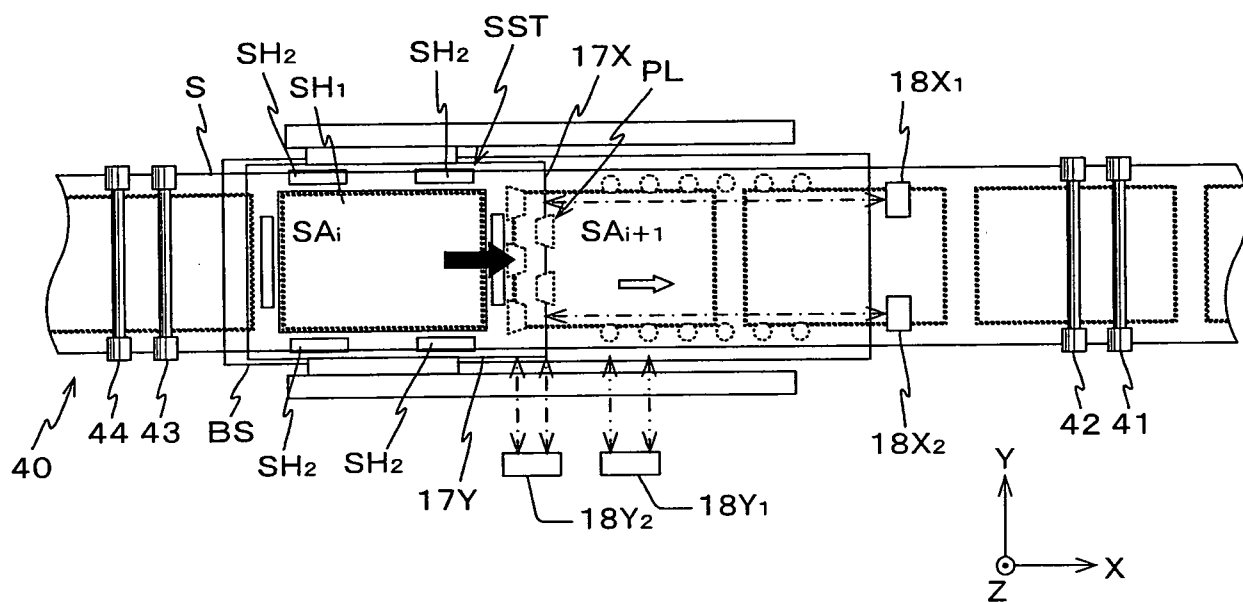


FIG. 19

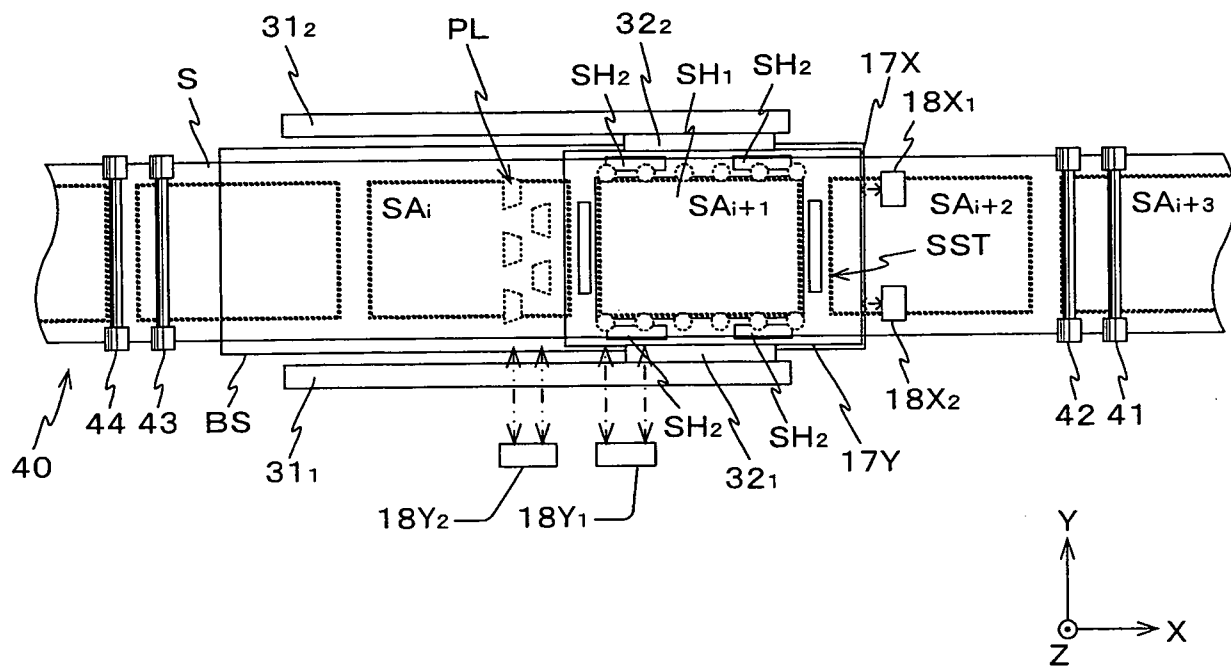


FIG. 20

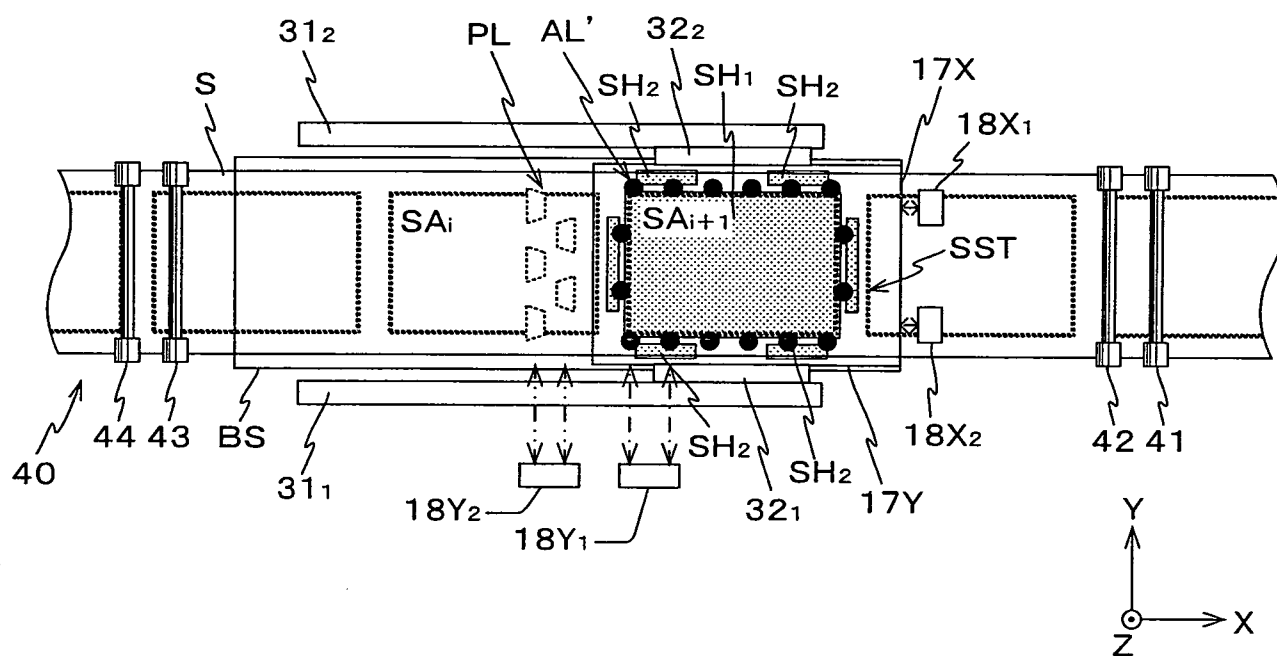
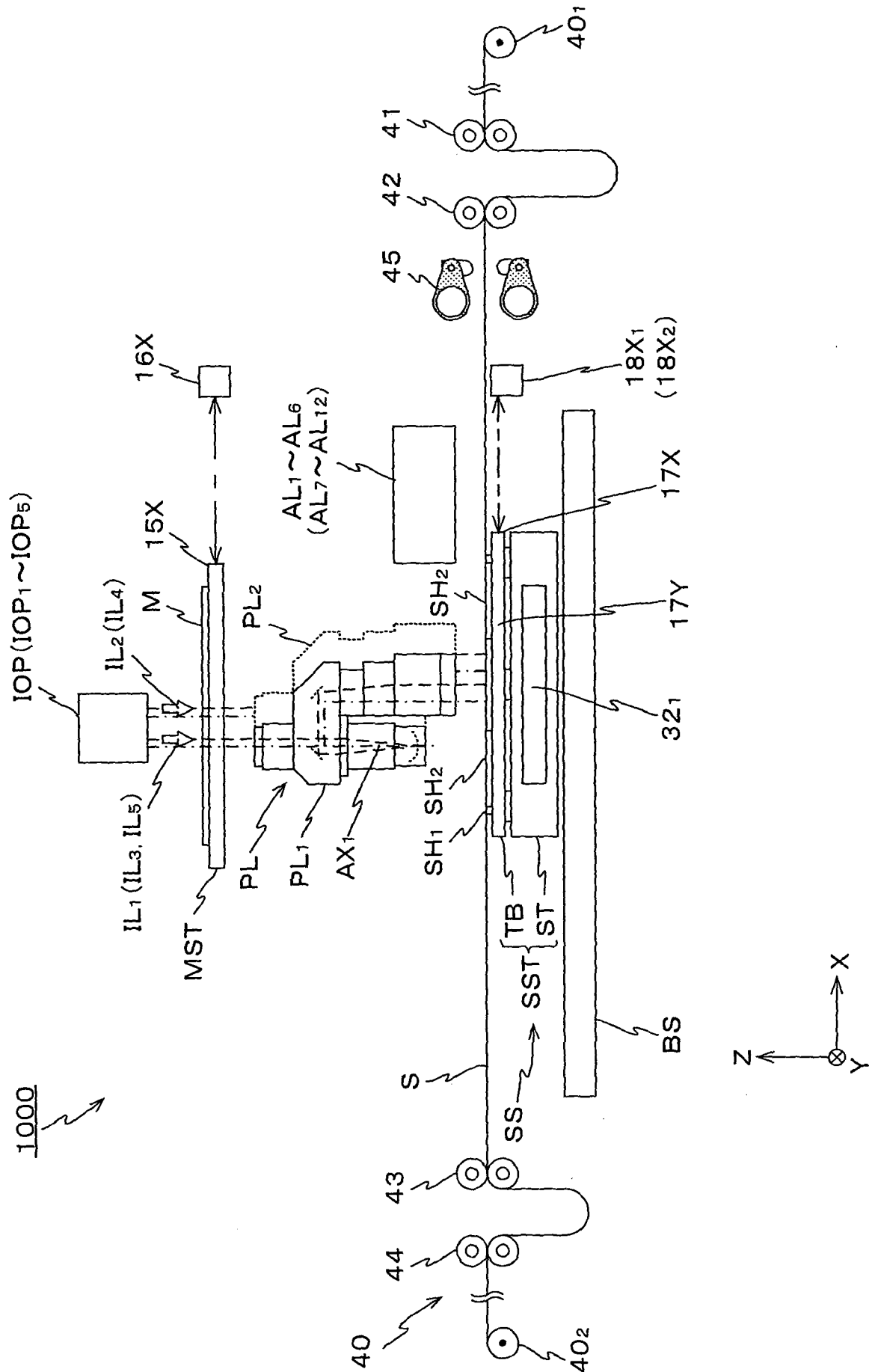


FIG. 21



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FIG. 22

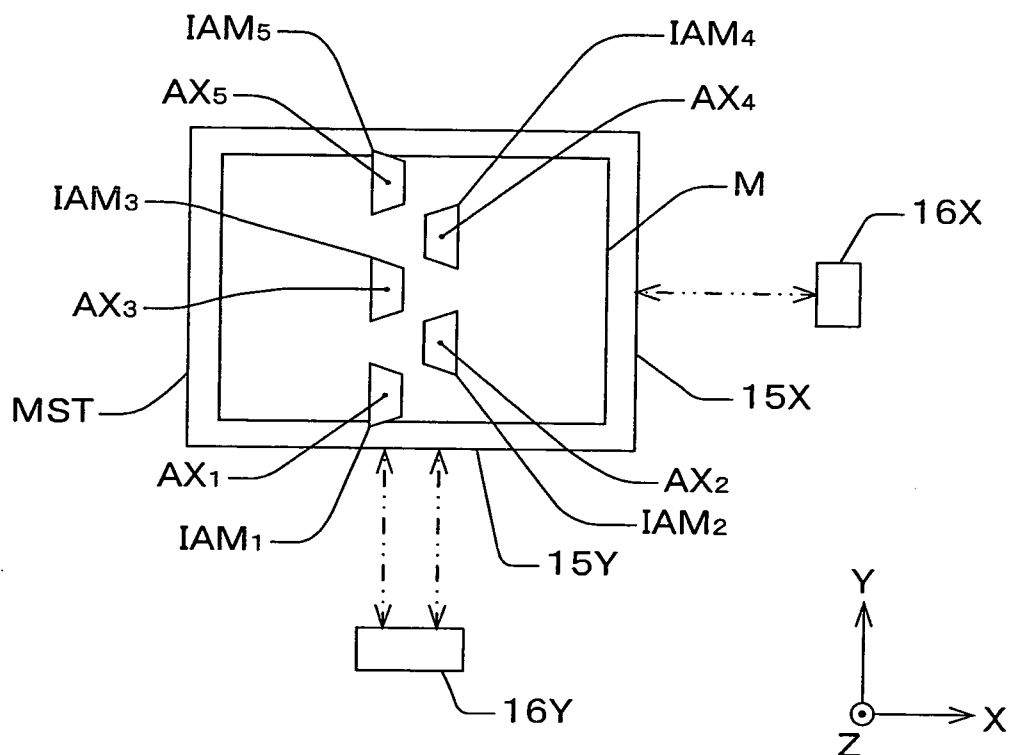
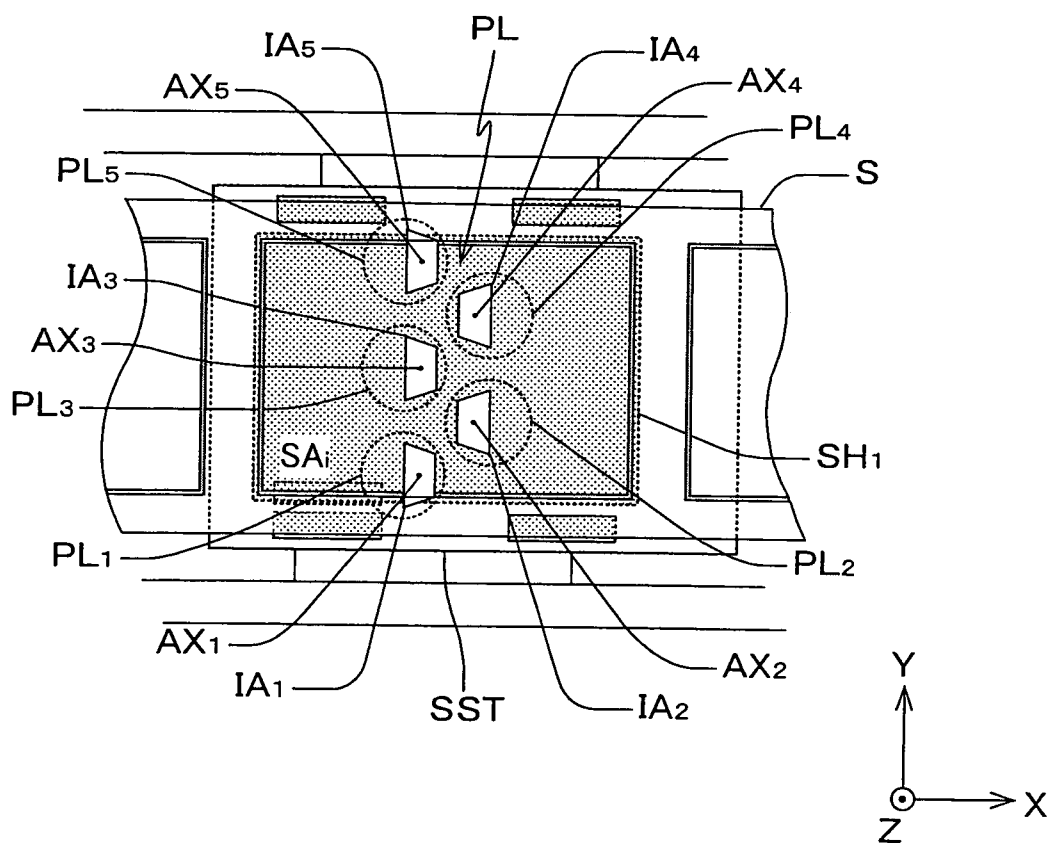


FIG. 23



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FIG. 25A

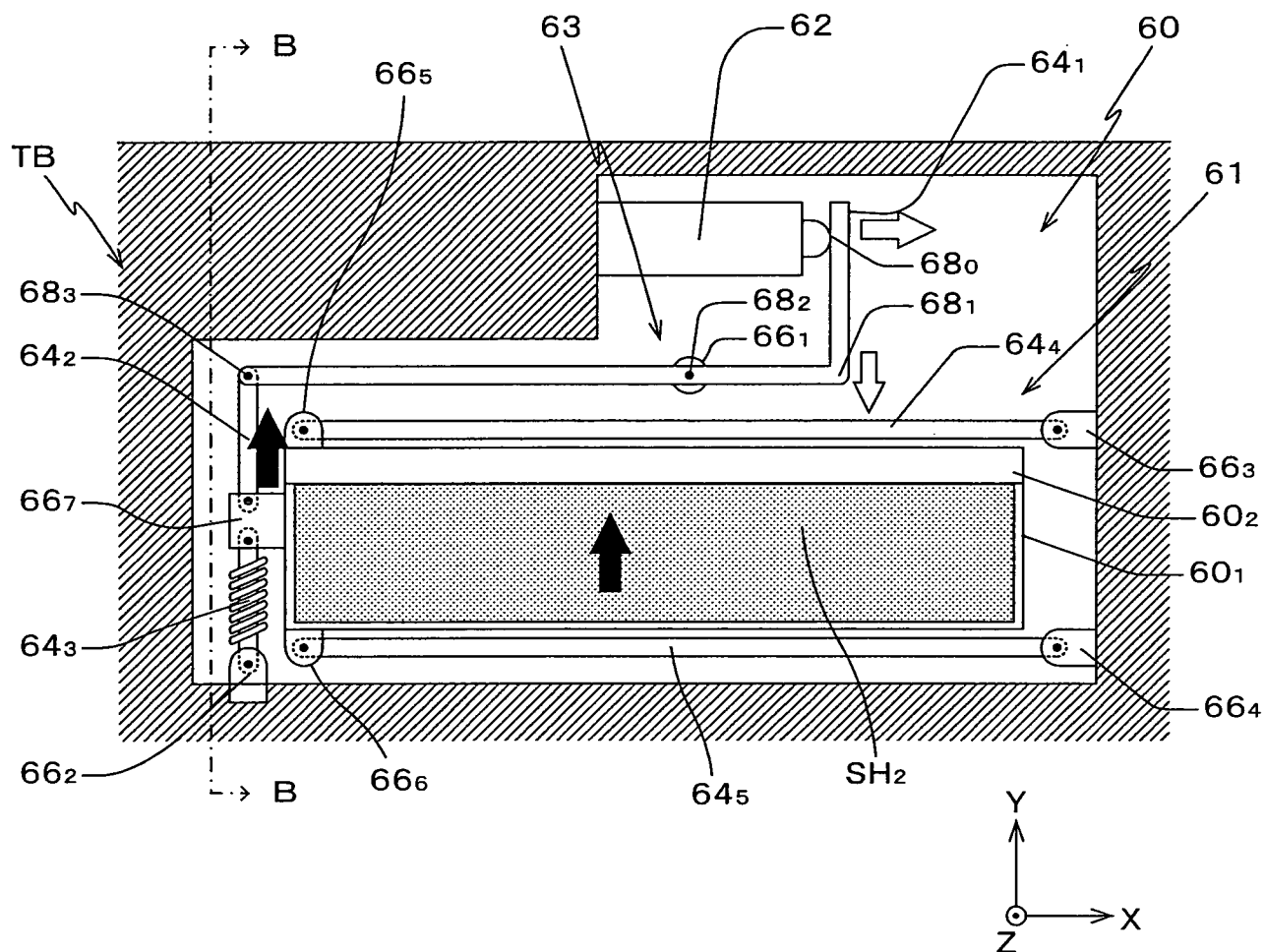


FIG. 25B

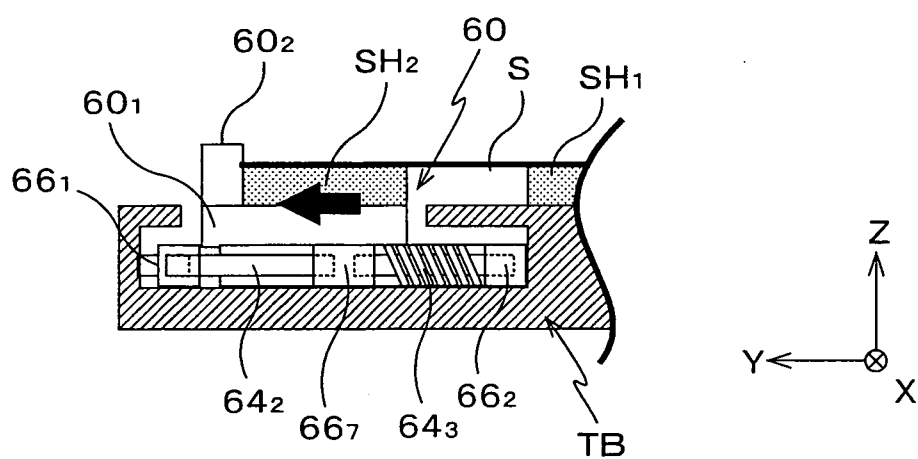


FIG. 26

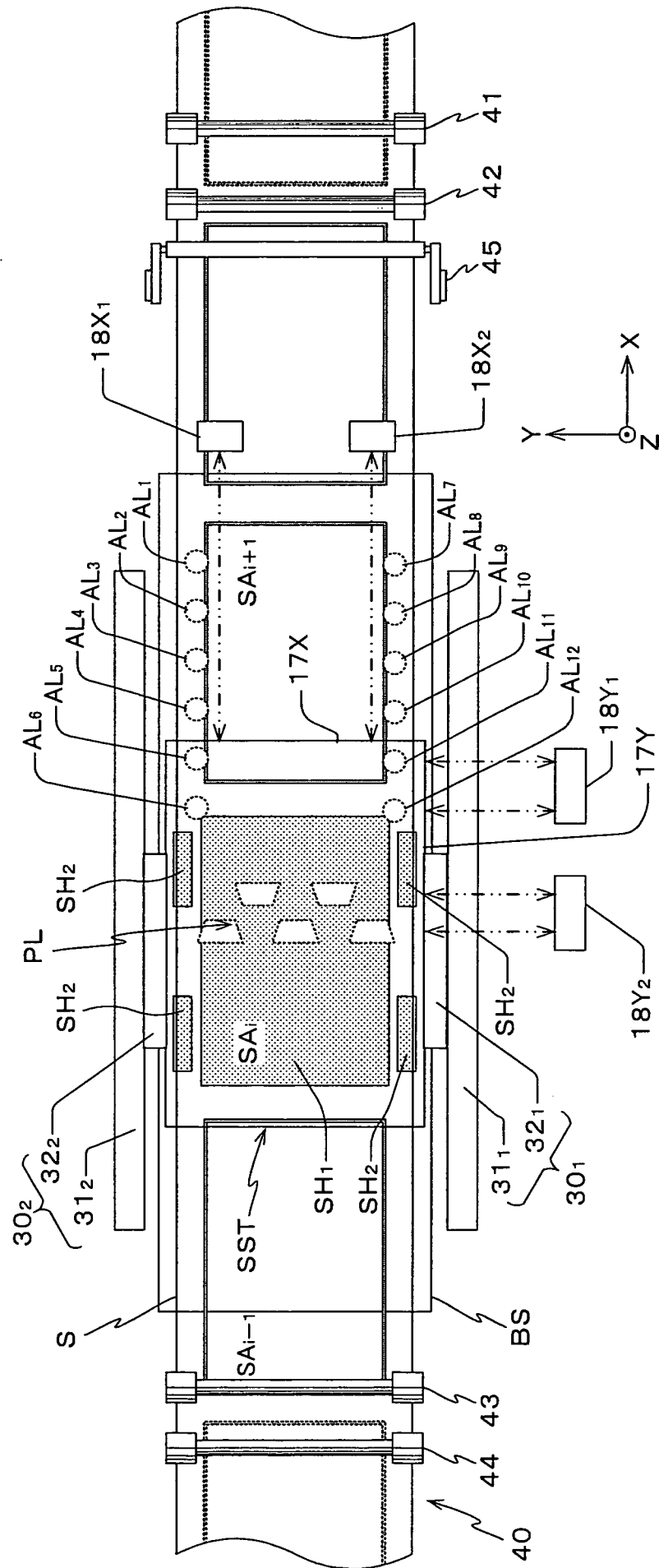


FIG. 27A

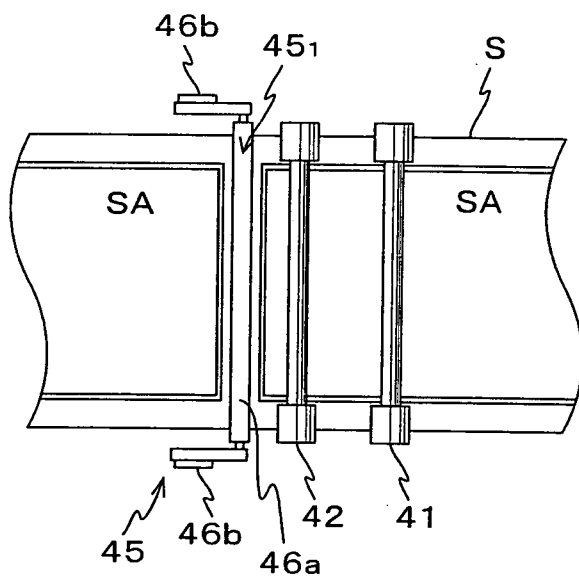


FIG. 27B

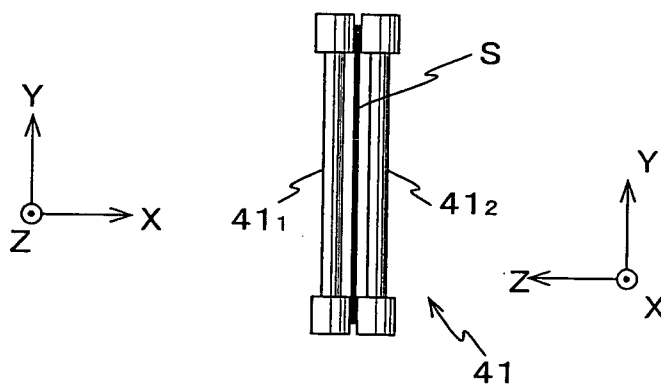


FIG. 27C

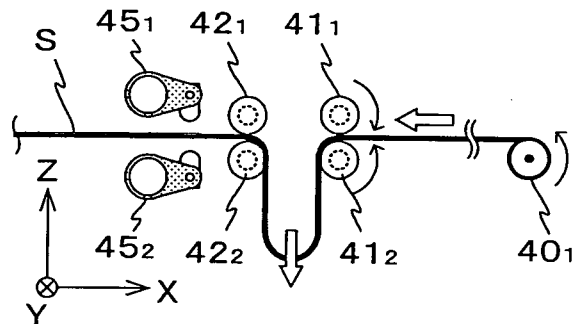


FIG. 27D

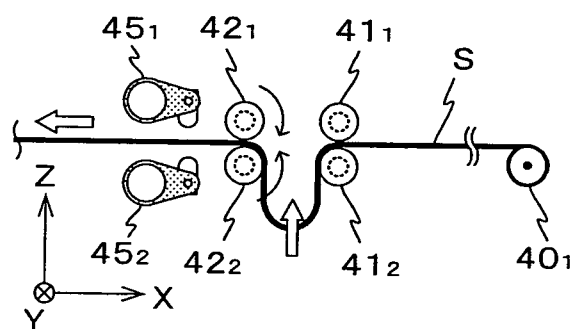


FIG. 27E

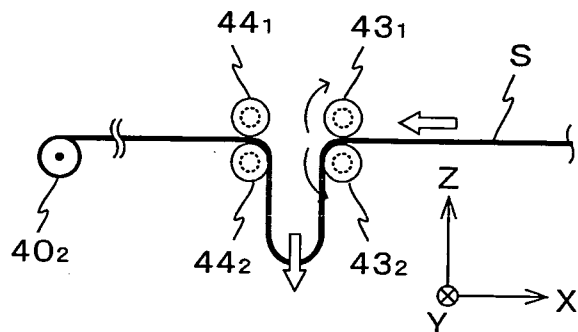


FIG. 27F

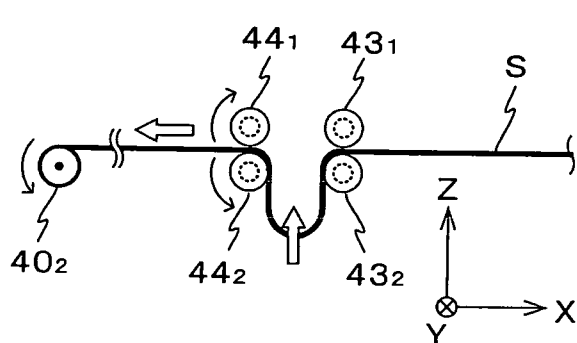
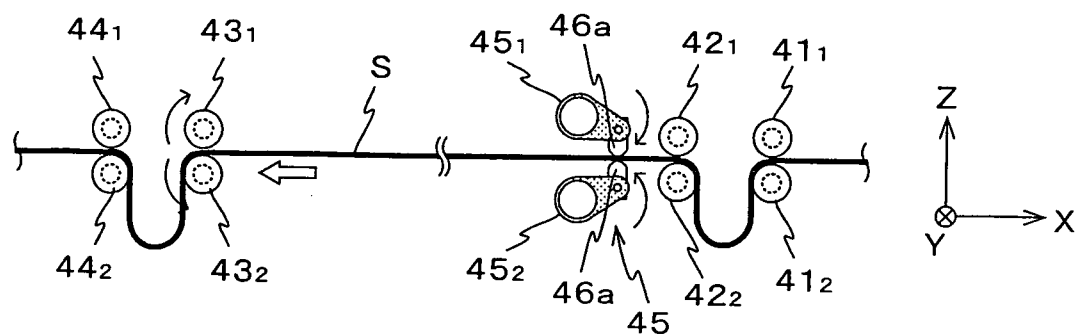
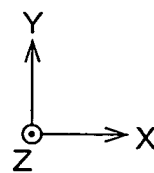
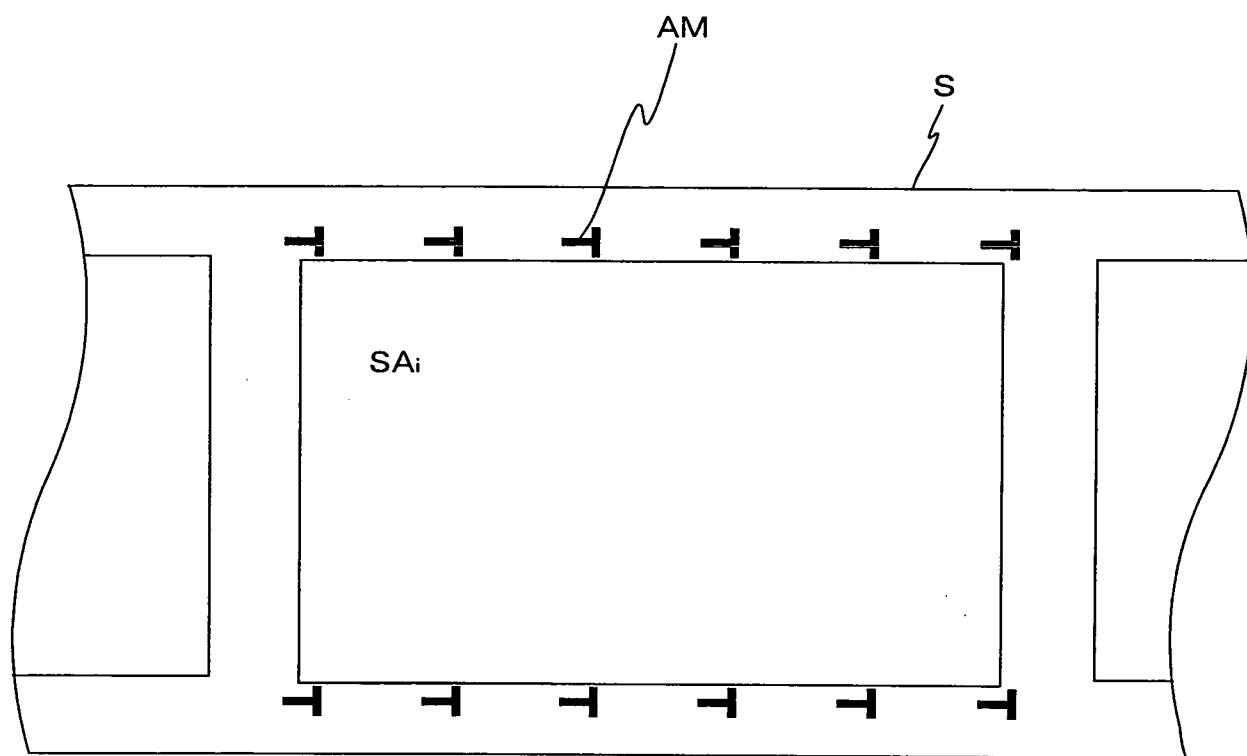


FIG. 27G



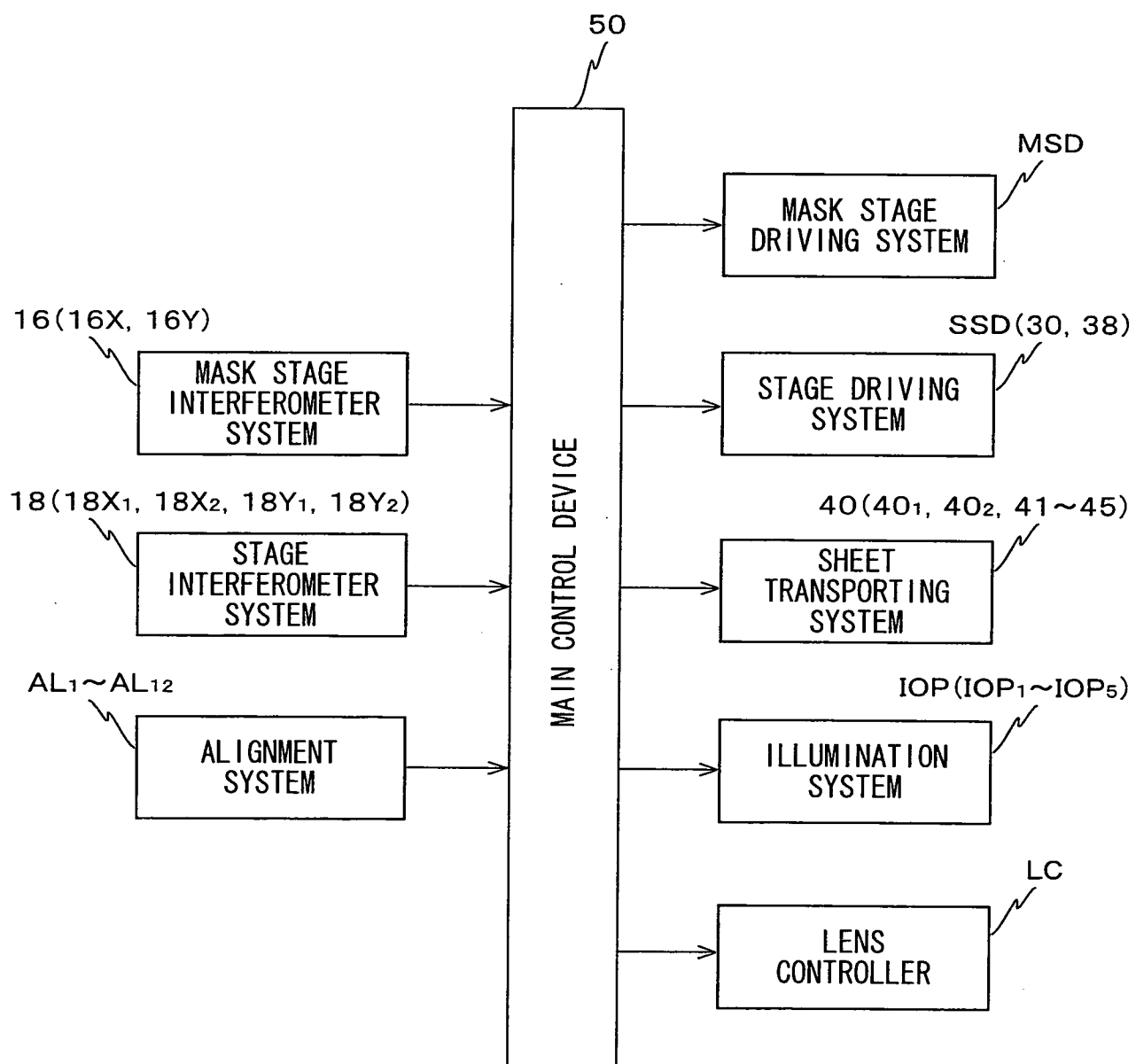
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FIG. 28



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FIG. 29



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FIG. 30

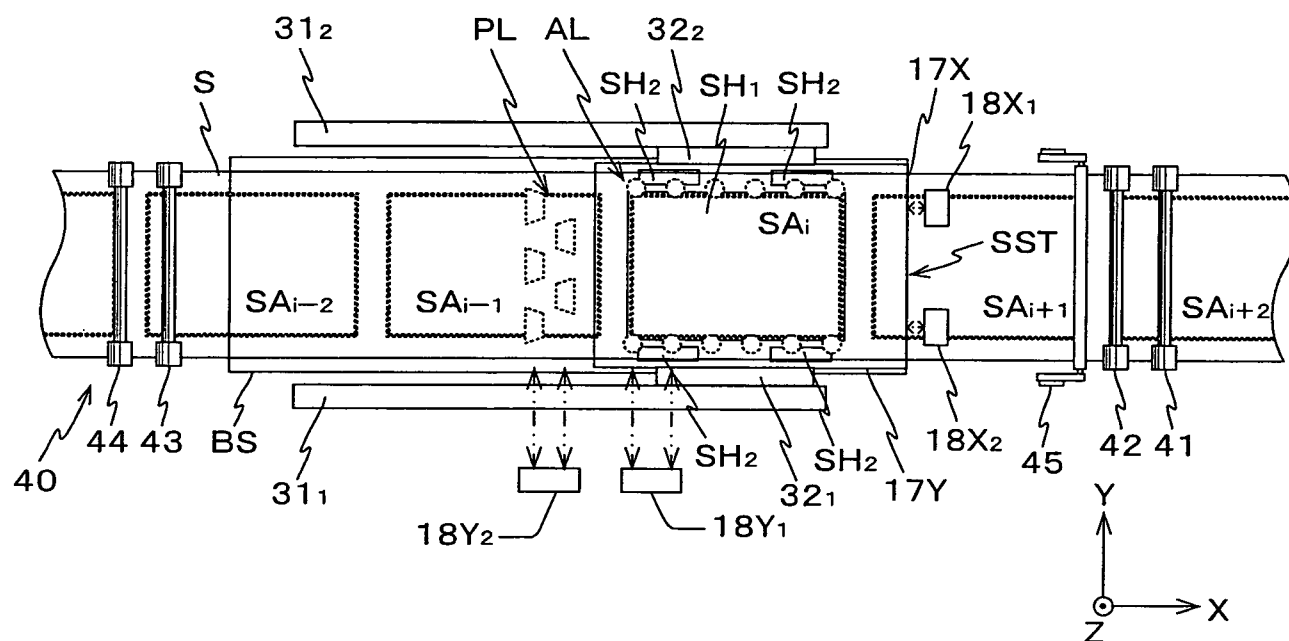


FIG. 31

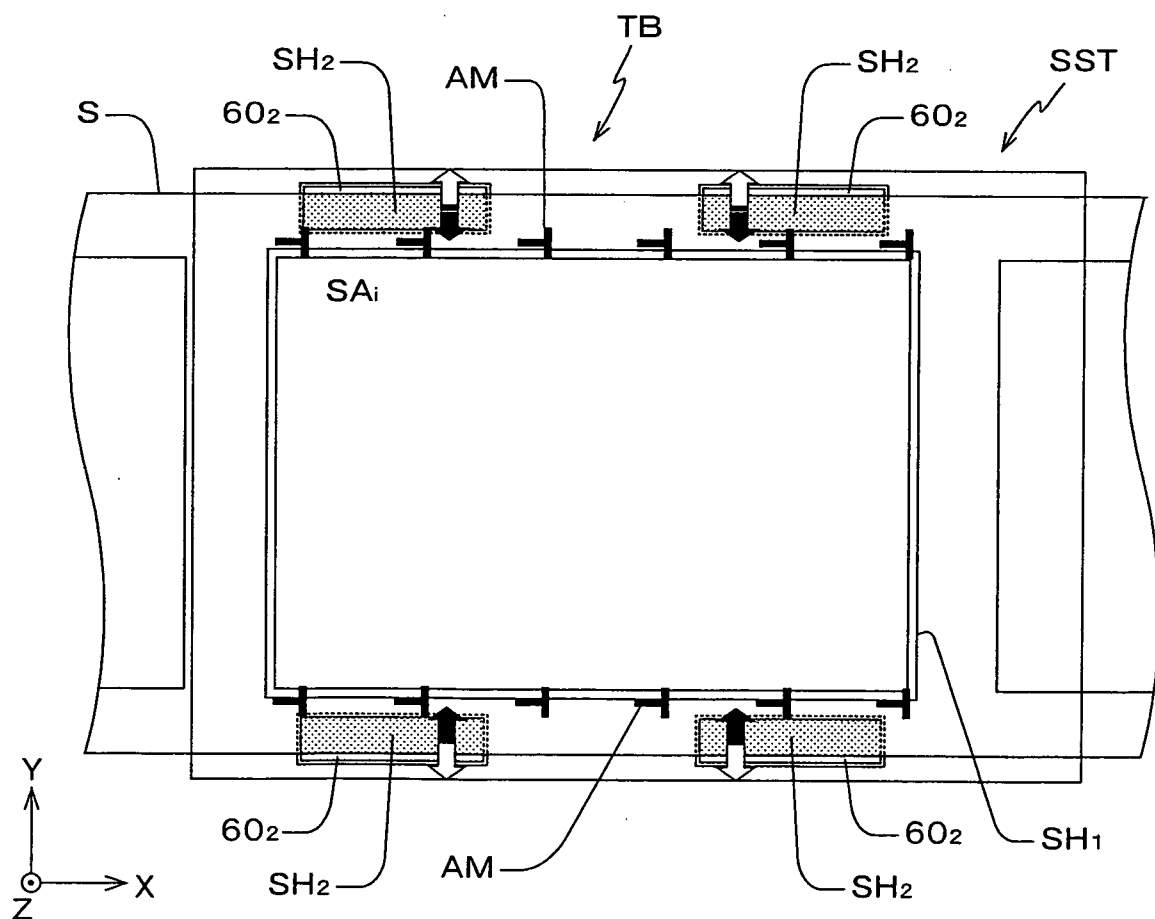
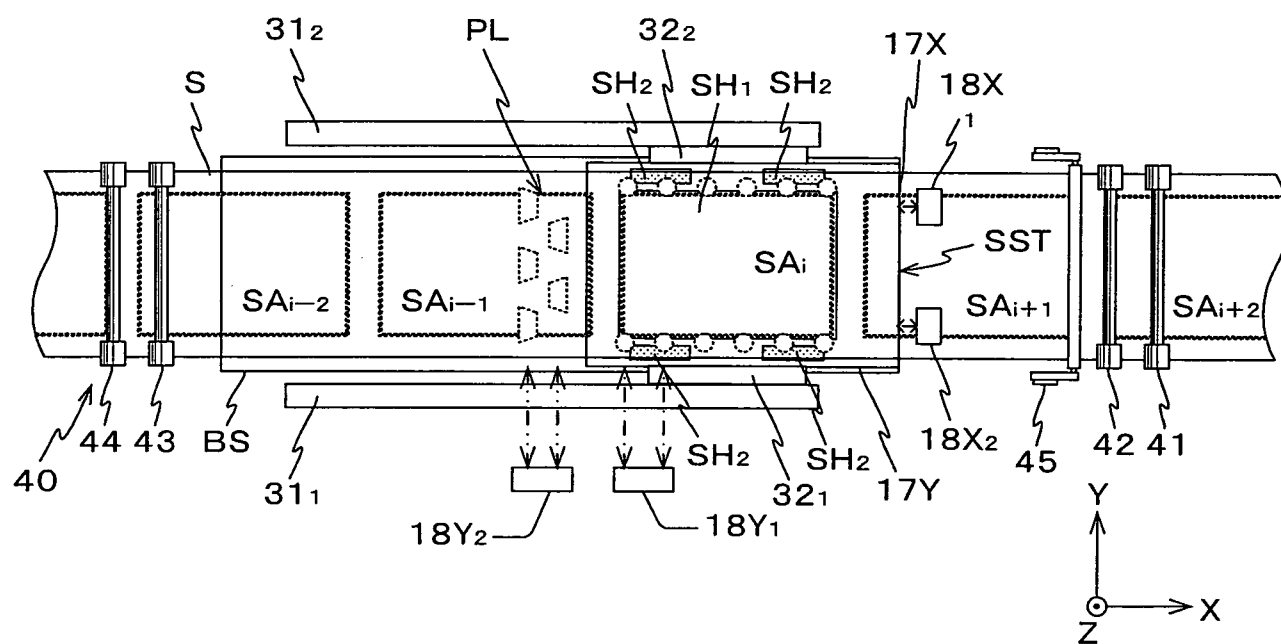


FIG. 32



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FIG. 33

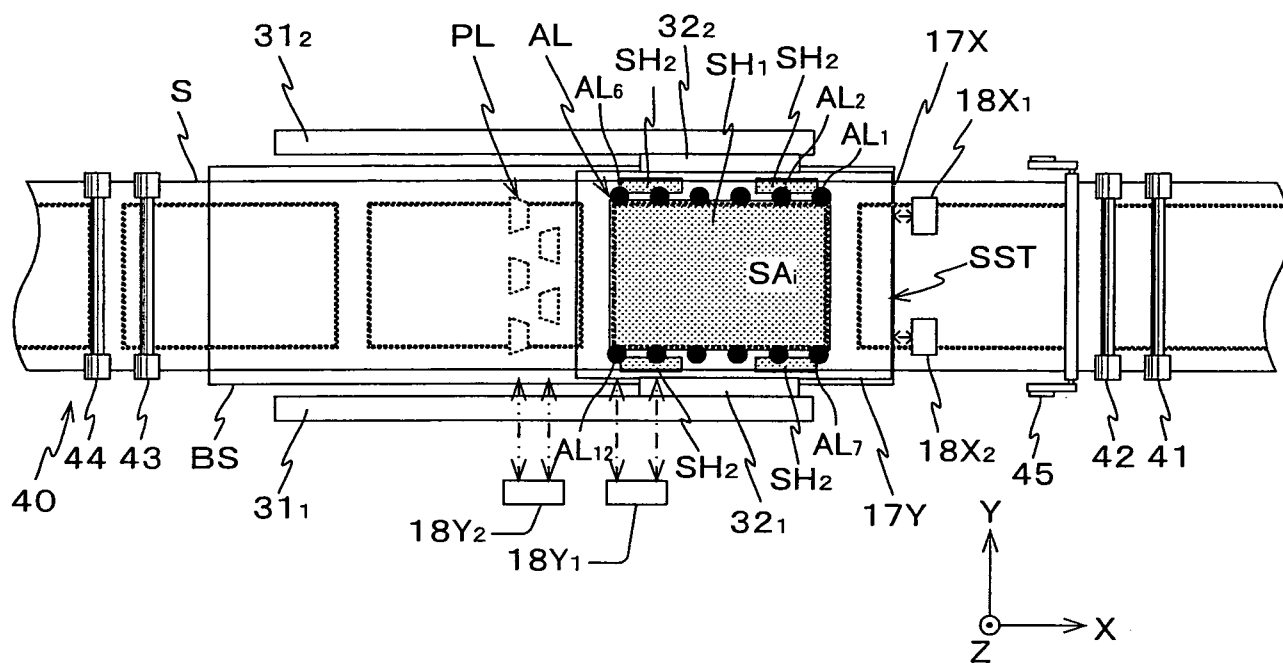
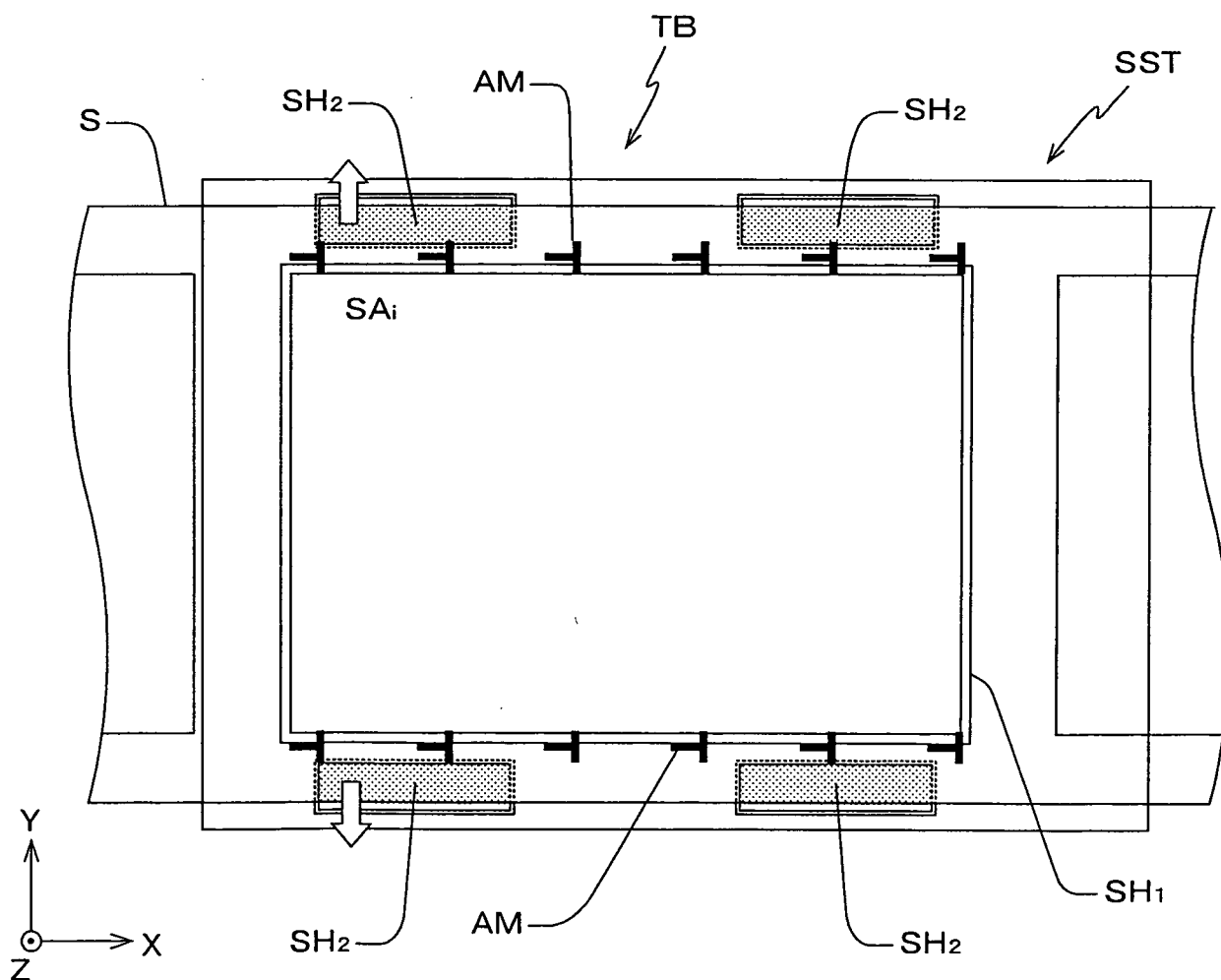


FIG. 34



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FIG. 35

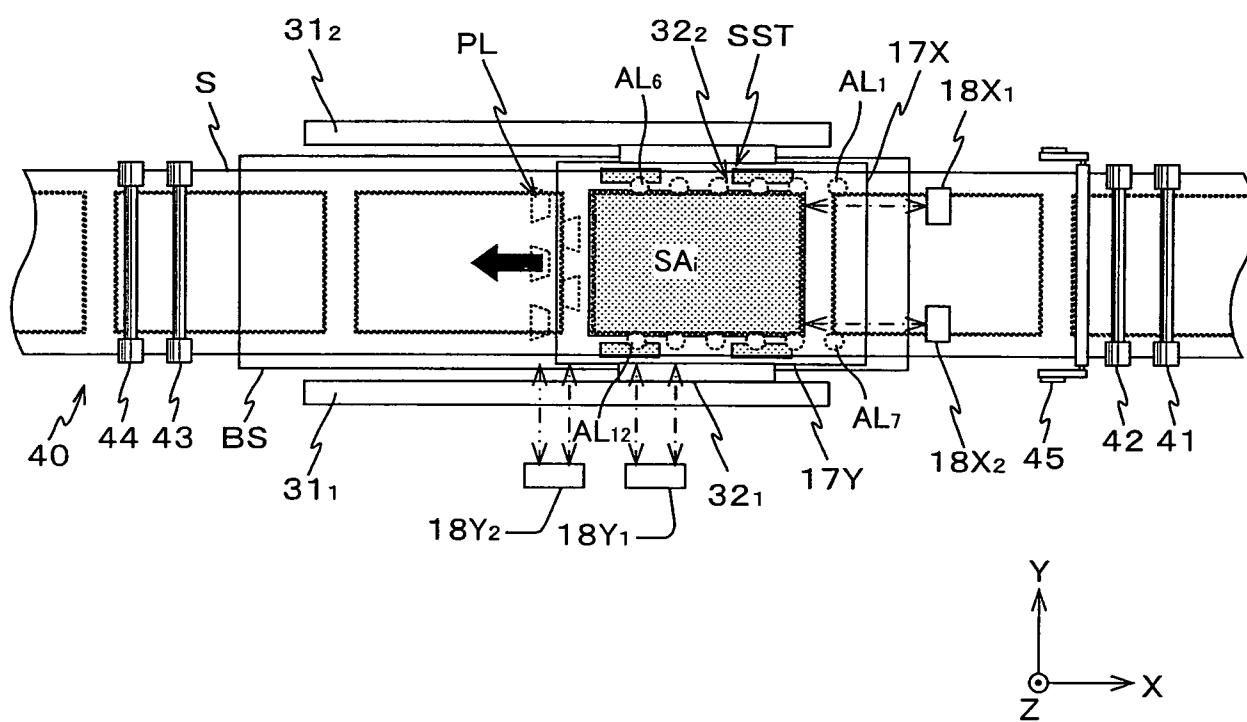


FIG. 36

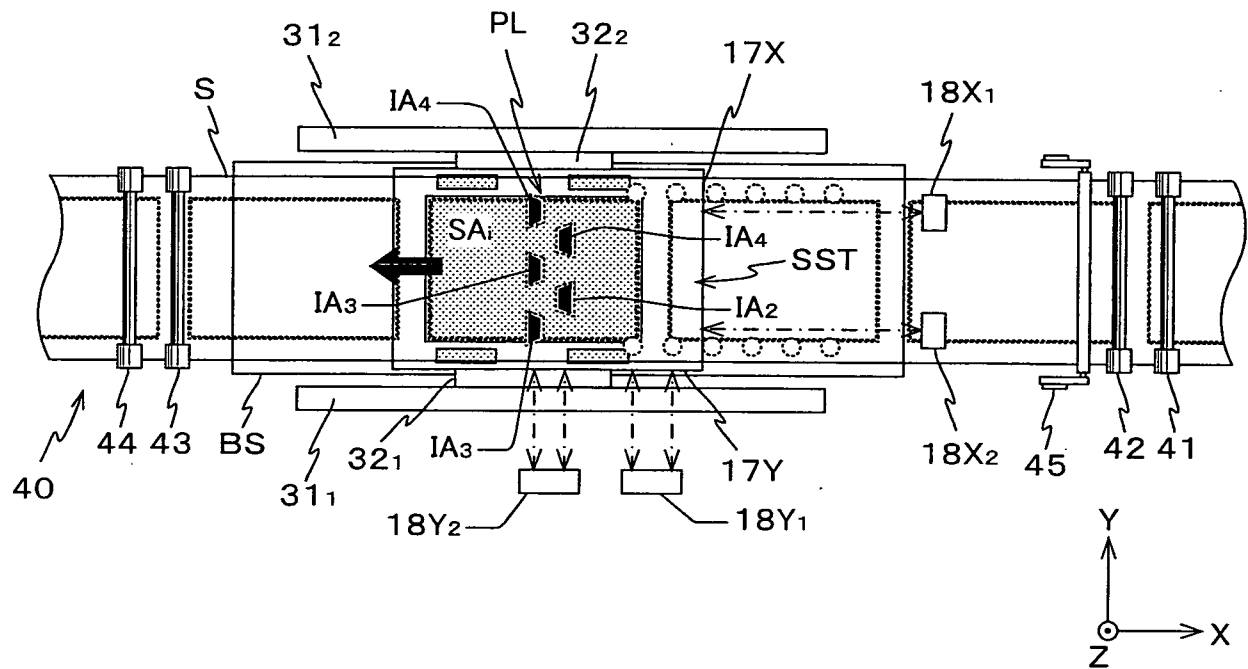
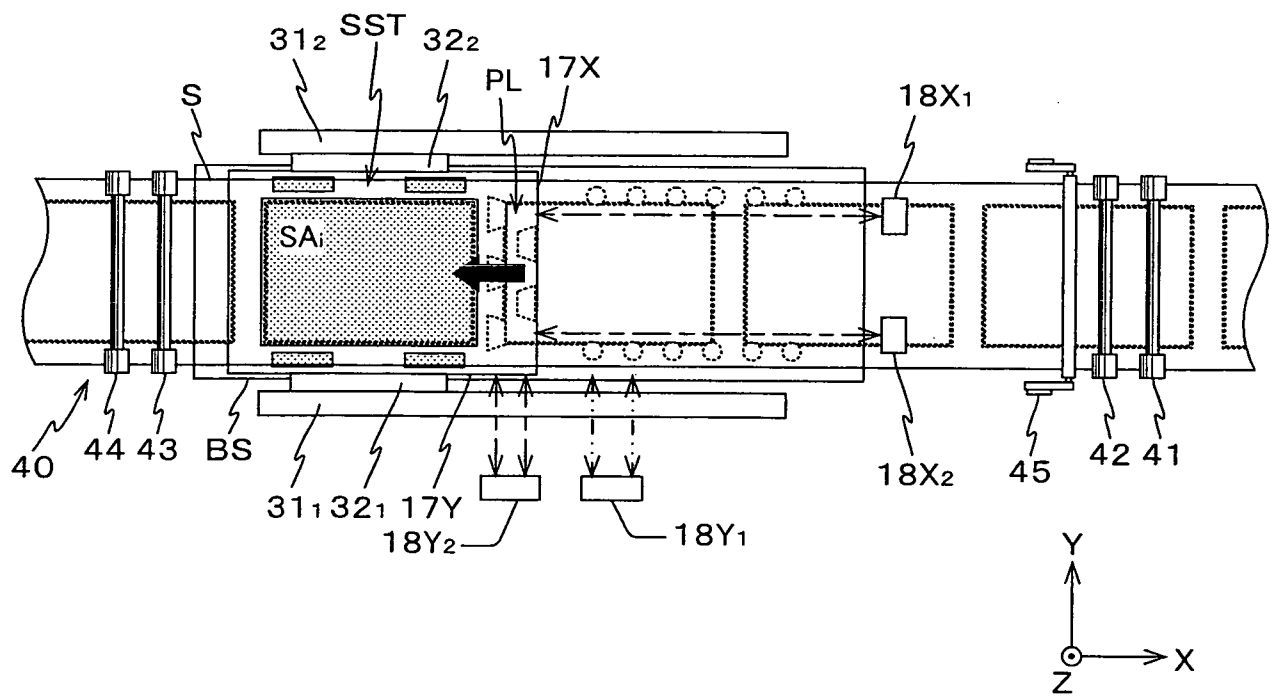


FIG. 37



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FIG. 38

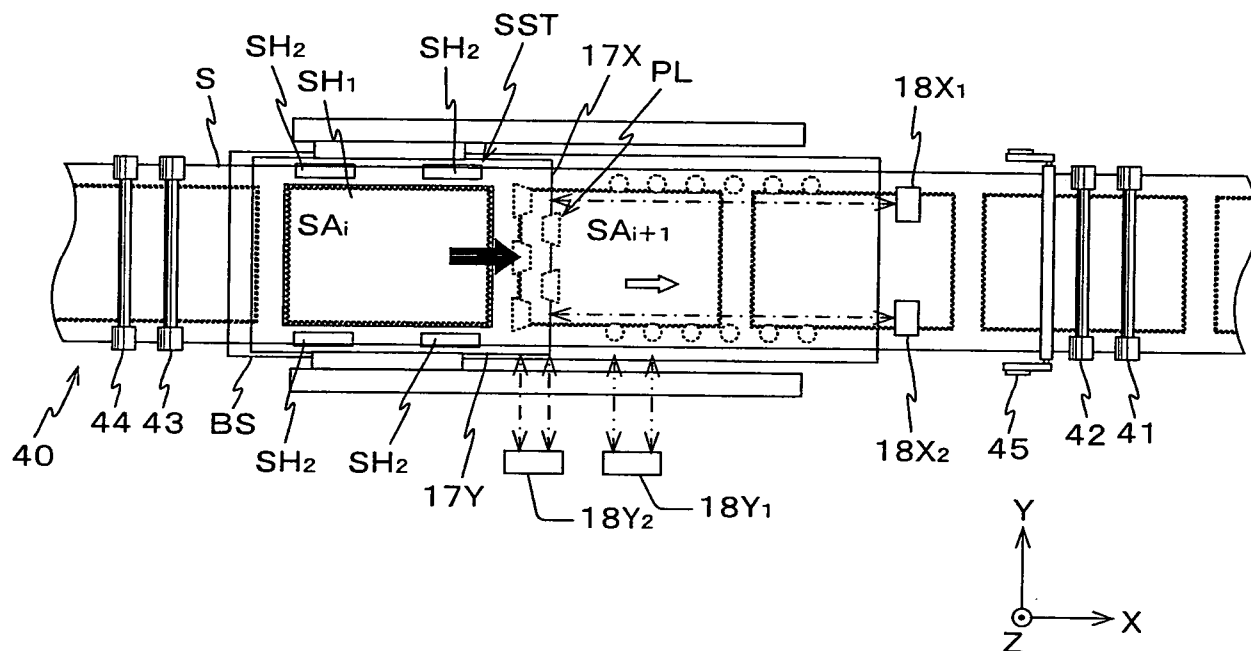


FIG. 39

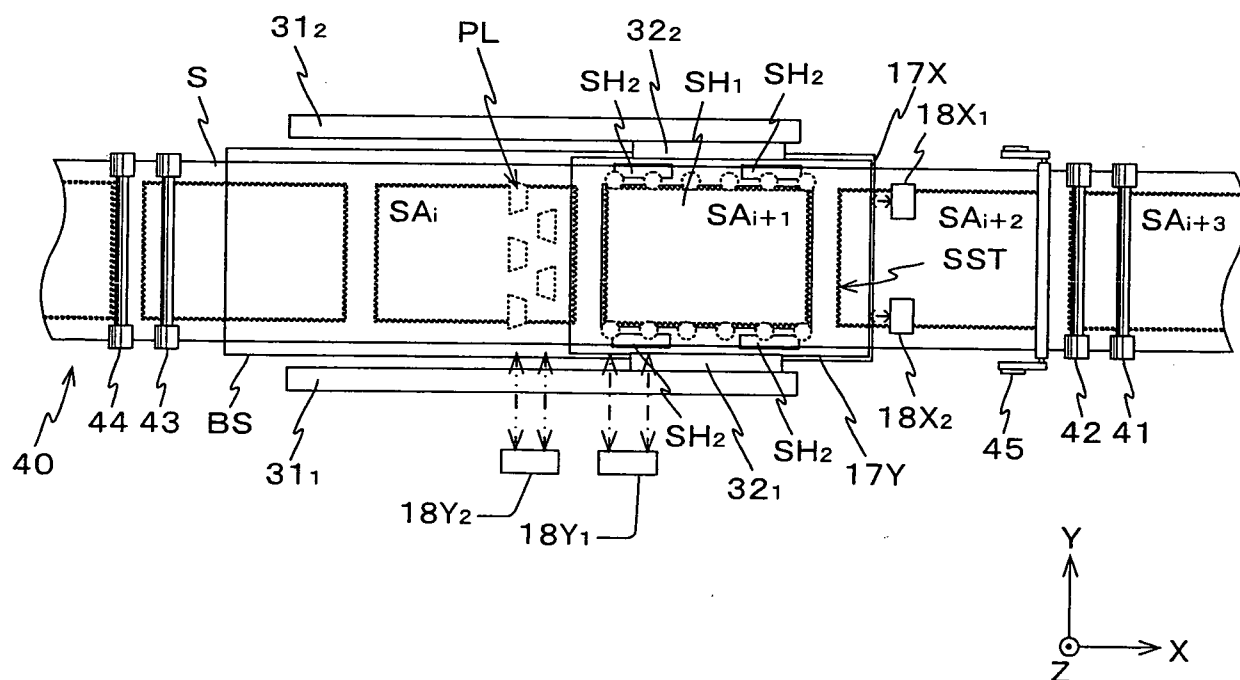
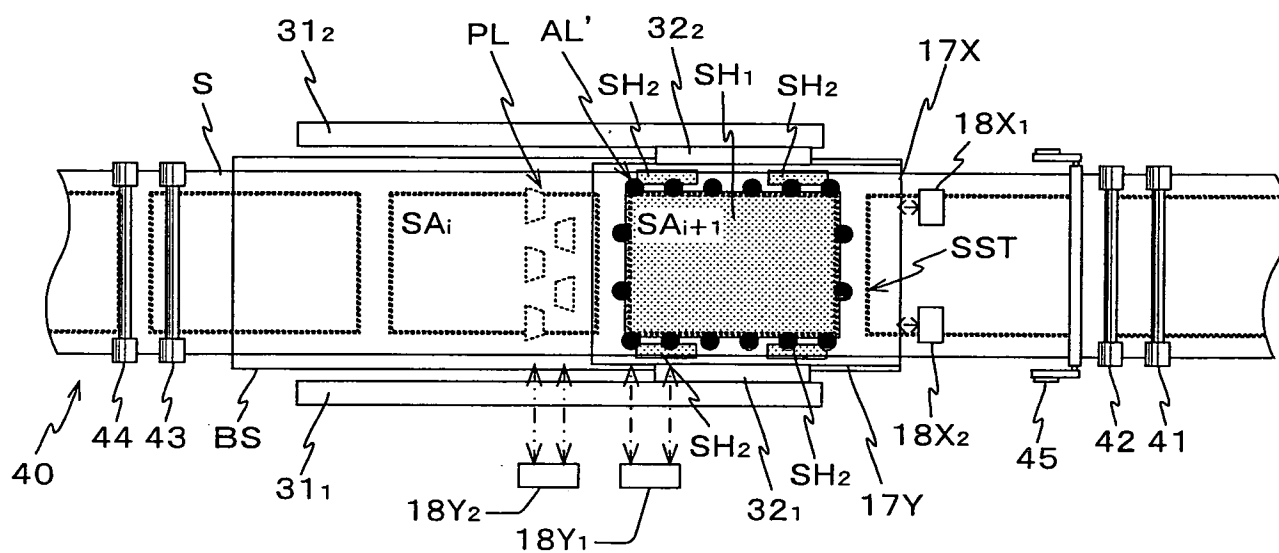


FIG. 40



INTERNATIONAL SEARCH REPORT

International application No

PCT/JP2010/062483

A. CLASSIFICATION OF SUBJECT MATTER

INV. G03F7/20 G03F9/00
ADD.

According to International Patent Classification (IPC) or to both national classification and IPC

B. FIELDS SEARCHED

Minimum documentation searched (classification system followed by classification symbols)

G03F B41J H05K

Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched

Electronic data base consulted during the international search (name of data base and, where practical, search terms used)

EPO-Internal

C. DOCUMENTS CONSIDERED TO BE RELEVANT

Category*	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
X	JP 2004 347964 A (USHIO ELECTRIC INC) 9 December 2004 (2004-12-09) paragraphs [0003], [0009], [0010], [0013] - [0023], [0028]; figures 1-6 -----	1-36
A	US 2005/087578 A1 (HEWLETT PACKARD DEVELOPMENT CO [US]) 28 April 2005 (2005-04-28) the whole document -----	1,11-13, 16,17, 19,23, 24,26, 34,35
A	JP 9 070731 A (USHIO ELECTRIC INC) 18 March 1997 (1997-03-18) the whole document -----	1,26

☐ Further documents are listed in the continuation of Box C.

☒ See patent family annex.

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"P" document published prior to the international filing date but later than the priority date claimed

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Date of the actual completion of the international search

5 October 2010

Date of mailing of the international search report

25/10/2010

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Authorized officer

Roesch, Guillaume

INTERNATIONAL SEARCH REPORT

Information on patent family members

International application No

PCT/JP2010/062483

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